



國家同步輻射研究中心

National Synchrotron Radiation Research Center

*Angle-resolved photoemission spectroscopy
(ARPES) for 2D layered structure : graphene and
topological insulators*

Cheng-Maw Cheng (鄭澄懋)

makalu@nsrrc.org.tw

NTHU, 2013/05/09

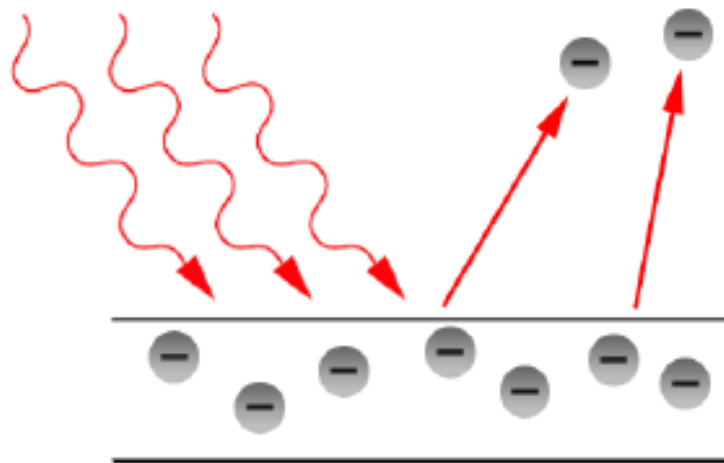
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Outline

- Introduction to angle-resolved photoemission spectroscopy (ARPES)
 - The principle of ARPES
 - Synchrotron light source
 - Current status of ARPES beamline at NSRRC
 - Scientific cases
- The electronic structure of 2D layered structure
 - Surface states and quantum well states
 - Graphene (BLG)
 - Topological insulators (Tis)
- Summary



What is photoemission?



Photon in $\rightarrow$ electron out (emission)



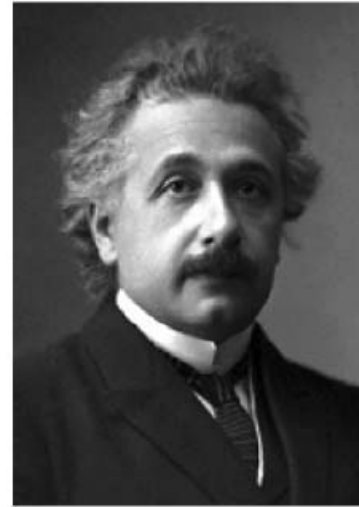
X-ray¹ Photoelectron spectroscopy, based on the photoelectric effect,^{2,3} was developed in the mid-1960's as a practical technique by Kai Siegbahn and his research group at the University of Uppsala, Sweden.⁴



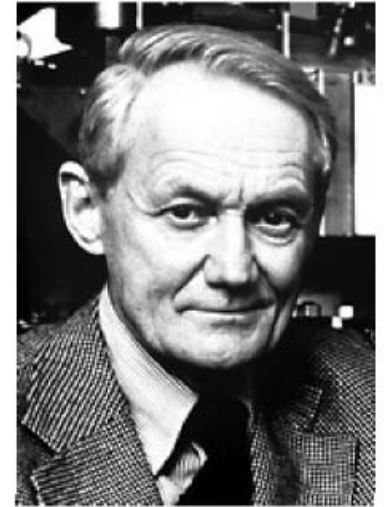
Wilhelm Conrad Röntgen



Heinrich Rudolf Hertz



Albert Einstein



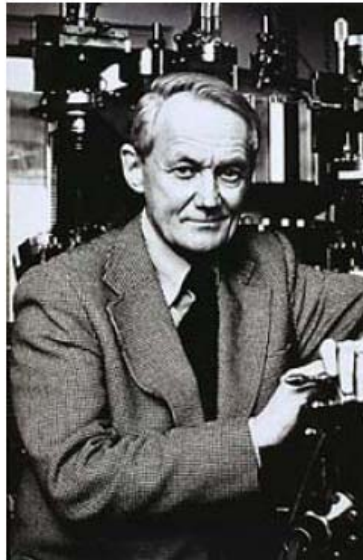
Kai M. Siegbahn



1. W. Röntgen, 1901 Nobel Prize in Physics "in recognition of the extraordinary services he has rendered by the discovery of the remarkable rays subsequently named after him."
2. H. Hertz, *Ann. Physik* **31,983 (1887)**.
3. A. Einstein, *Ann. Physik* **17,132 (1905)**. **1921 Nobel Prize in Physics "for his services to Theoretical Physics, and especially for his discovery of the law of the photoelectric effect."**
4. K. Siegbahn, Et. Al., *Nova Acta Regiae Soc.Sci., Ser. IV, Vol. 20 (1967)*. **1981 Nobel Prize in Physics "for his contribution to the development of high resolution electron spectroscopy."**

Kai Siegbahn: Development of X-ray Photoelectron Spectroscopy

C. Nordling E. Sokolowski and K. Siegbahn, *Phys. Rev.* **1957**, 105, 1676.



Precision Method for Obtaining Absolute Values of Atomic Binding Energies

CARL NORDLING, EVELYN SOKOLOWSKI, AND KAI SIEGBAHN

Department of Physics, University of Uppsala, Uppsala, Sweden

(Received January 10, 1957)

WE have recently developed a precision method of investigating atomic binding energies, which we believe will find application in a variety of problems in atomic and solid state physics. In principle, the method

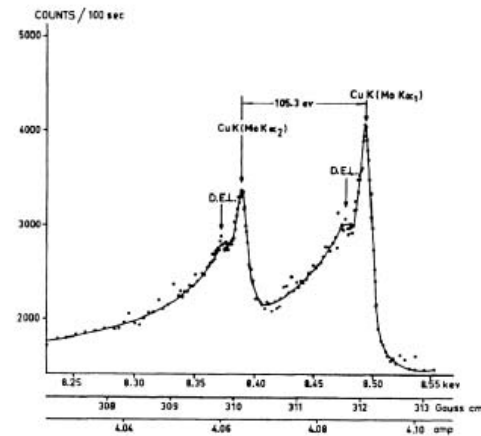
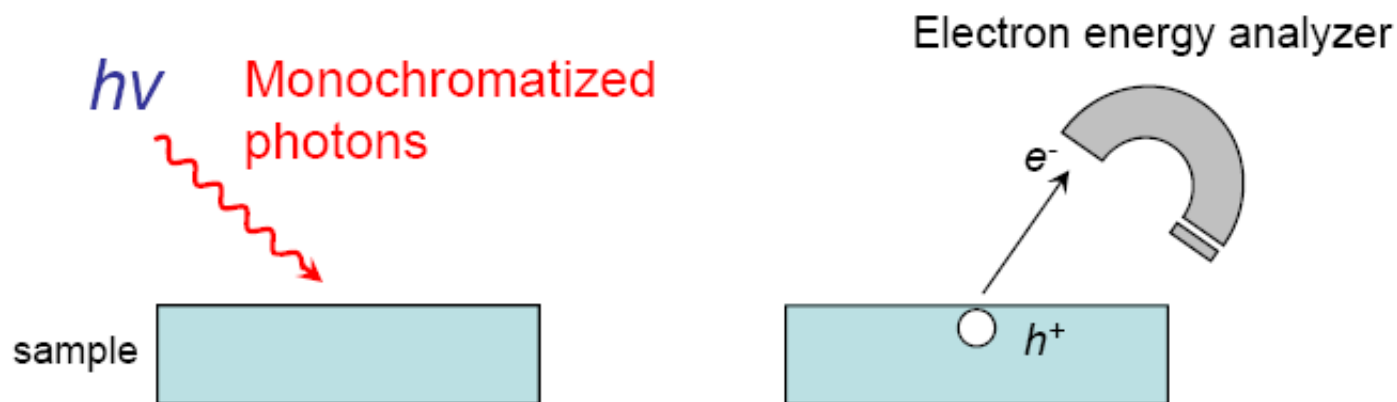


FIG. 1. Lines resulting from photoelectrons expelled from Cu by Mo $K\alpha_1$ and Mo $K\alpha_2$ x-radiation. The satellites marked D.E.L. are interpreted as due to electrons which have suffered a discrete energy loss when scattered in the source.

Nobel Prize in Physics 1981

(His father, Manne Siegbahn, won the Nobel Prize in Physics in 1924 for the development of X-ray spectroscopy)

What is photoemission spectroscopy? (photoelectron spectroscopy) (PES)



Initial state: ground (neutral) state

Final state: hole (excited) state

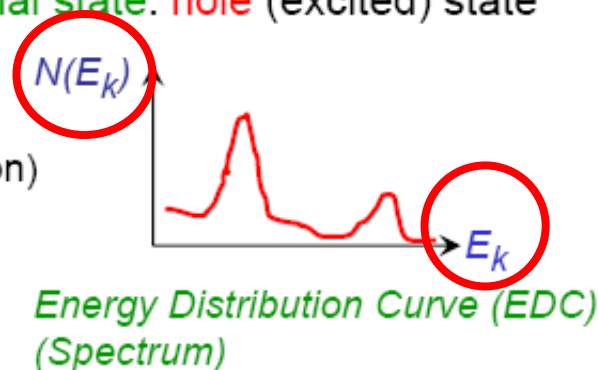
Conservation of energy

$$E_k = h\nu + E_i - E_f \text{ (most general expression)}$$

E_k : photoelectron kinetic energy

$E_i(N)$: total initial state system energy

$E_f(N-1)$: total final state system energy

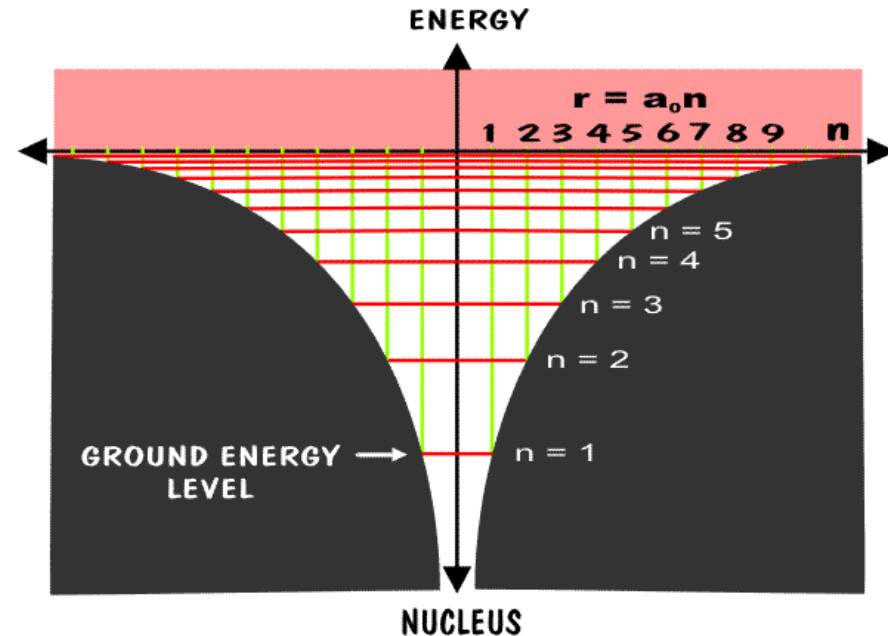
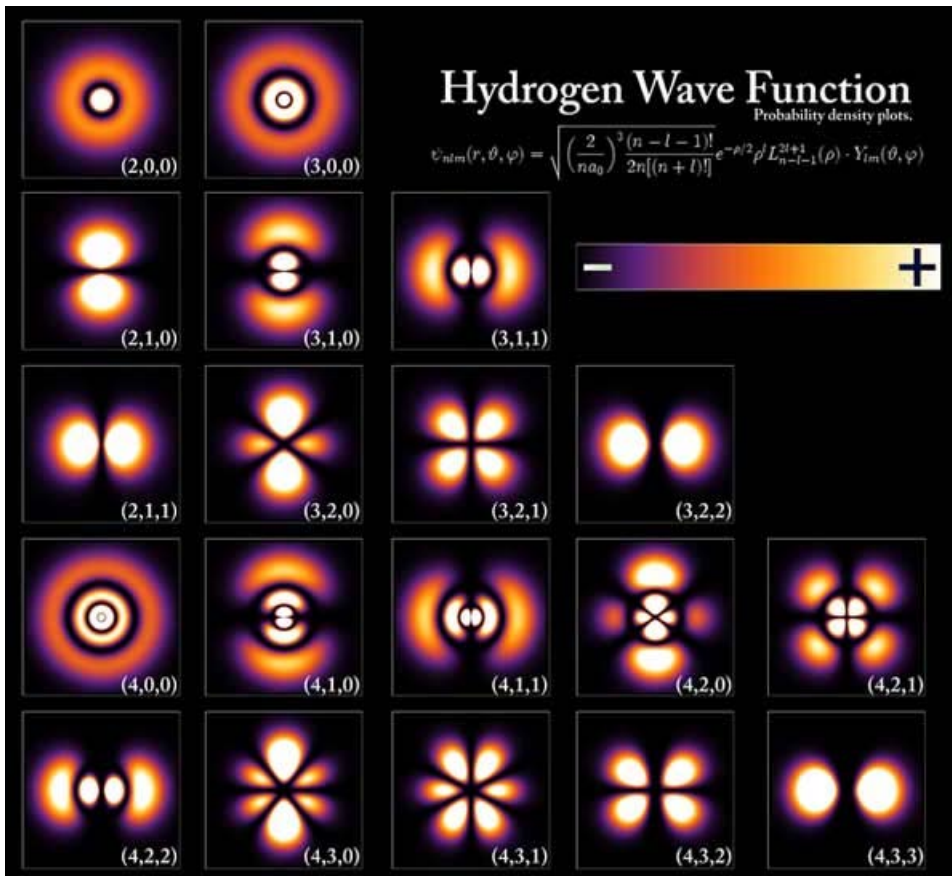


What are the samples and probed states?

- Atoms atomic orbitals (states)
- Molecules molecular orbitals
 core level states (atomic like)
- Nanoprticles valence bands/states
 core level states (atomic like)
- Solids valence bands
 core level states (atomic like)

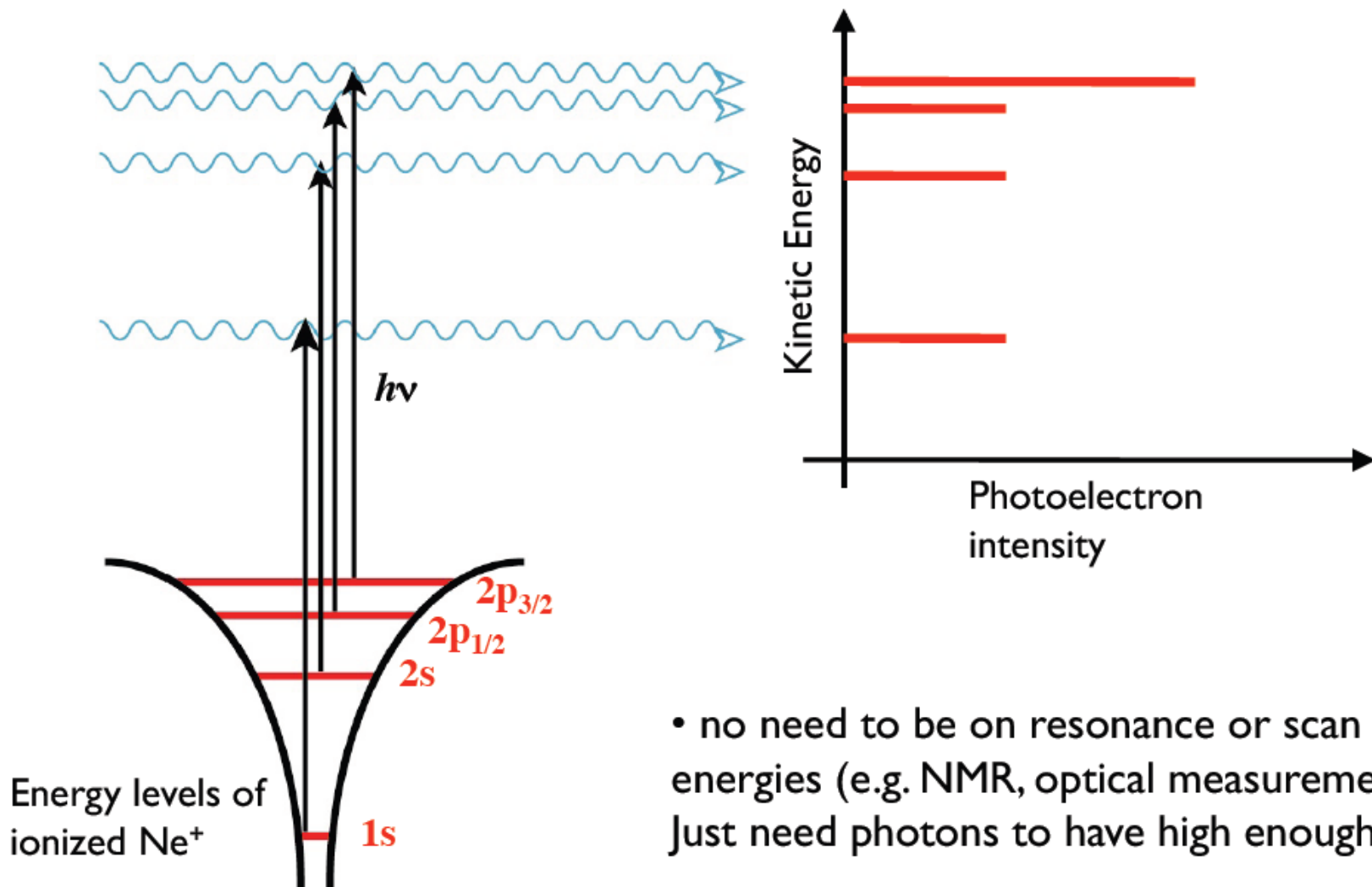


The energy level of hydrogen atom



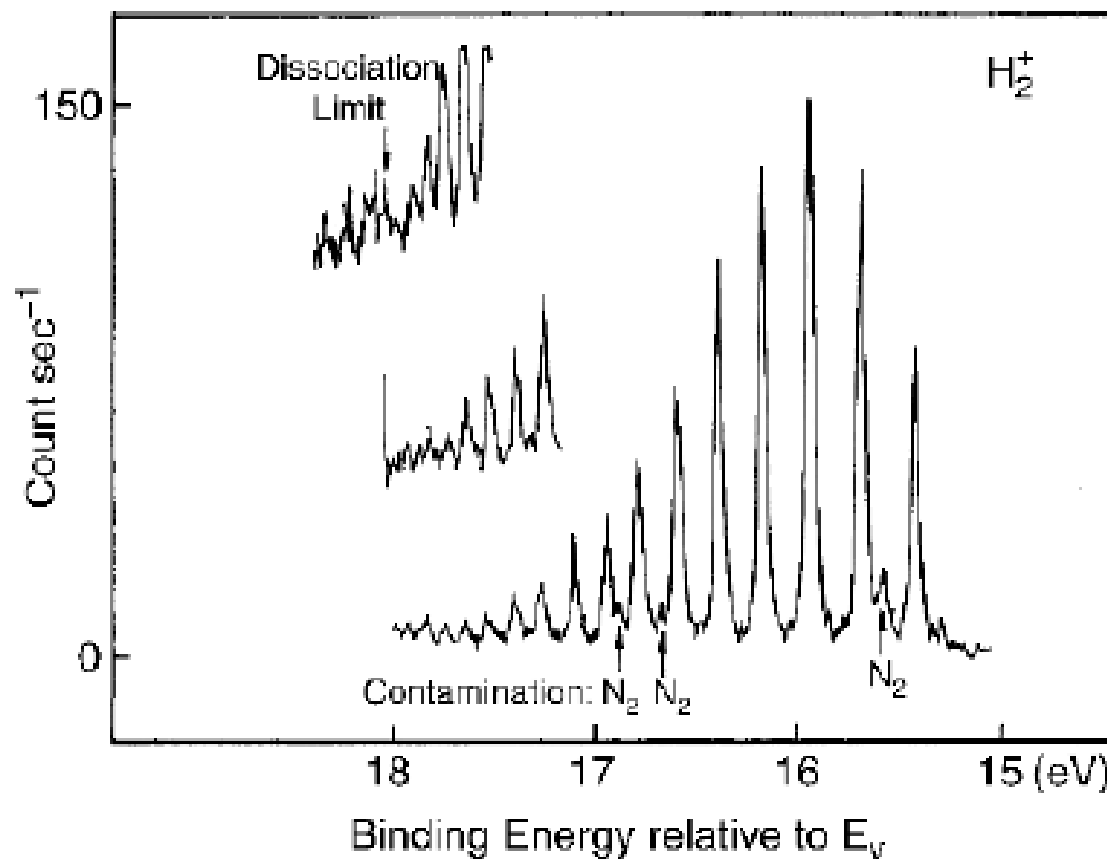
Electron ionization levels are formed from discrete levels in an atom

Energy conservation : $h\nu - E_I = \text{KE}$



- no need to be on resonance or scan photon energies (e.g. NMR, optical measurements). Just need photons to have high enough energy!

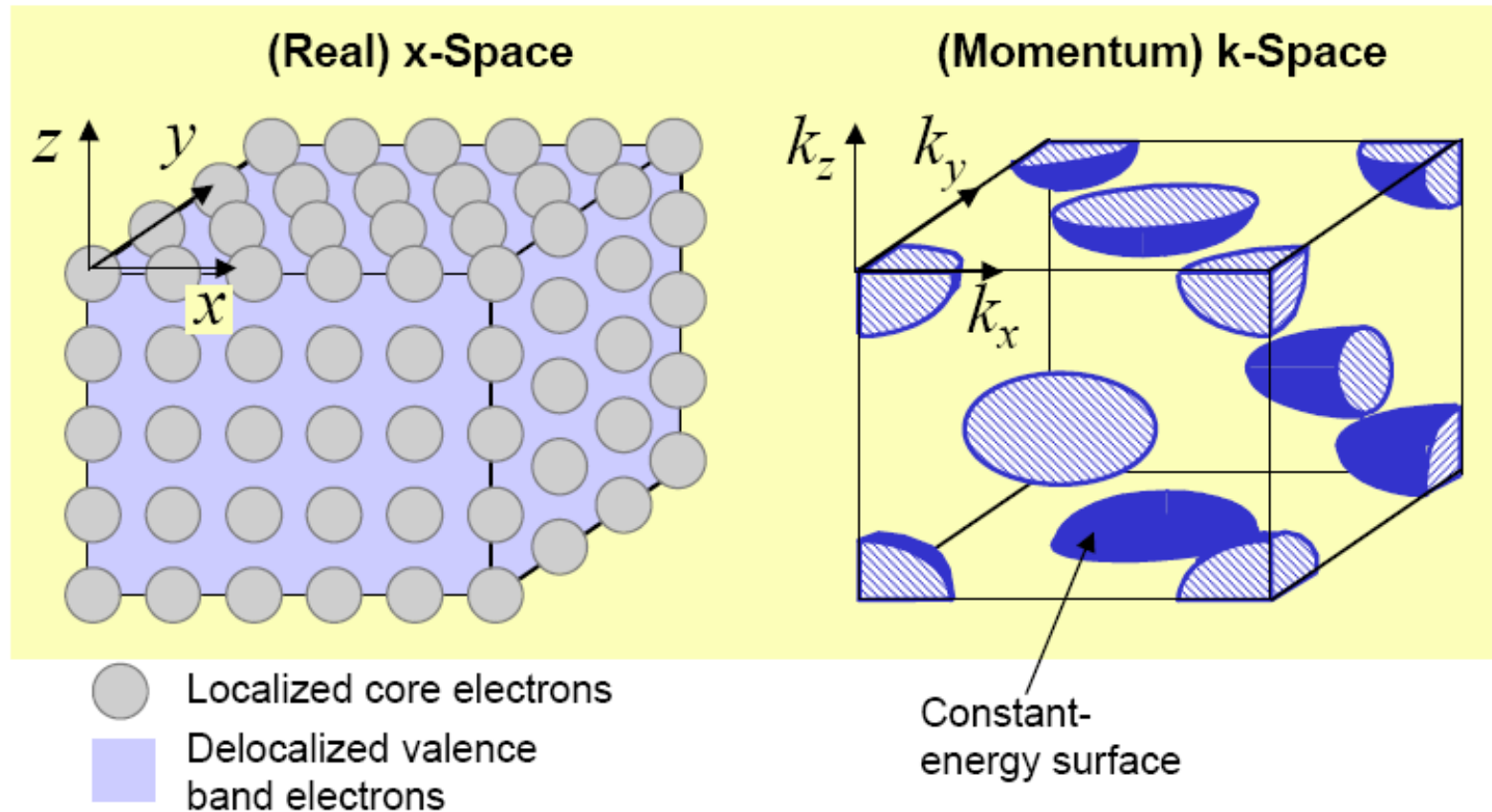
Xeon gas phase test



ect	
t:	R4000-4MS278
	Scienta
	1/27/2011
gy:	2 eV
	Scienta
oe:	59000 ms
	1
t Resolution:	3.8 meV
t Resolution:	1.7 meV

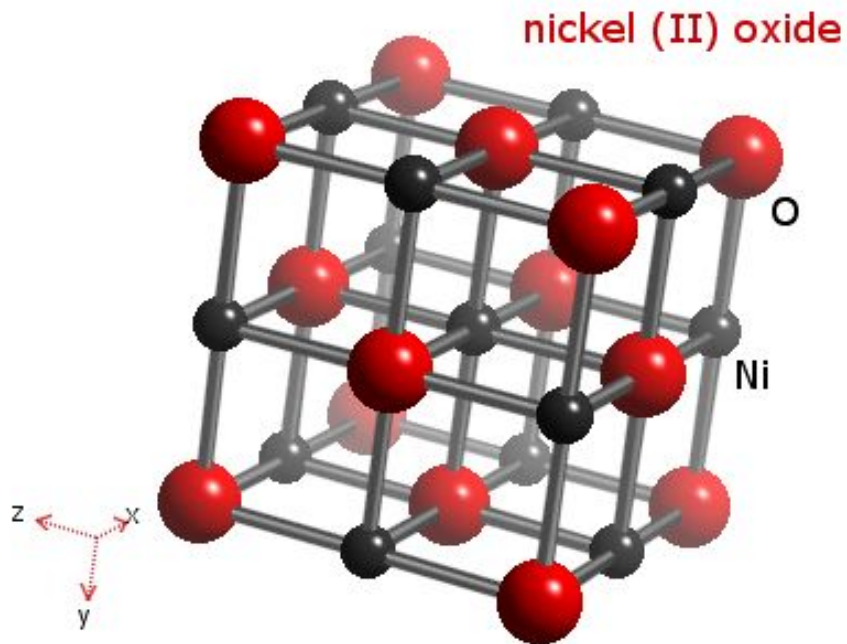


The crystal structure and momentum space



primitive vectors $\mathbf{a}_1, \mathbf{a}_2, \mathbf{a}_3$

reciprocal lattice vector $\mathbf{b}_1, \mathbf{b}_2, \mathbf{b}_3$



$$\vec{b}_1 = 2\pi \frac{\vec{a}_2 \times \vec{a}_3}{V}$$

$$\vec{b}_2 = 2\pi \frac{\vec{a}_3 \times \vec{a}_1}{V}$$

$$\vec{b}_3 = 2\pi \frac{\vec{a}_1 \times \vec{a}_2}{V}$$

$$V = \vec{a}_1 \cdot \vec{a}_2 \times \vec{a}_3$$

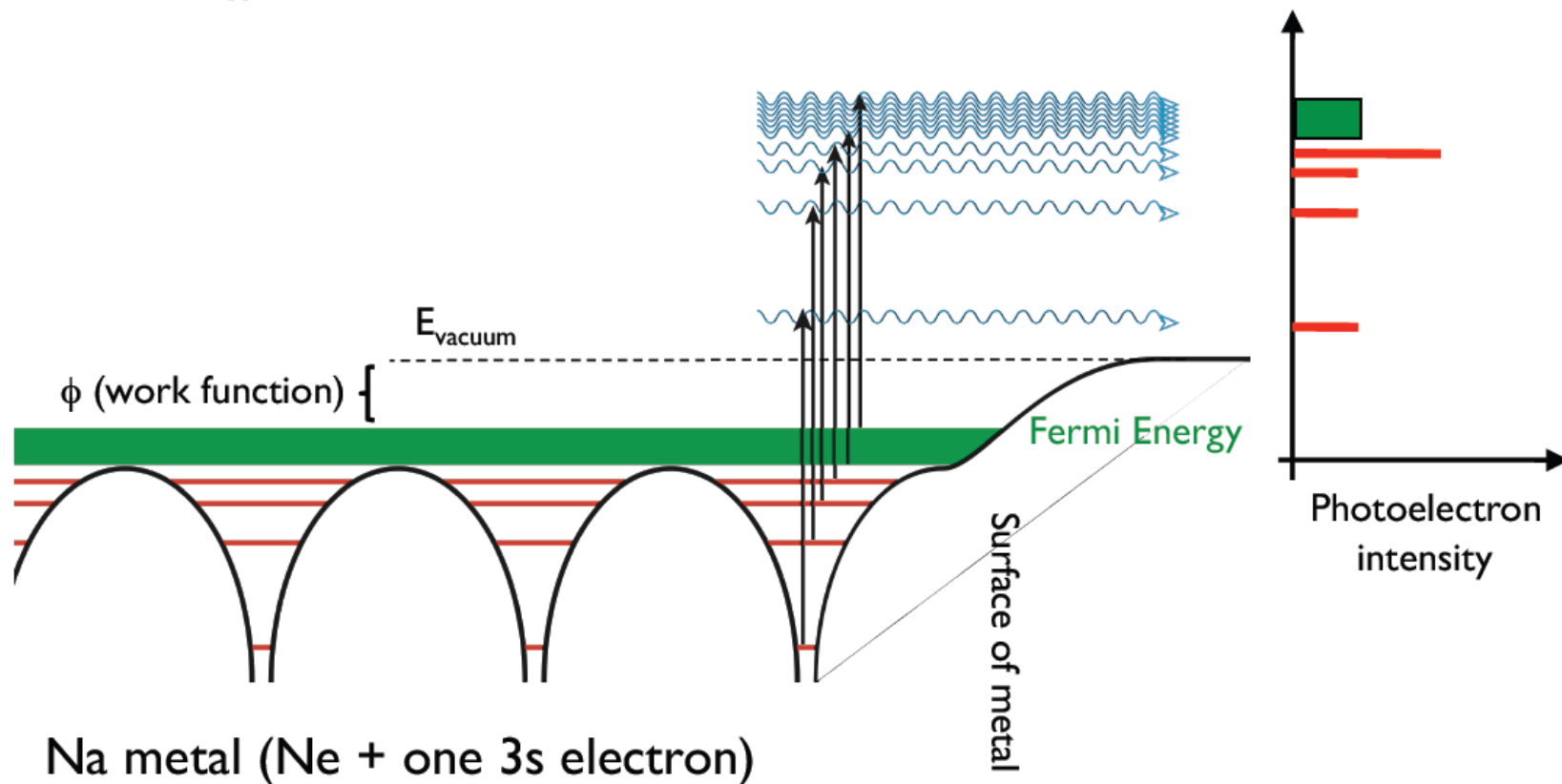
reciprocal lattice $\mathbf{G}$:

$$\vec{G} = l\vec{b}_1 + m\vec{b}_2 + n\vec{b}_3$$

l, m, n are any integers



- Deeply bound “*core*” electrons remain basically unchanged
- Outermost “*valence*” electrons hybridize forming continuous “*energy bands*”



Band theory

Two approximations

Nearly free electrons. Electrons are **non-interacting** in a periodic **crystal potential** which is **relatively weak** and can be treated as a perturbation. As in the free-electron-gas model, they are still subject to the Pauli exclusion principle.

Free electron gas :

The interactions between electrons and between electrons and nuclei are turned off, subject only to the Pauli exclusion principle.

Tightly-bonding approximation

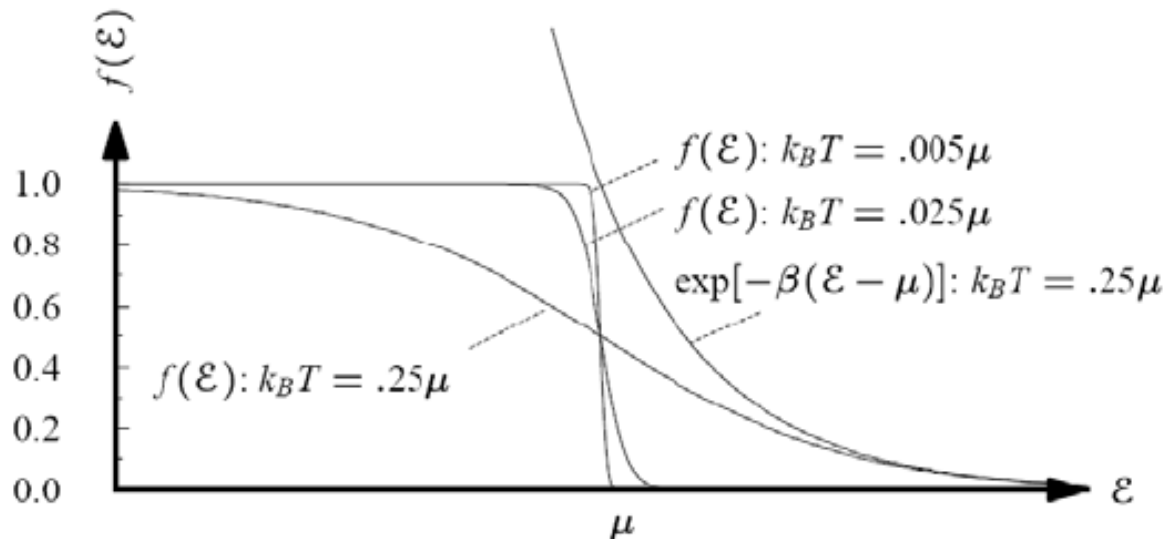
Electrons are tightly bound to particular atoms, **overlapping only weakly with neighbors.**

Fermi-Dirac Distribution

Thermal Properties of Free Electron Gas:

Almost every electronic transport property of solids is proportional to $D(\mathcal{E}_F)$.

Fermi function $f(\mathcal{E}) = \frac{1}{e^{(\mathcal{E}-\mu)/k_B T} + 1}$
(Fermi-Dirac distribution)



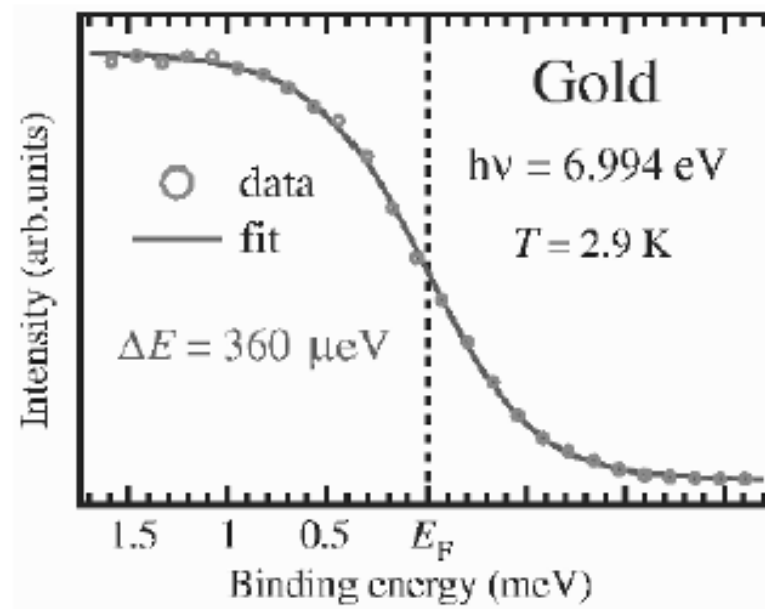
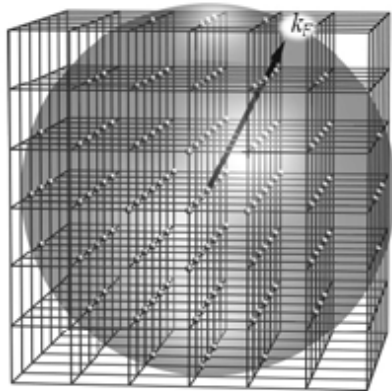


Fig. 2.3. Ultra-high resolution photoemission spectrum on a polycrystalline gold sample (evaporated Au film) for the determination of the energy resolution. The Fermi edge was measured at $T = 2.9$ K using a frequency tripled ($\text{KBe}_2\text{BO}_3\text{F}_2$ crystal, KBBF) YVO_3 laser for the photoexcitation ($h\nu = 6.994$ eV) [15]



Density of State



In building up the ground state of very large N electrons, the ground state corresponds to **setting the occupation number $f_k = 1$ for $k \leq k_F$ and $f_k = 0$ for others;** k_F is called the **Fermi vector**.

The volume of the Fermi sphere is $\frac{4\pi k_F^3}{3}$.

$$\text{Electronic density } n = \frac{N}{V} = \left(\frac{4\pi k_F^3}{3}\right) D_{\vec{k}} = \left(\frac{4\pi k_F^3}{3}\right) \frac{2}{(2\pi)^3} = \frac{k_F^3}{3\pi^2}$$

For an energy $\mathcal{E}$, total numbers of states:

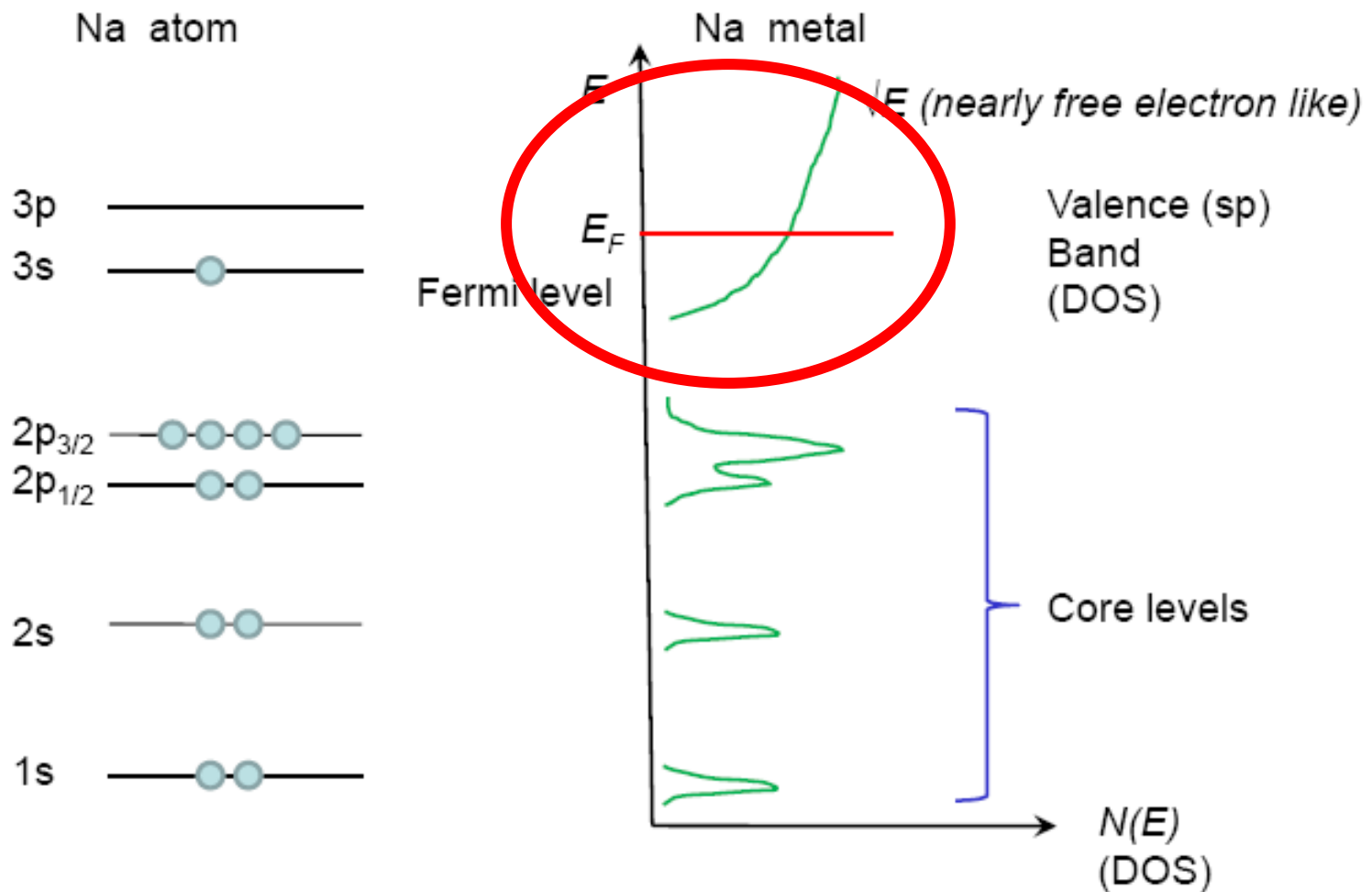
$$N = V \frac{k^3}{3\pi^2} = V \frac{(2m\mathcal{E})^{3/2}}{3\pi^2 \hbar^3} \quad \because \mathcal{E} = \frac{\hbar^2 k^2}{2m} \quad k = \frac{\sqrt{2m\mathcal{E}}}{\hbar}$$

Energy density of states $D(\mathcal{E}) \equiv \frac{1}{V} \frac{dN}{d\mathcal{E}}$

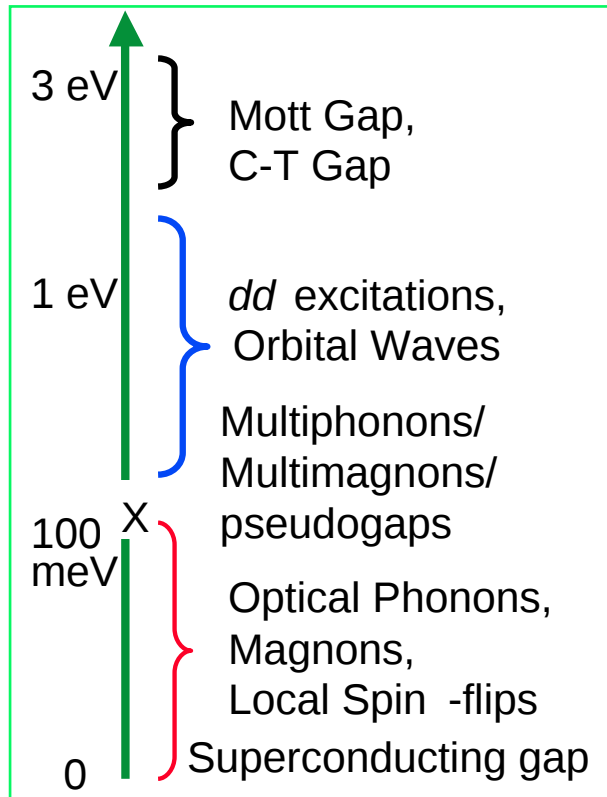
$$D(\mathcal{E}) = \frac{1}{V} \frac{dN}{d\mathcal{E}} = \frac{\sqrt{2m^3\mathcal{E}}}{\pi^2 \hbar^3}$$

No. of states bounded between $\mathcal{E}(k)$ and $\mathcal{E}(k) + d\mathcal{E}$ per unit volume

Single particle description of energy levels (Density of States) (most convenient in PE)



Energy scale and important excitations



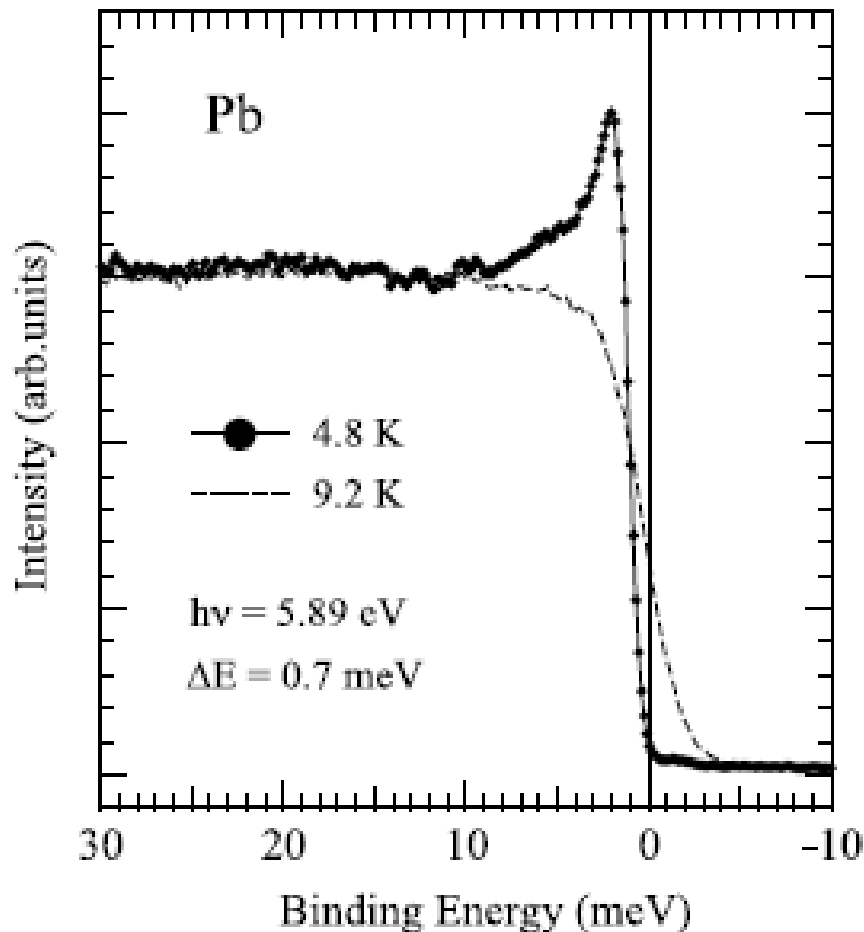
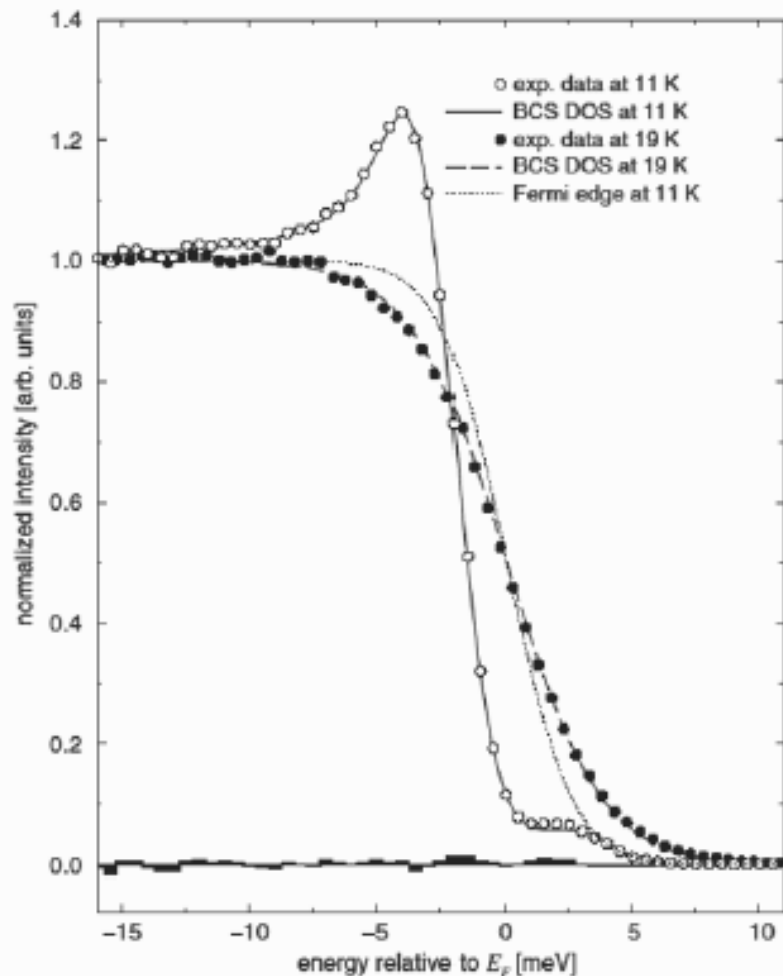
- Superconducting gap $\sim 1 - 100 \text{ meV}$
- Optical Phonons: $\sim 40 - 70 \text{ meV}$
- Magnons: $\sim 10 \text{ meV} - 40 \text{ meV}$
- Pseudogap $\sim 30 - 300 \text{ meV}$
- Multiphonons and multimagnons $\sim 50 - 500 \text{ meV}$
- Orbital fluctuations (originated from optically forbidden *d-d* excitations): $\sim 100 \text{ meV} - 1.5 \text{ eV}$

Requirement: High Energy Resolution with High Intensity

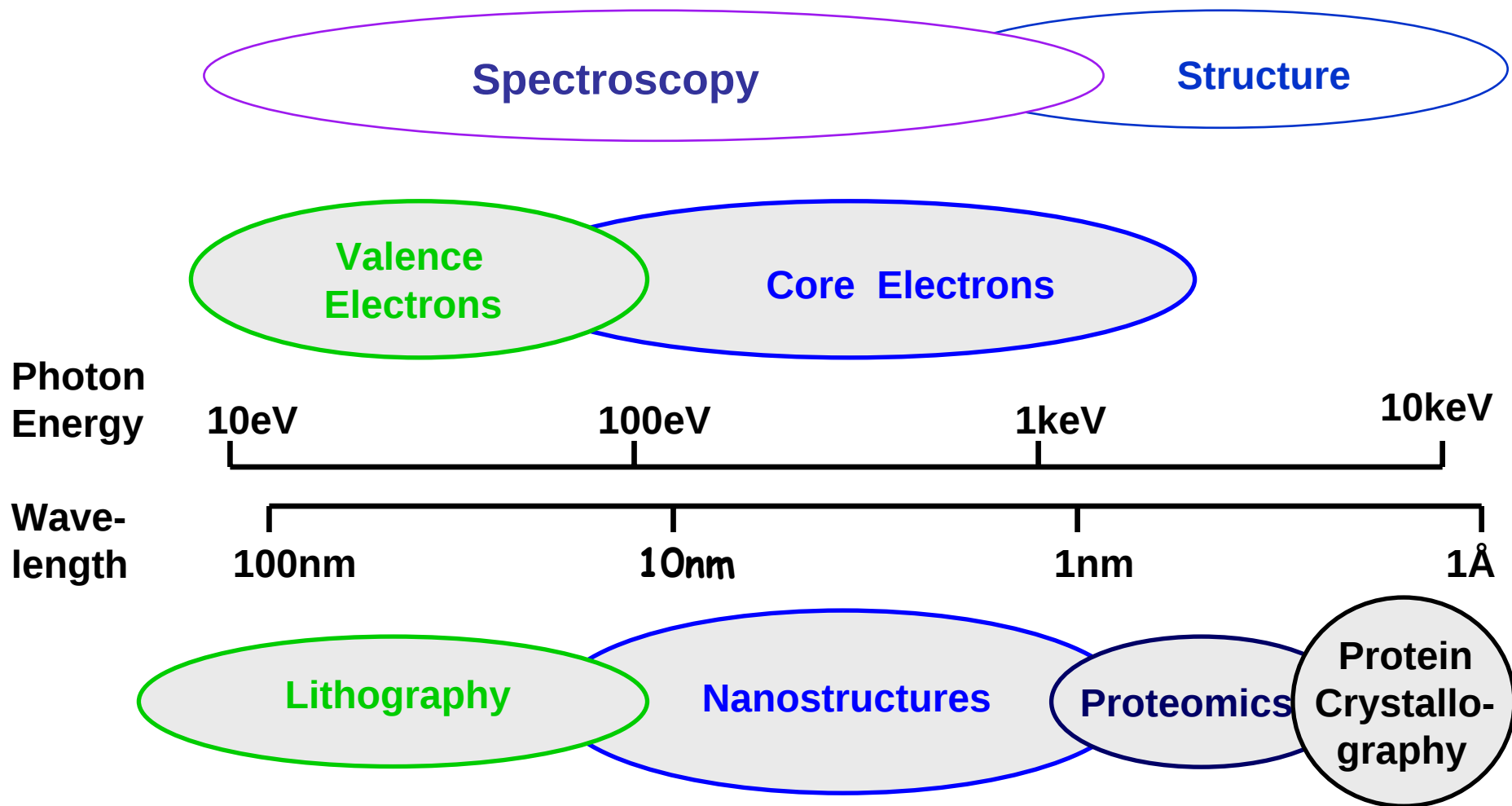


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Superconducting gap



Science with Light Sources



Light sources and terminology

- **Ultraviolet Photoemission Spectroscopy (UPS)**
 - UV He lamp (21.2 eV, 40.8 eV)
 - Laser (high harmonic generation): 6 eV (BBO), 8 eV (KDDP), 11 eV (gas cell)
 - Valence band PES, direct electronic state info.
- X-ray Photoemission Spectroscopy (XPS)
(Electron Spectroscopy for Chemical Analysis) (ESCA)
 - X-ray gun (Al: 1486.6 eV, Mg: 1253.6 eV)
 - core level PE, indirect electronic state info
 - chemical analysis
- **Synchrotron radiation**
 - continuous tunable wavelength
 - valance band and core level

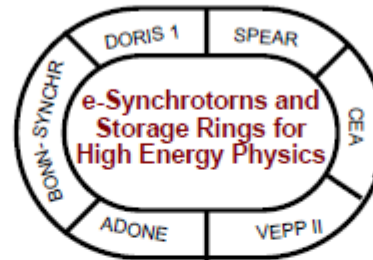


3rd Synchrotron Radiation light source

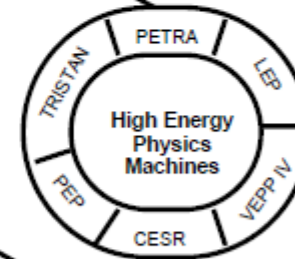
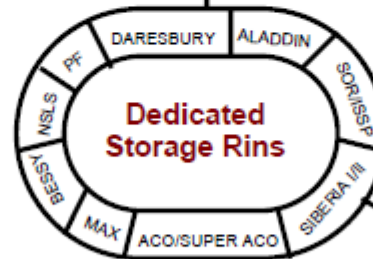
Synchrotron Radiation

Year 1947: First Synchrotron Radiation observed in weak focusing synchrotron betatrons

1st G :1960-1970

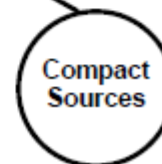
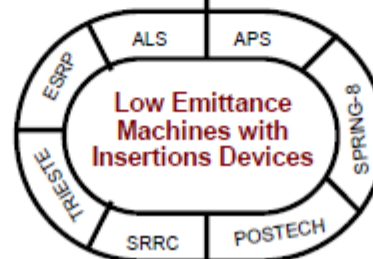


2nd G :1970-1980



3rd G :1980-

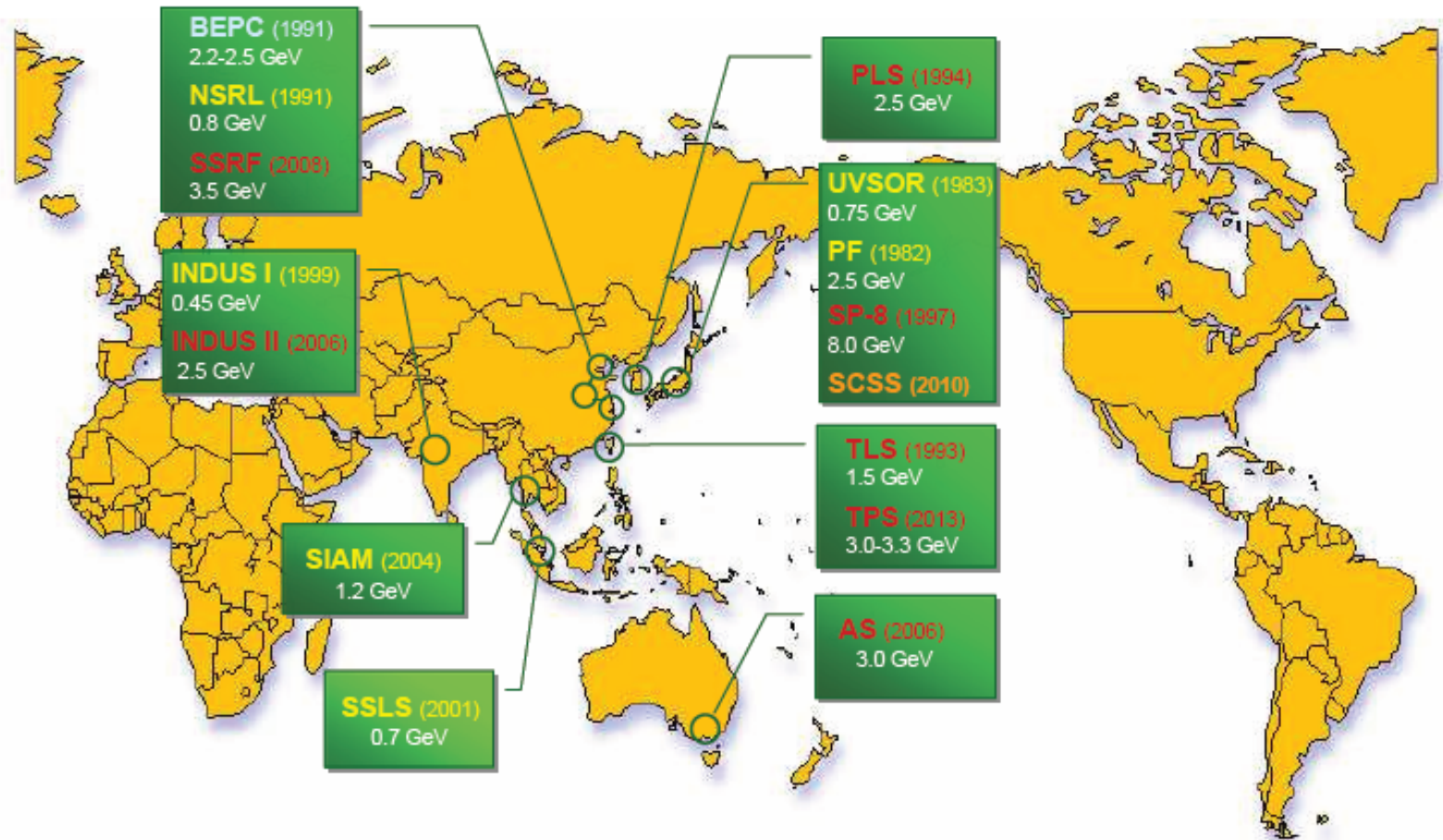
- Straight sections for insertion devices
- Low emittance



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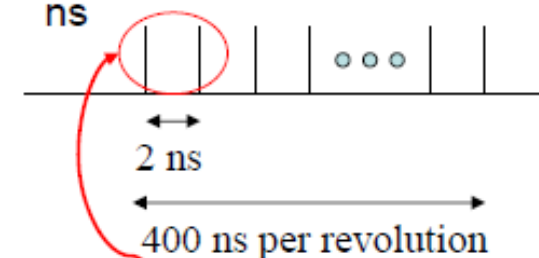
Cheiron2008_KSLiang-9

SR Facilities in Asia Oceania Region

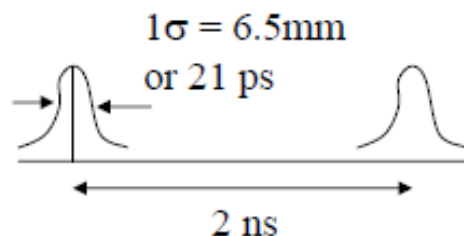


Basic Parameters of Taiwan Light Source

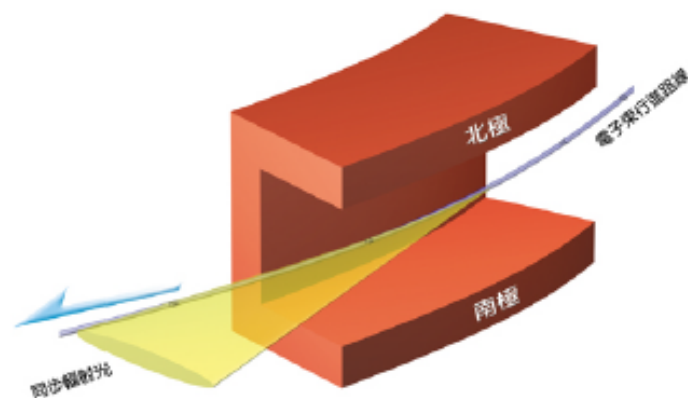
- Interval between bunches: 2 ns
- Bunch length (1σ @1.6MV): 6.5 mm
- Bunch duration (1σ): 21 ps
- SC Cavity length: 24 cm
- Flight time through SC cavity: 0.8 ns



Zoom in



- Bunch current (180/200 filling to $I_{\text{avg}}=300$ mA): 1.67 mA/bunch or 4.17×10^9 electrons/bunch

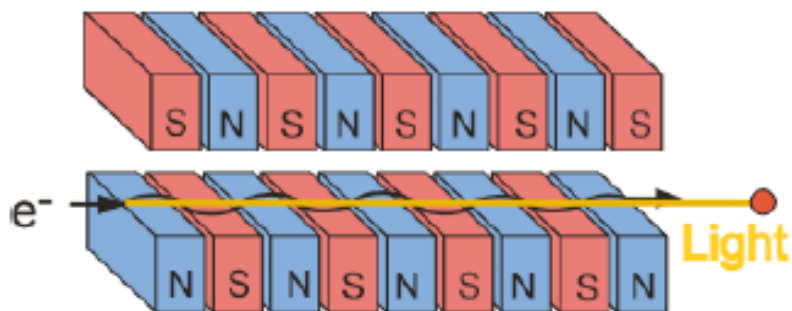


- Critical energy of SR
 $E_c(\text{keV}) = 0.665 E^2 (\text{GeV}) B(\text{T})$

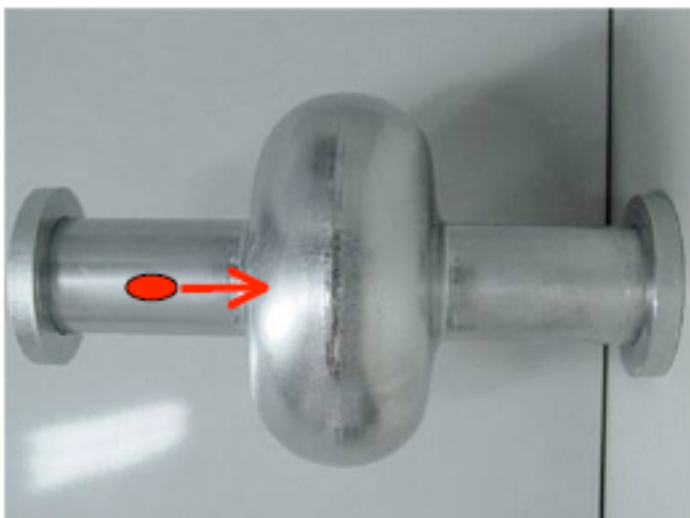
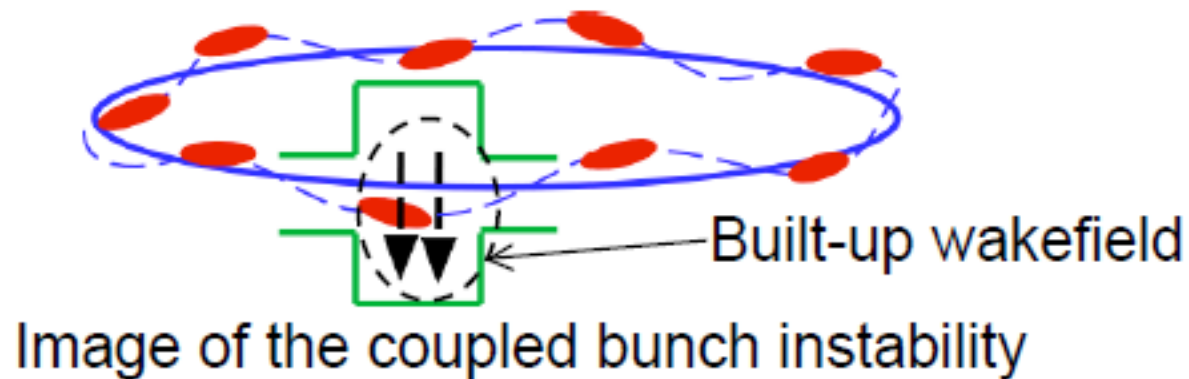


Light source properties vs electron beam performance(1)

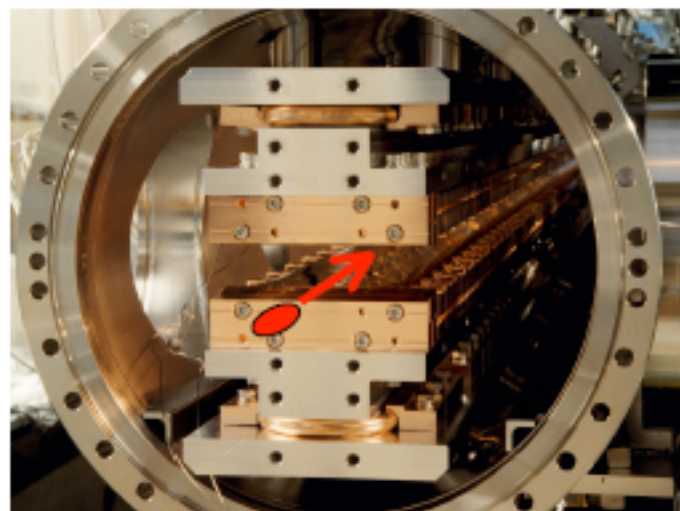
Main devices to supply SR to users are “undulators”, which are installed in magnet-free straight sections in 3rd-generation SR sources.



5. Current limiting factors(4)



High Q structure (RF cavity)



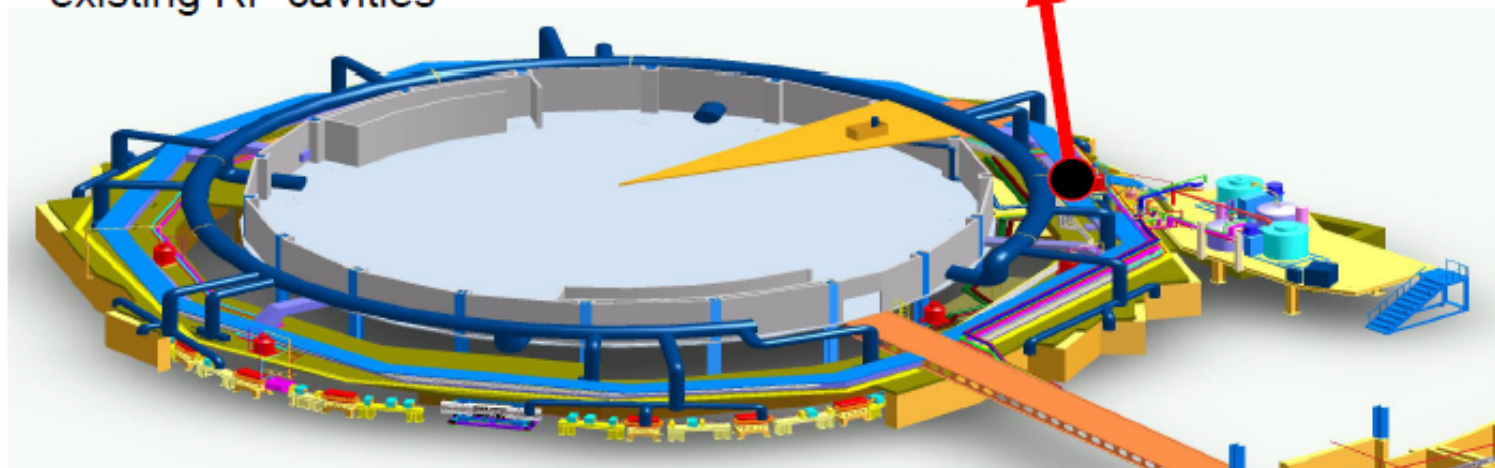
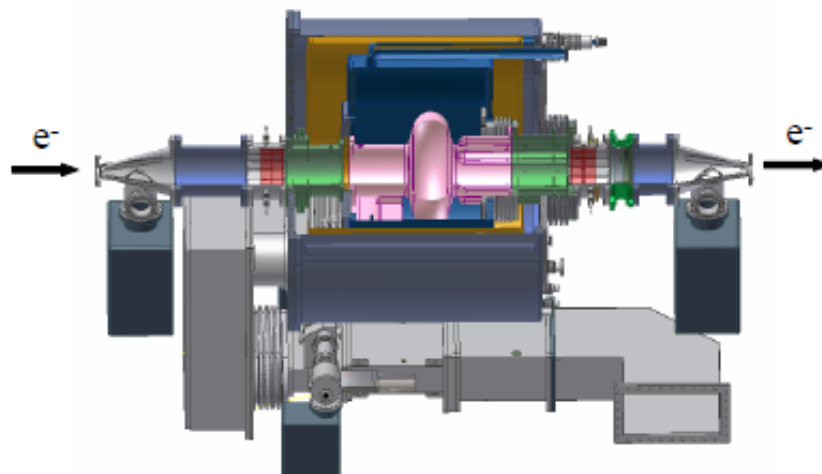
Narrow gap undulator



Superconducting RF Cavity

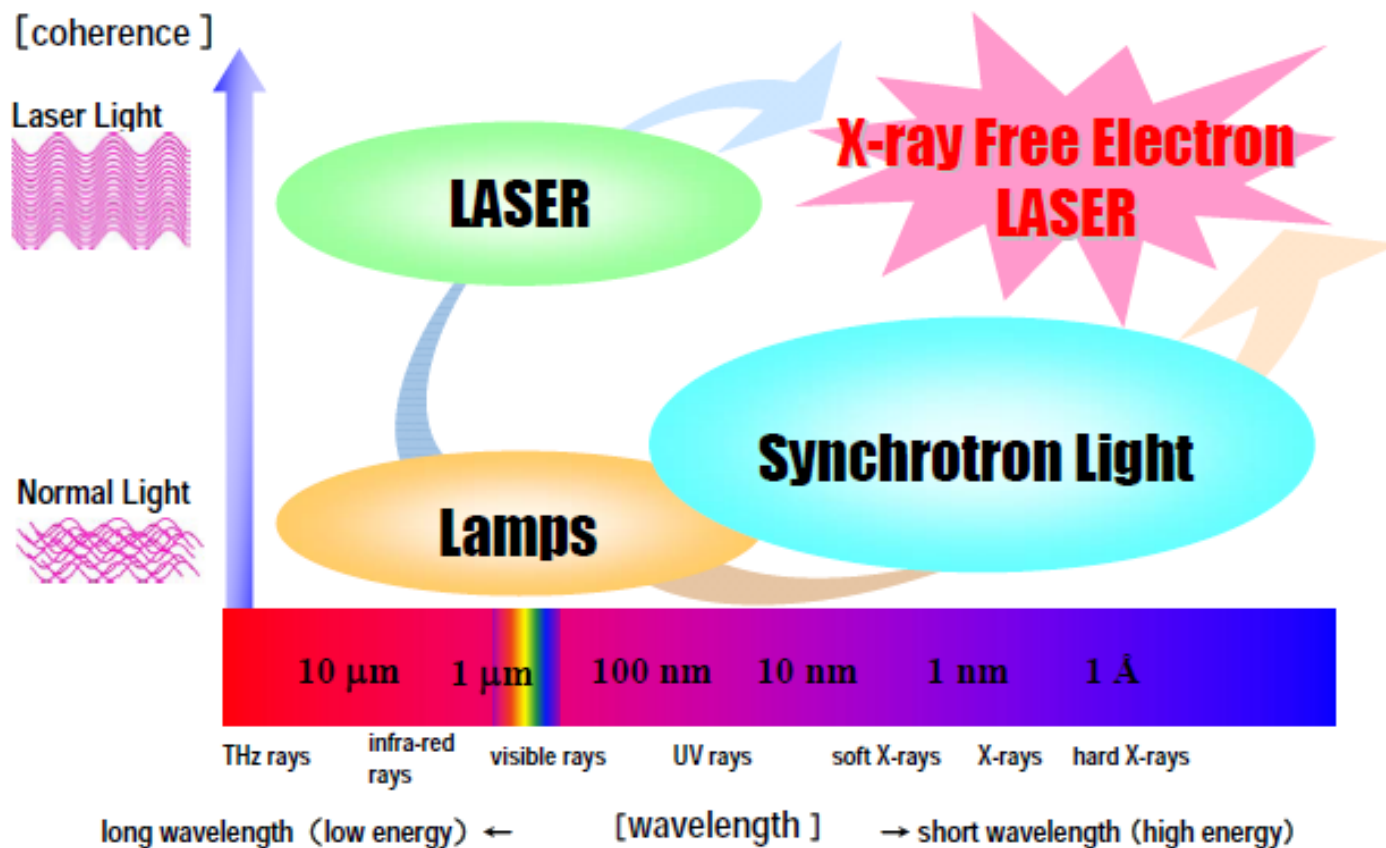
Goals :

- To increase the maximum electron beam current of the storage ring from 240 mA to 500 mA
- To eliminate beam instabilities caused by the strong higher-order modes (HOMs) of the existing RF cavities

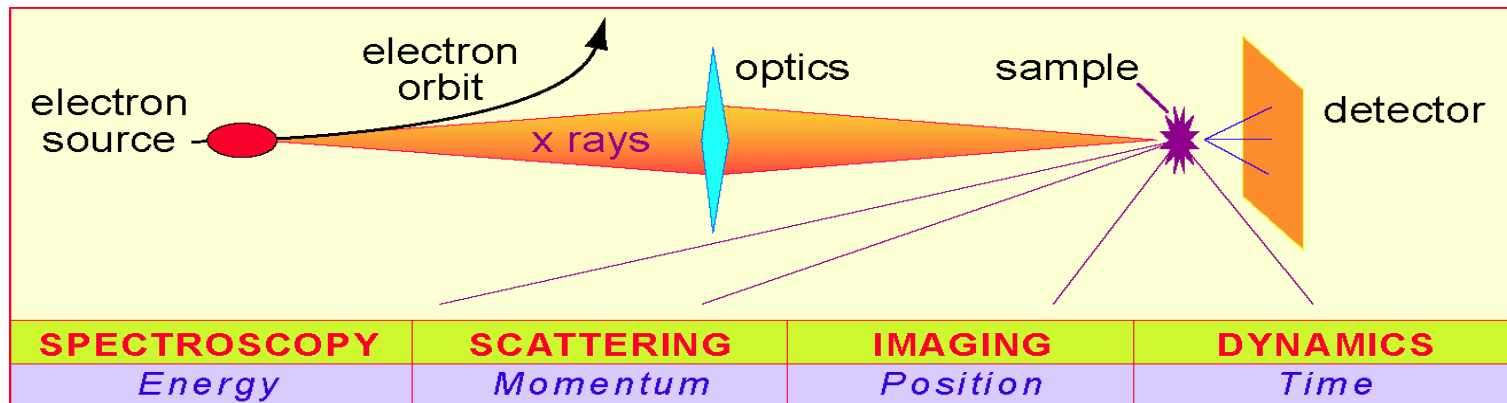


“X-ray Free Electron Laser, XFEL”

coherent light to explore nano-world



Techniques of Synchrotron Radiation (SR)



The fundamental parameters necessary for perception of physical world:

- **Energy** (spectroscopy, state of matter)
- **Momentum** (scattering)
- **Position** (imaging, spatial distribution)
- **Time** (dynamics)



numerous techniques of SR

Spectroscopy

- 01 Low-Energy Spectroscopy
- 02 Soft X-Ray Spectroscopy
- 03 Hard X-Ray Spectroscopy
- 04 Optics/Calibration/Metrology

Scattering

- 05 Hard X-Ray Diffraction
- 06 Macromolecular Crystallography
- 07 Hard X-Ray Scattering
- 08 Soft X-Ray Scattering

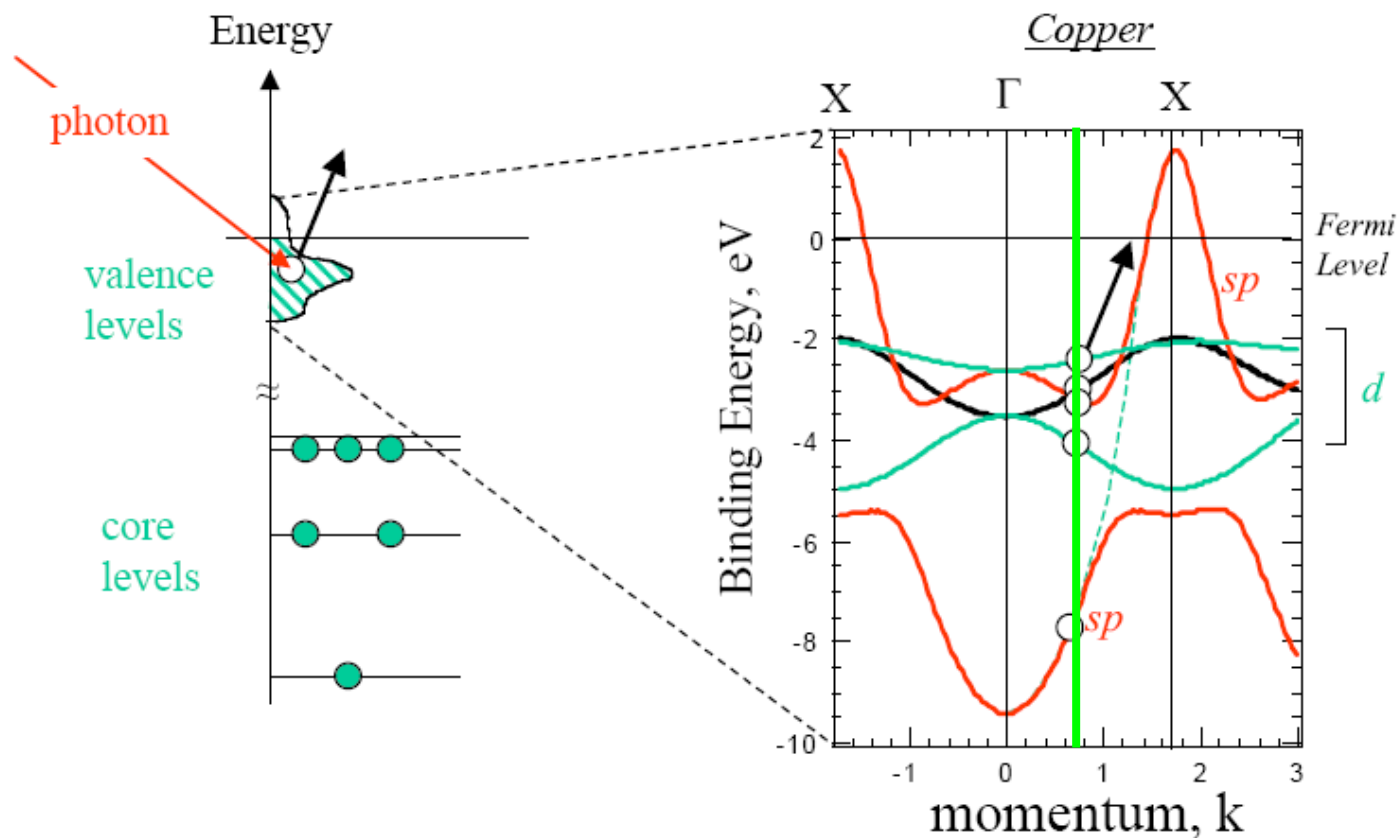
Imaging

- 09 Hard X-Ray Imaging
- 10 Soft X-Ray Imaging
- 11 Infrared Imaging
- 12 Lithography

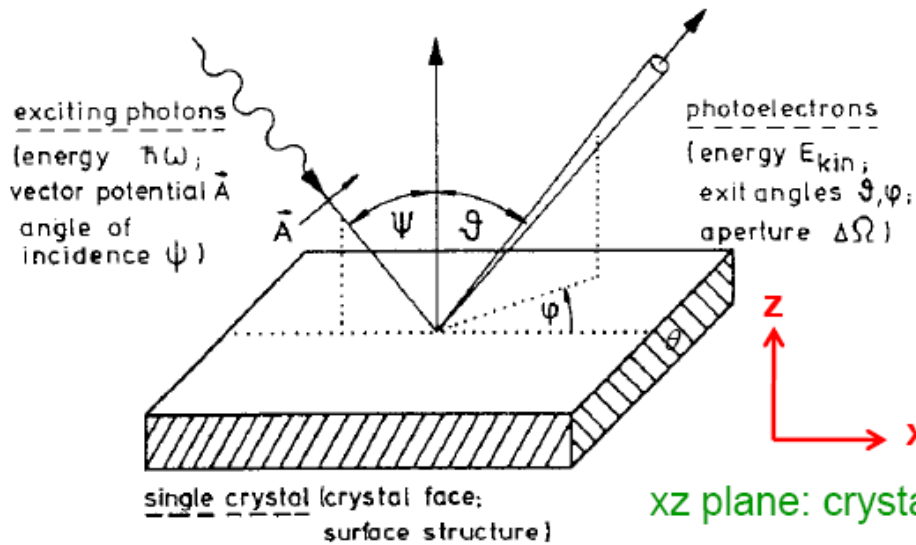


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Angle-integrated photoemission (AIPES) and angle-resolved photoemission (ARPES)



Angular Resolved Photoemission Spectroscopy (ARPES)



Electron emission angle: θ

Photon incident angle: ψ , s- and p-polarization

$$k_{\parallel} = \sqrt{\frac{2m}{\hbar^2} E_k} \cdot \sin \theta$$

$$k_{\parallel} (\text{\AA}^{-1}) = 0.5123 \sqrt{E_k (eV)} \cdot \sin \theta$$

$$k_{\parallel}(\text{inside}) = k_{\parallel}(\text{outside})$$

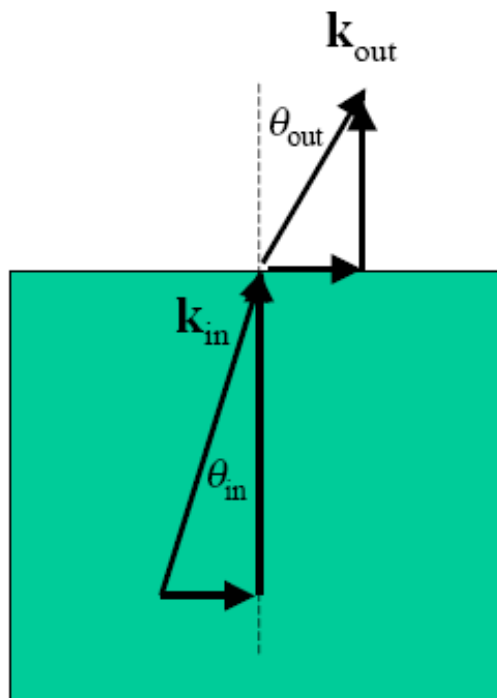
Conservation of linear momentum

Important for 3D and 2D band mapping

$$k_{\perp} = 0.5123 \sqrt{(E_{kin} \cos^2 \theta + V_0)}$$



Conservation of linear momentum parallel to the surface



Kinematic relations

$$k_{out} = \sqrt{\frac{2m}{\hbar^2} E_{kin}}$$

$$k_{in} = \sqrt{\frac{2m}{\hbar^2} (E_{kin} + V_0)}$$

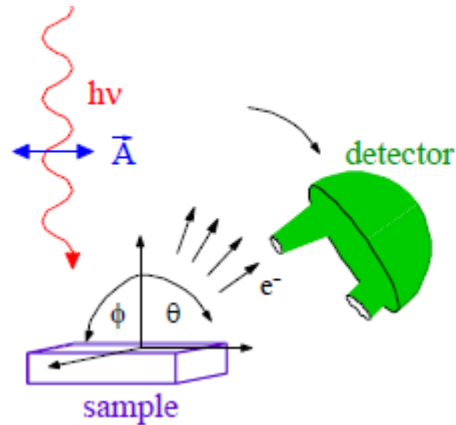
$$k_{out,\parallel} = k_{in,\parallel} \equiv k_{\parallel}$$

“Snell’s Law”

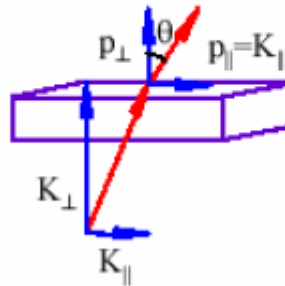
$$k_{\parallel} = \sin \theta_{out} \sqrt{\frac{2m}{\hbar^2} E_{kin}} = \sin \theta_{in} \sqrt{\frac{2m}{\hbar^2} (E_{kin} + V_0)}$$

Critical angle for emission

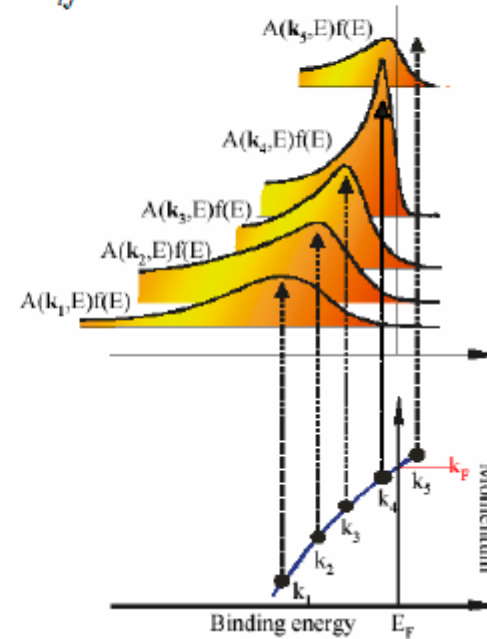
$$(\sin \theta_{out})_{\max} = \sqrt{\frac{E_{kin}}{E_{kin} + V_0}}$$



Electron momentum
Parallel to the surface is
conserved



$$\text{Intensity} \propto \sum_{i,f} \left| \langle f | \vec{p} \cdot \vec{A} | i \rangle \right|^2 A(\vec{k}, E) f(E)$$



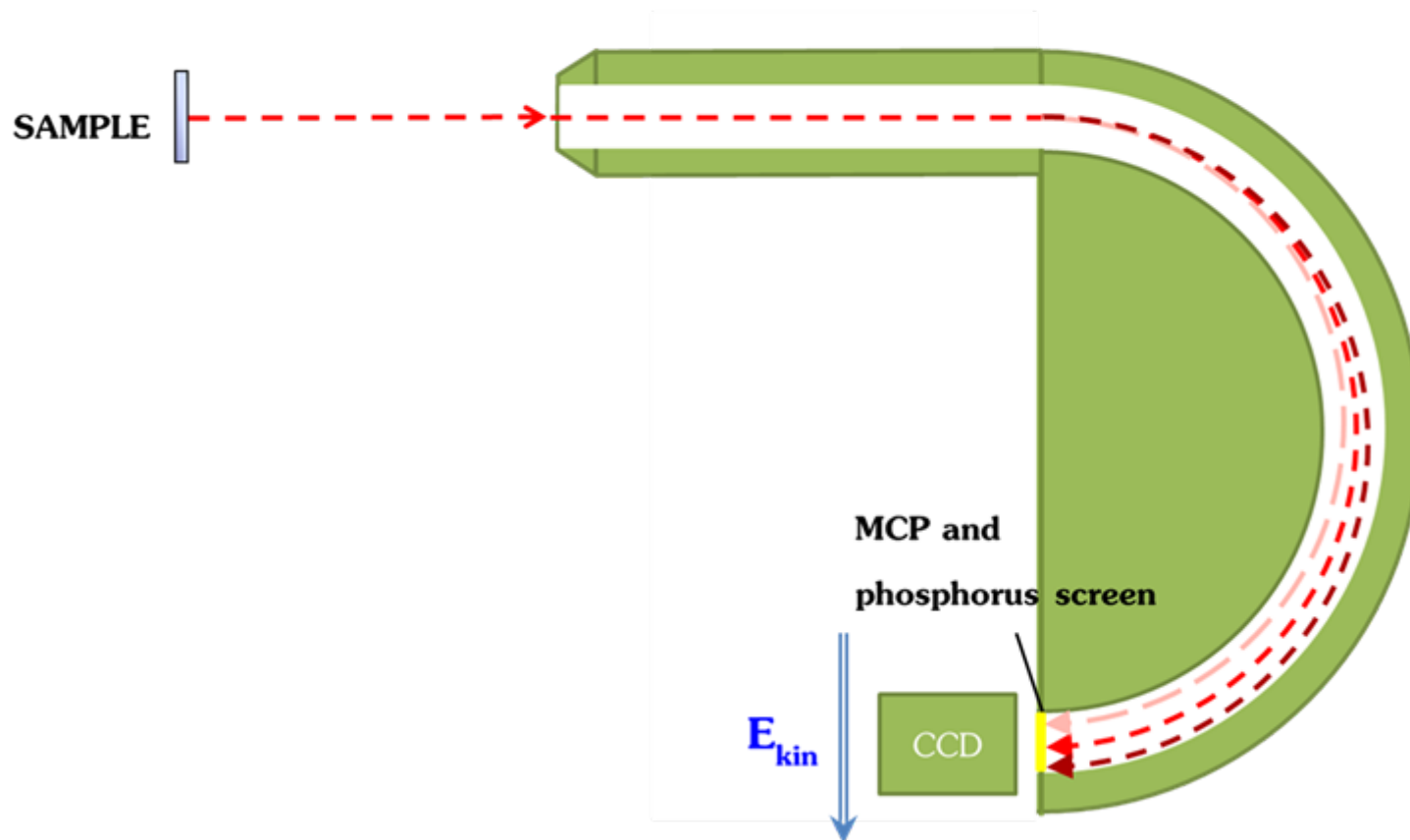
$$k_{\perp} = 0.5123 \sqrt{(E_{kin} \cos^2 \theta + V_0)}$$

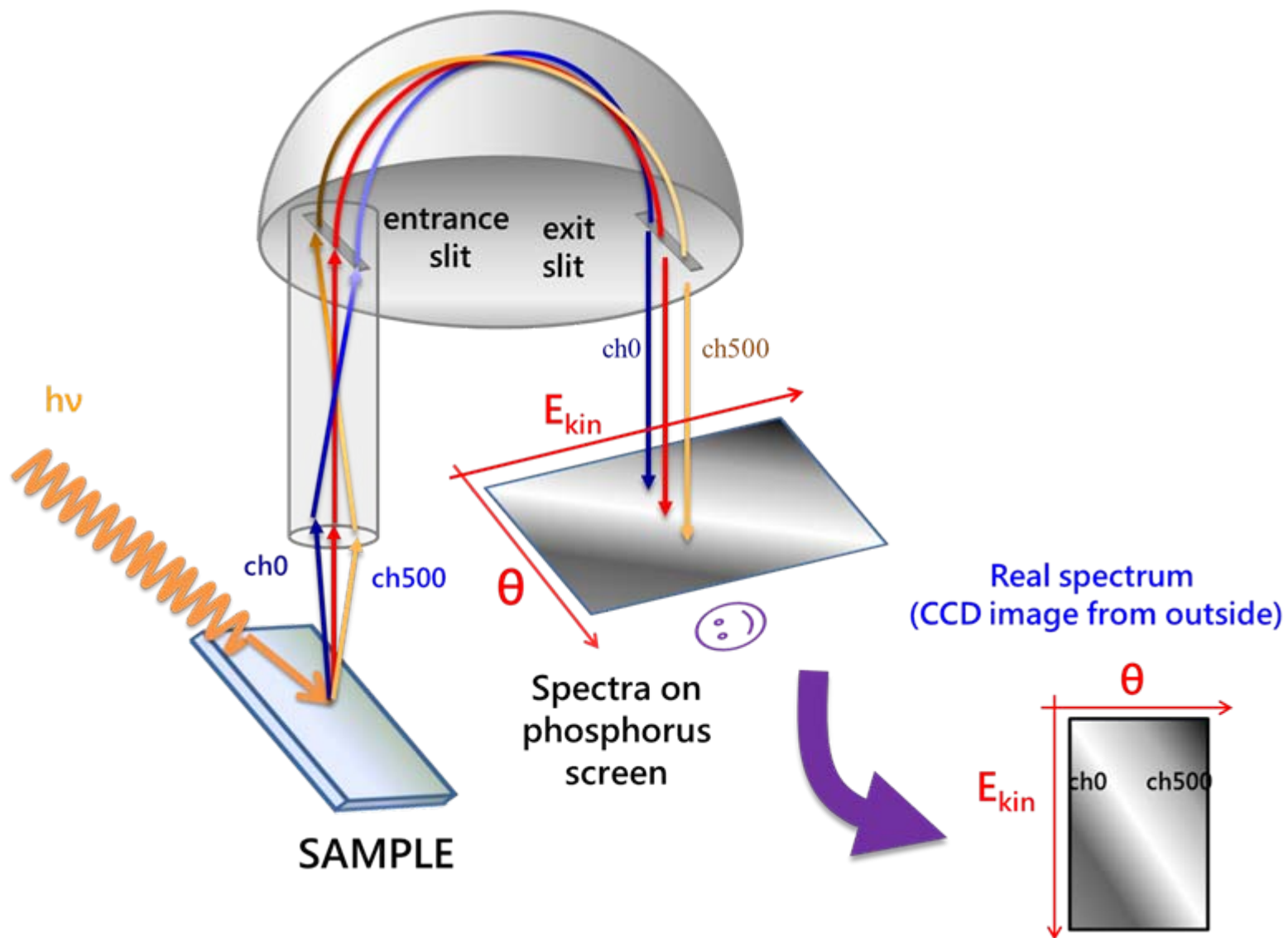
$$k_{//} = 0.5123 \sqrt{E_{kin}} \sin \theta$$

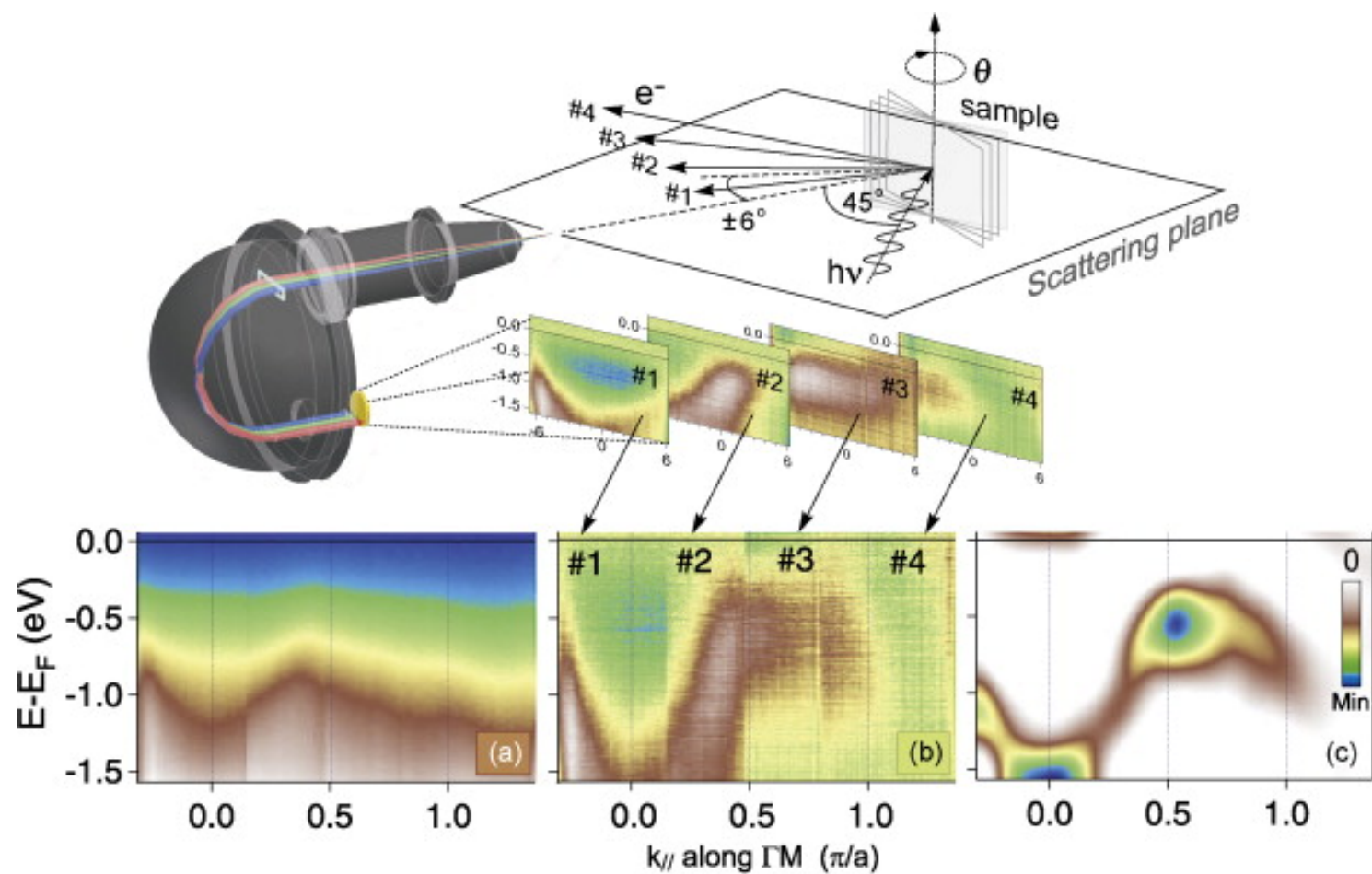
- Low photon energy provides better momentum resolution.
- We expect to study the electronic structure of solids at low photon energies (10 eV~100 eV).



SCIENTA R4000 Side View

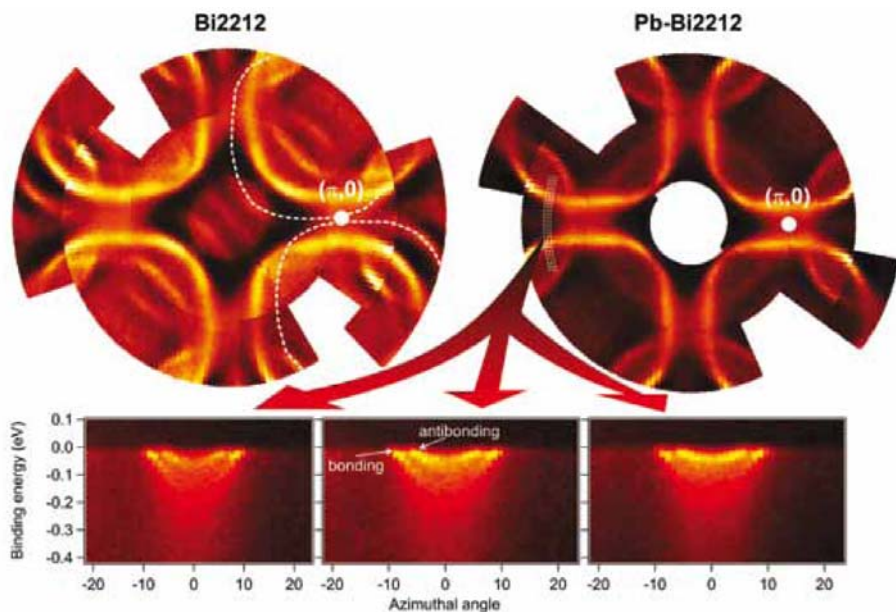




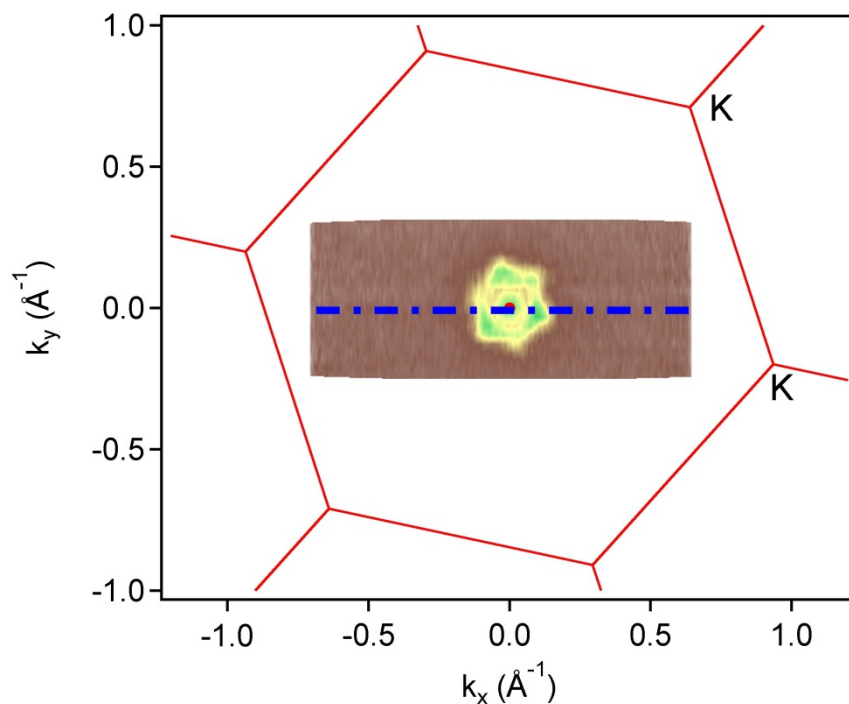


Angle is the soul of ARPES: Band mapping

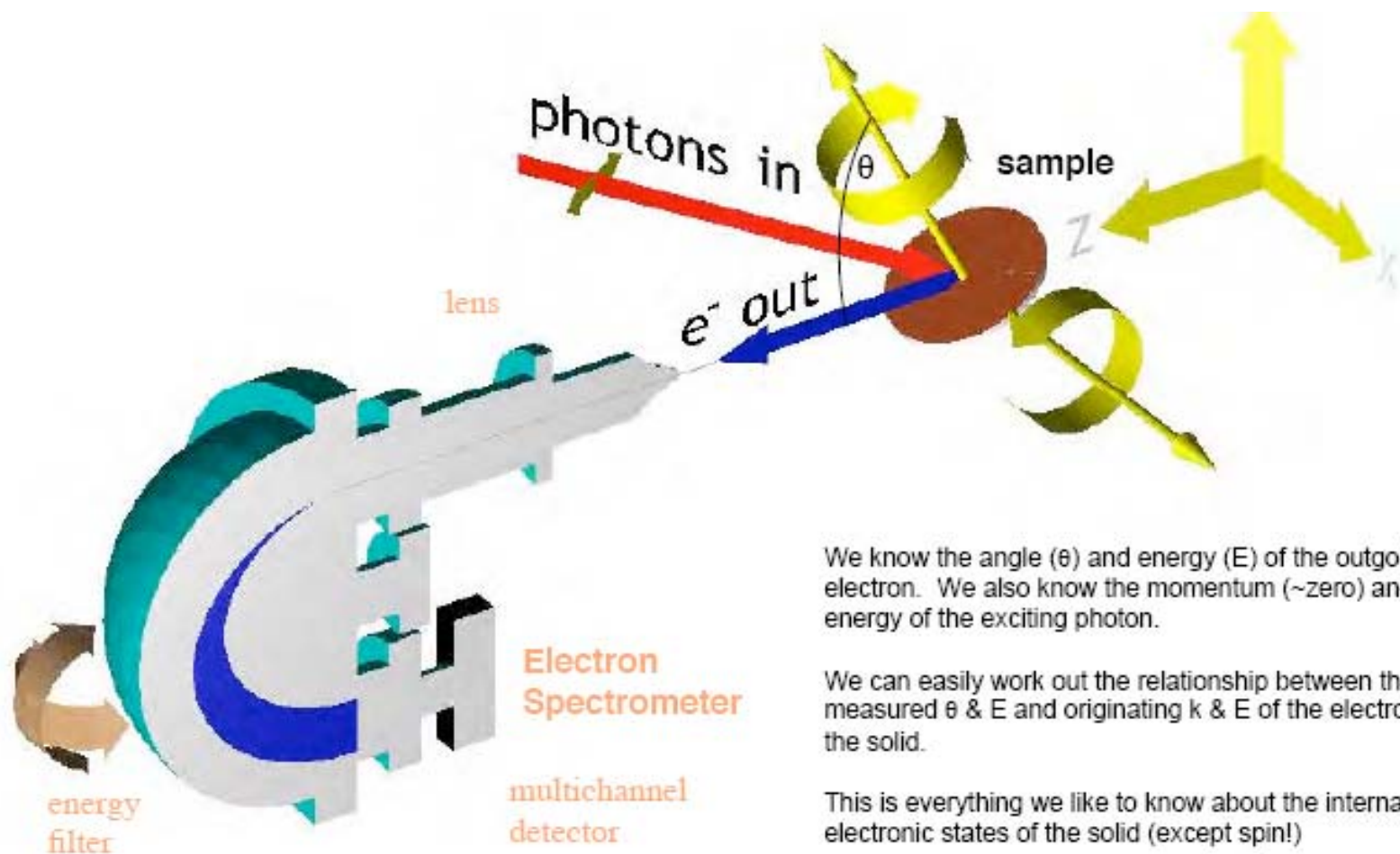
Azmuthal angle scan



Tilt angle scan



Experimental geometry



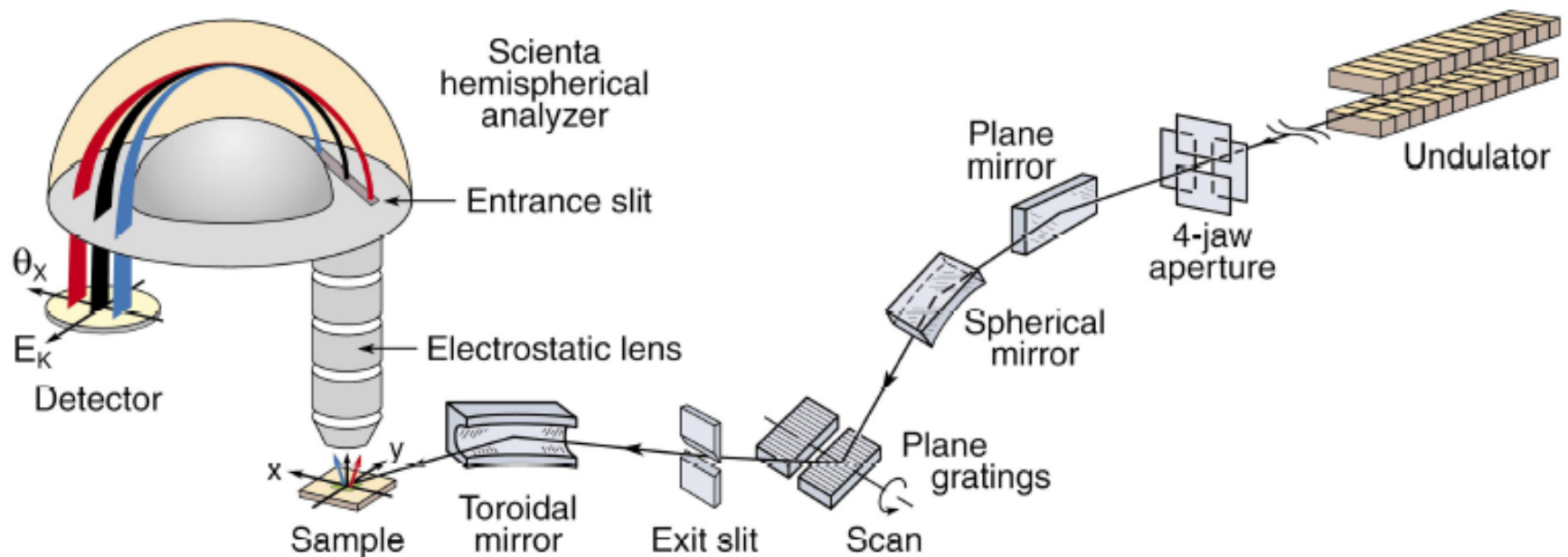
We know the angle (θ) and energy (E) of the outgoing electron. We also know the momentum ($\sim$ zero) and the energy of the exciting photon.

We can easily work out the relationship between the measured θ & E and originating k & E of the electrons in the solid.

This is everything we like to know about the internal electronic states of the solid (except spin!)

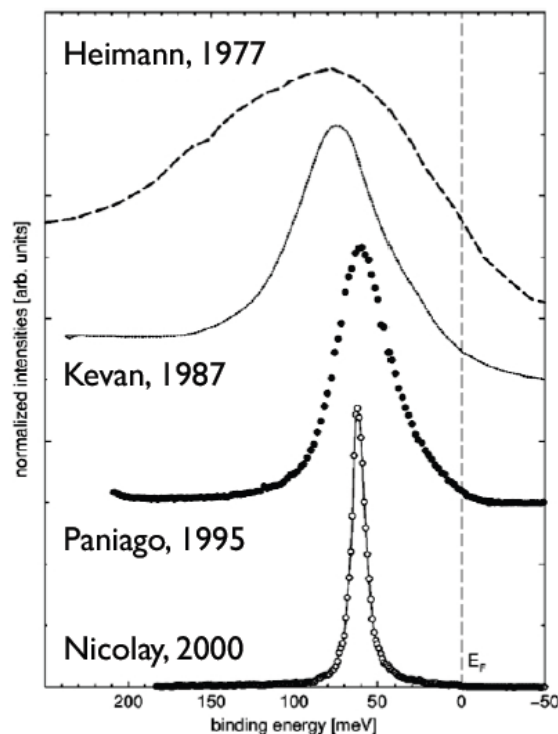


Beamline design for modern high resolution photoemission spectroscopy



The state-of-the-art in electron spectroscopy

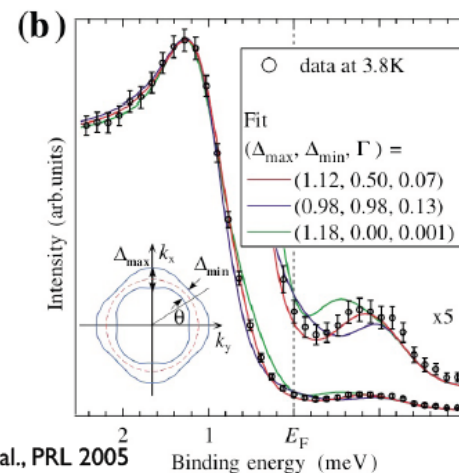
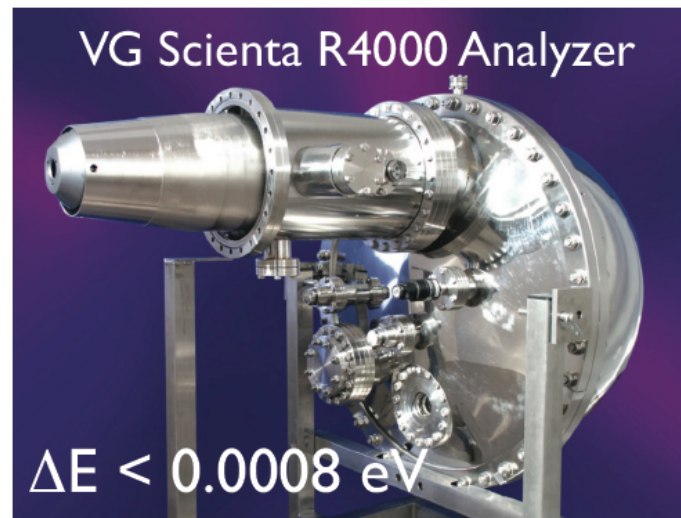
Evolution of instrumental resolution over time



F. Reinert et al., PRB (2001)



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T. Kiss et al., PRL 2005

Early ARPES experimental result

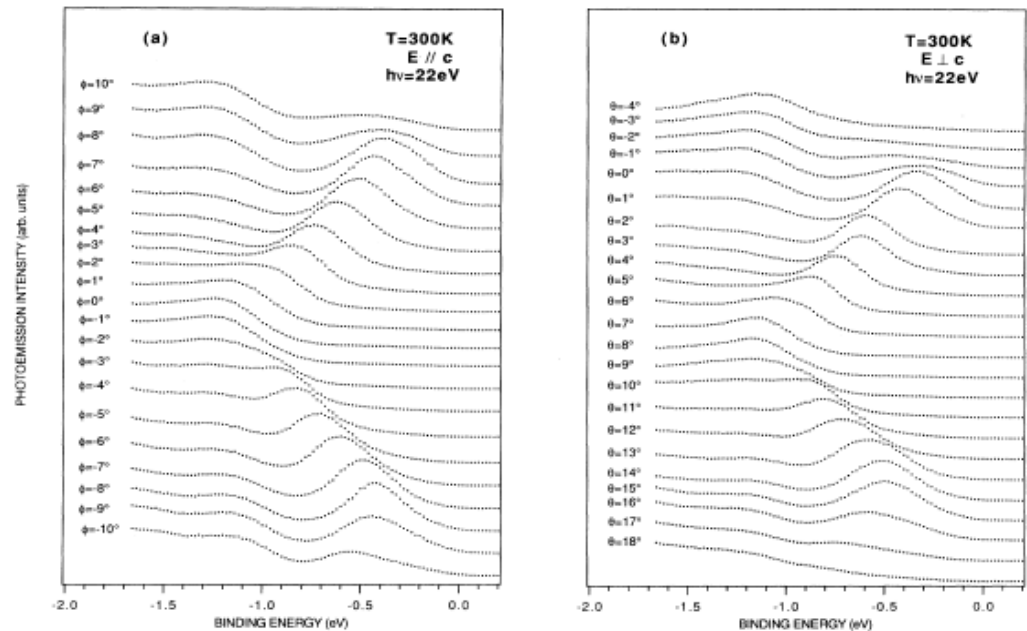
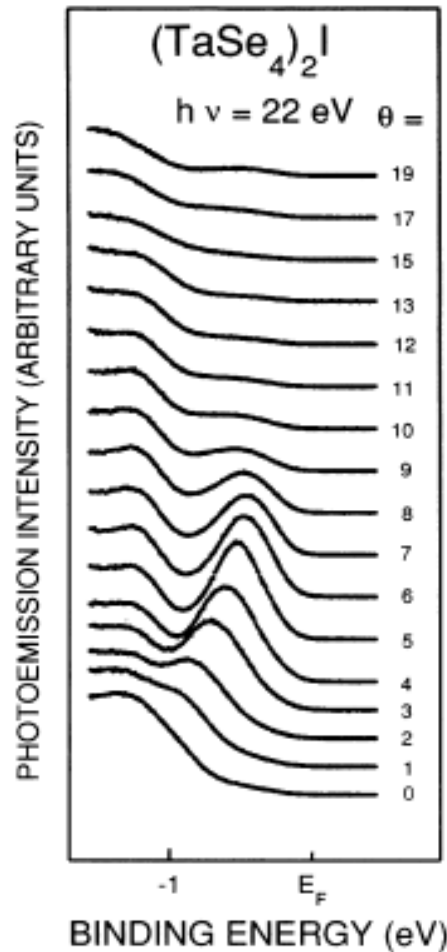


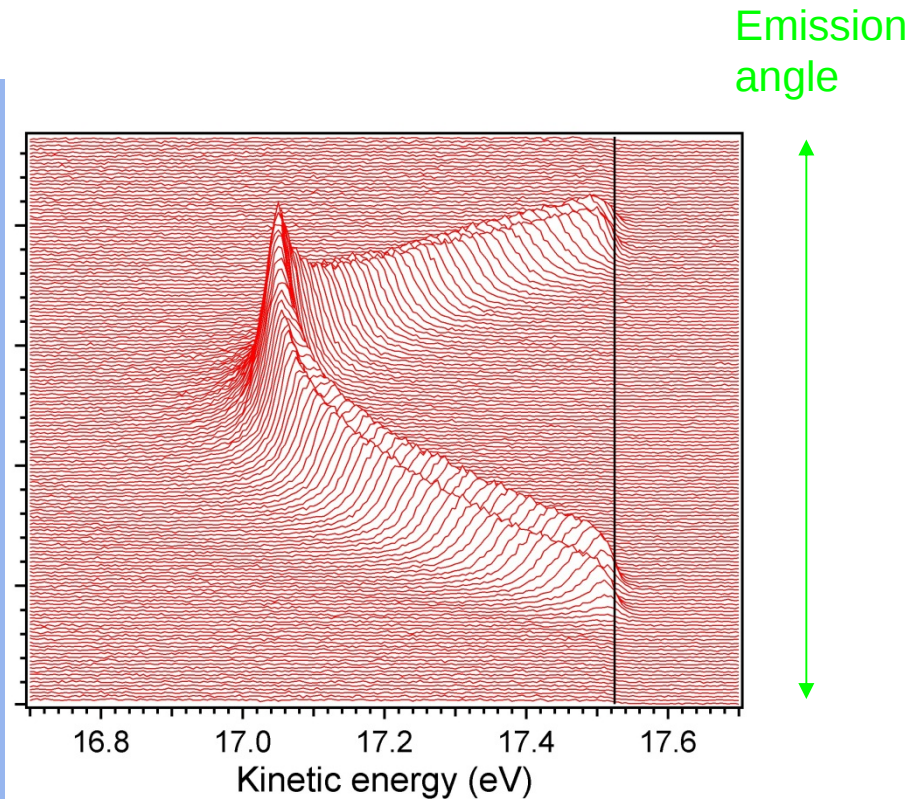
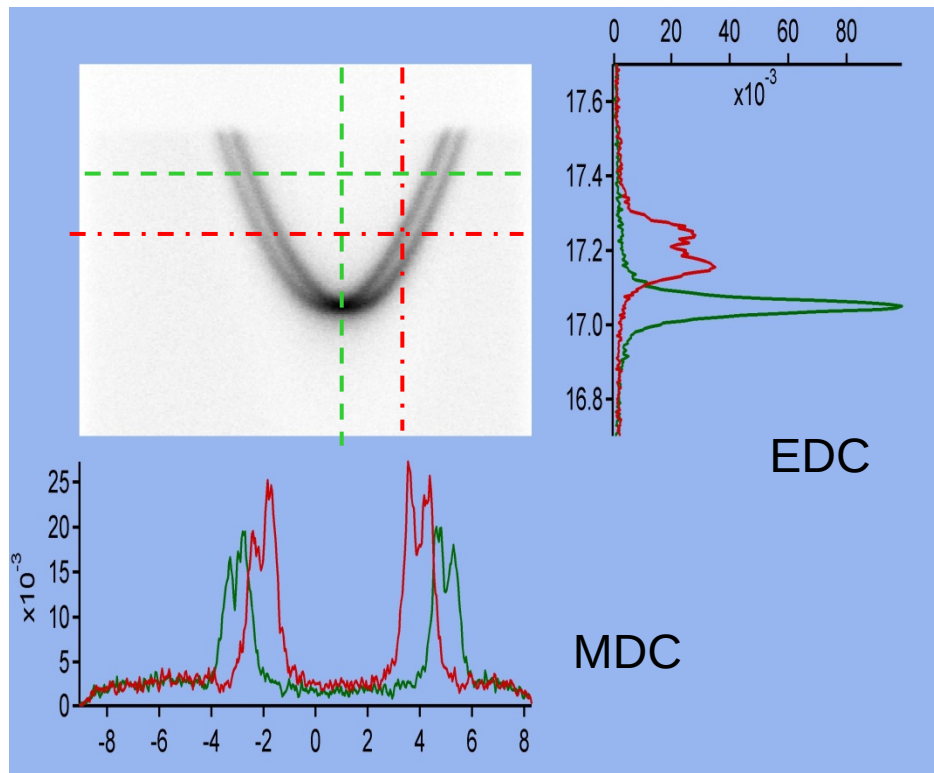
FIG. 1. Angle-resolved photoemission spectra taken using 22-eV photon energy, at room temperature, for photon electric field (a) parallel and (b) perpendicular to the conducting axis. The emission angle is along the conducting axis, with the surface normal defined as 0°.

Now a 2-D detector with $\pm 30^\circ$ and 0.1° angular resolution can be obtained.

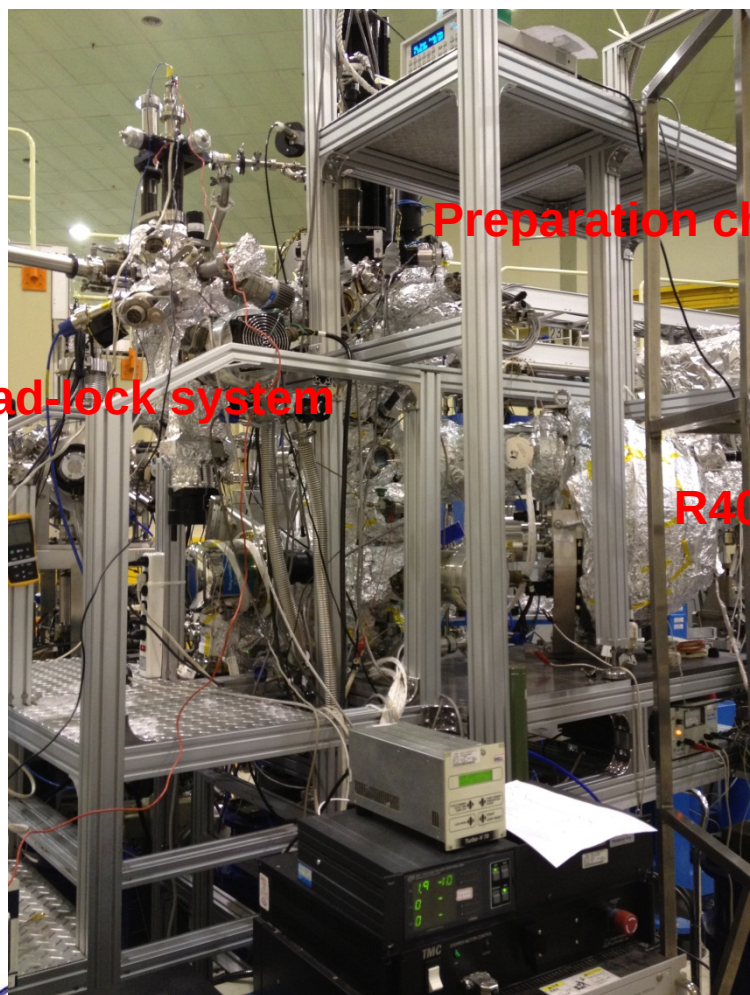
FIG. 1. A series of high-energy-resolution angle-resolved photoemission spectra, taken along the direction of the sample and for different values of the azimuthal angle.

Typical Experimental Result

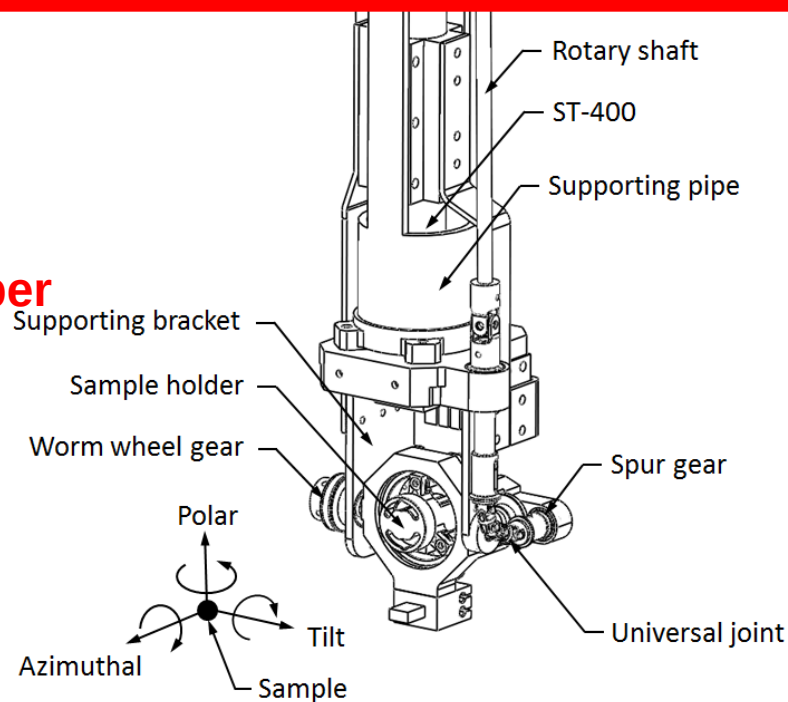
Accumulate spectra of Rashba effect on Au(111) as the angle is scanned



Current status of ARPES end station



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Base pressure : 4.5×10^{-11} torr

Sample Preparation: *in-situ* cleave, MBE growth

Lowest temperature range : 10 K

Manipulator : 6-axis motorized manipulator

Scienta R4000 analyzer, LEED, RHEED,
Sputtering, Load-lock system

Probe the electronic structure of materials

- Angle-resolved photoemission spectroscopy (ARPES) is the most general tool to probe band structure, low-lying excitations or spectral function mapping.
- Scientific topics for current users :
 - Molecular thin film/metal systems
 - Metal/semiconductor systems
 - Cuprates and complex oxides
 - Graphene based materials
 - Topological insulators
 - Iron-based superconductors



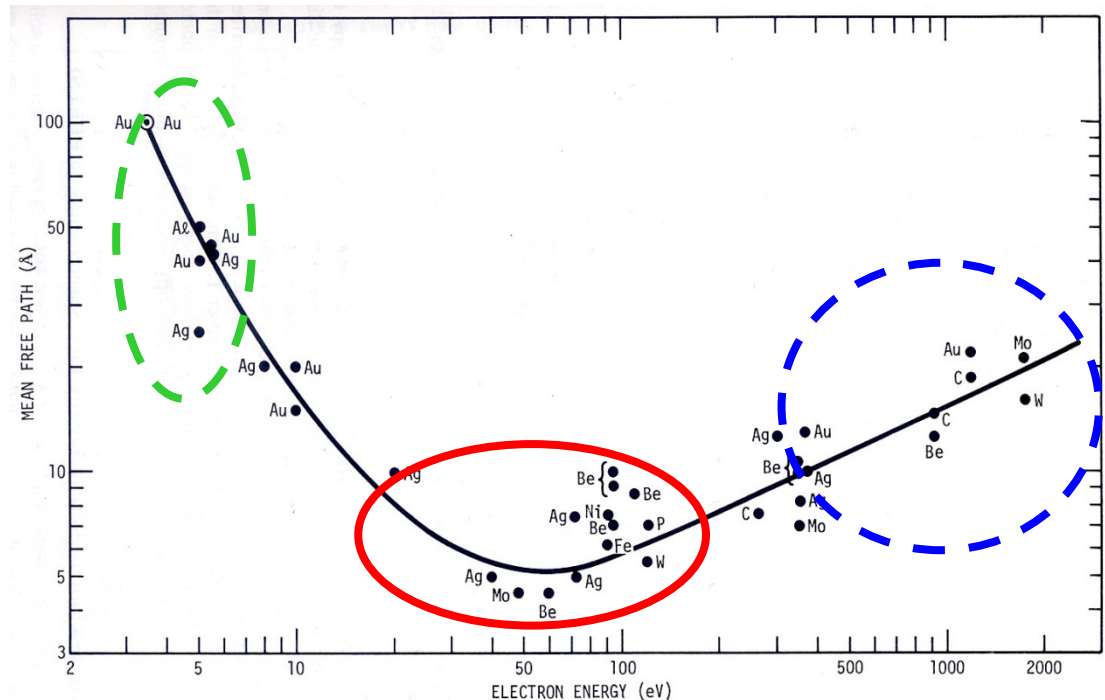
Electron Escape Depth : Surface Sensitivity

Why are electrons
so useful as probes
of surfaces?

Or

Not so useful for
studying bulk
properties !!

Minimum due to electron-electron scattering,
mainly plasmons
PES is a surface sensitive technique! (requires
UHV)
High energy photoemission: several keV to
increase bulk sensitivity



The requirement of ARPES

- UHV environment : better than 1×10^{-10} Torr
- Single crystals or *in-situ* growth thin films
- Conductors or semiconductors
- Tunable photon energies

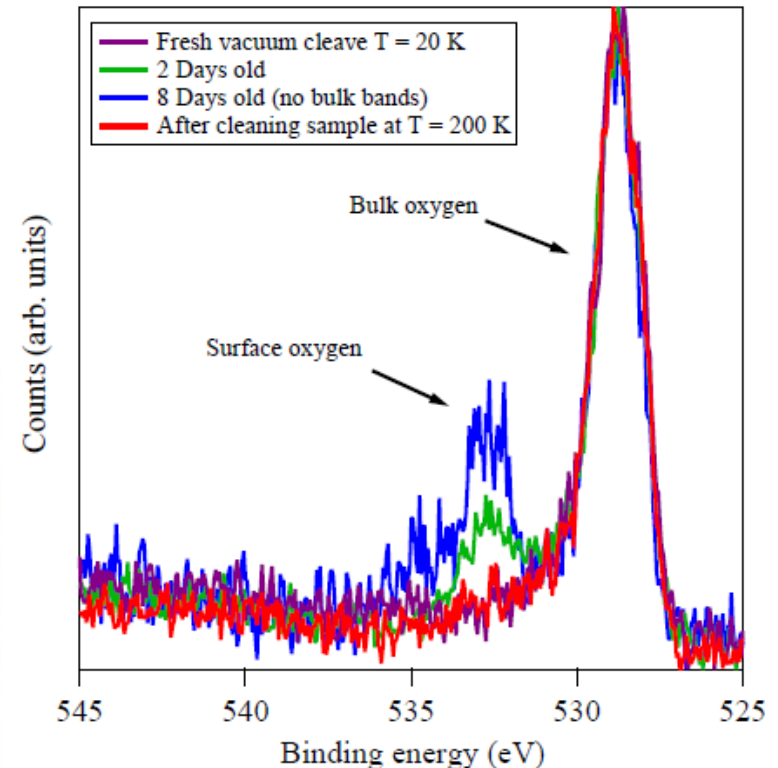
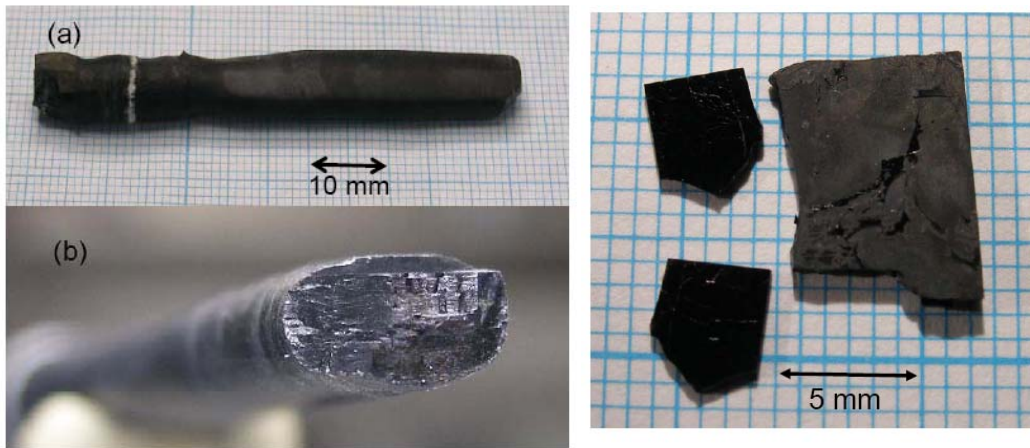
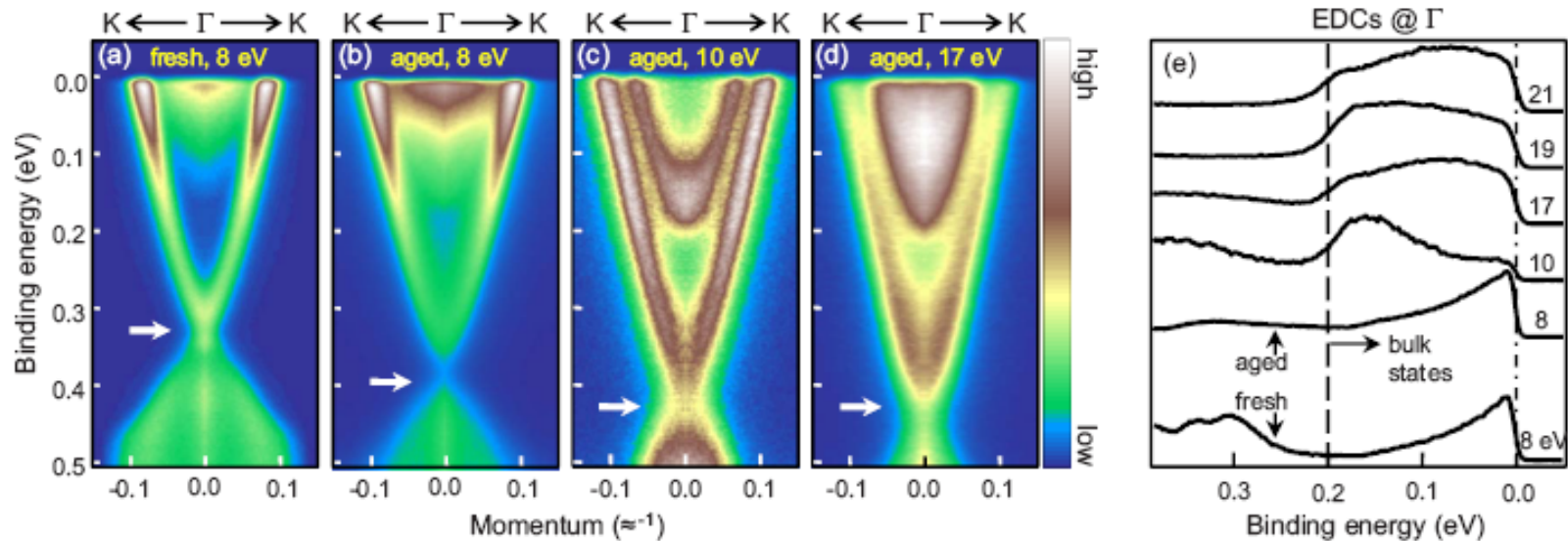


Figure 5.2: (color) The oxygen 1s peaks from Bi2212 at different times after the cleave. A constant background was subtracted from each spectrum to allow direct comparison. The peak derived from bulk oxygen is stable over time, while the surface oxygen peak grows as more oxygen sticks to the cold surface.

Impurity doping on topological insulators

Base pressure : 1×10^{-10} Torr

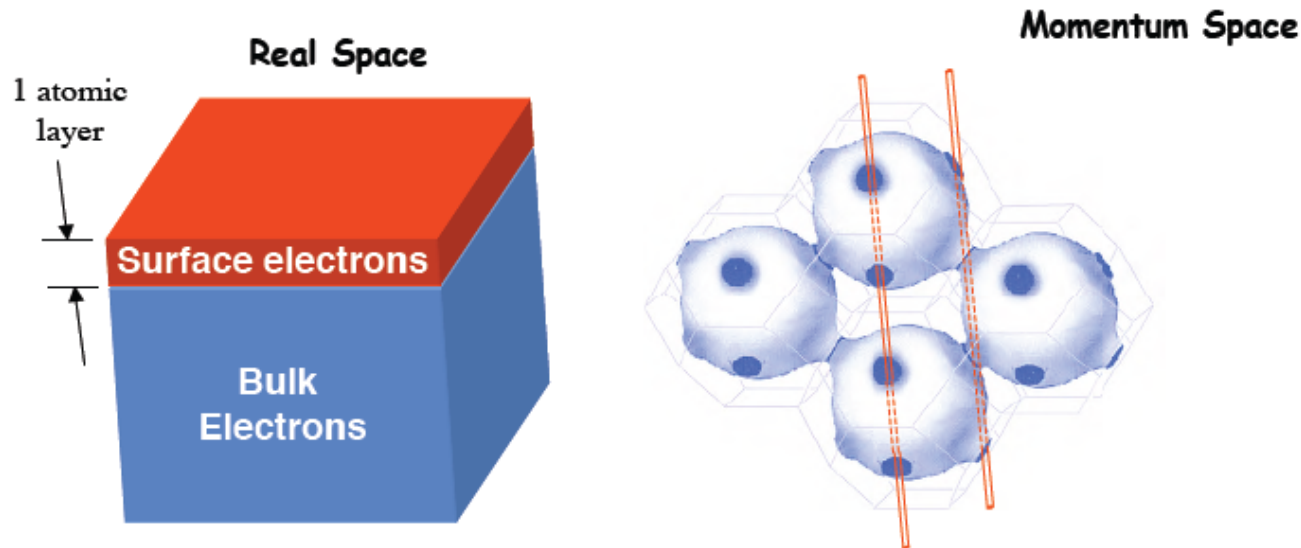
Bi_2Se_3 single crystal



Single crystals or *in-situ* growth well-ordered thin films are good candidates for ARPES measurement



Surface state



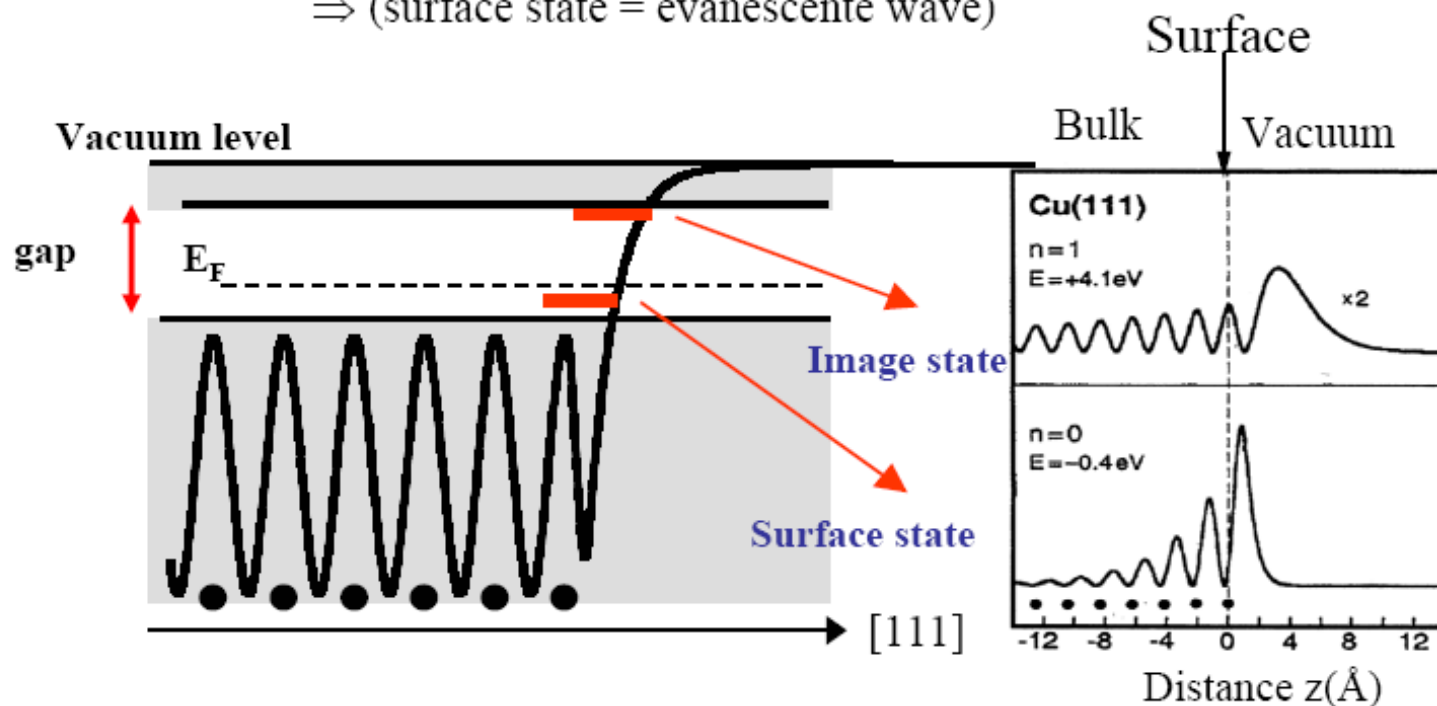
Surface states are highly localized in real space, therefore completely delocalized in k-space along k_z .
– NO DISPERSION OF SURFACE STATES in k_z direction



- Surface = Breakdown of the translational symmetry

⇒ Peculiar solution in the gap with a complex wave vector $k_{[111]}$

⇒ (surface state = evanescent wave)

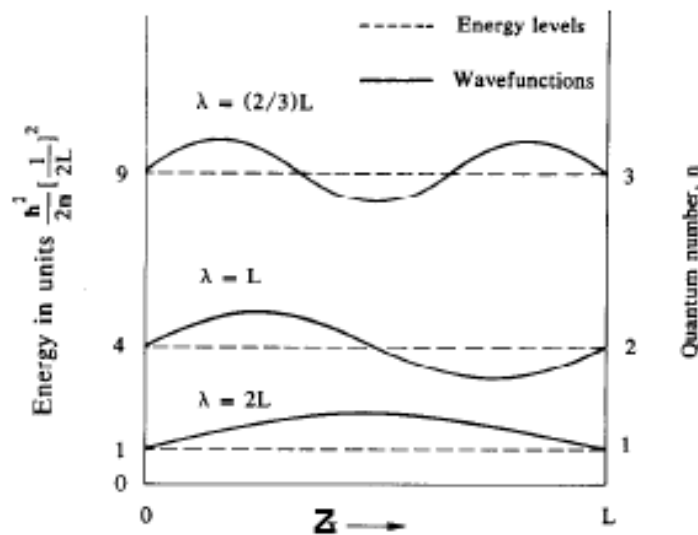


→ localisation of the electronic density at the surface

Surf. State is very sensitive to any structural modification



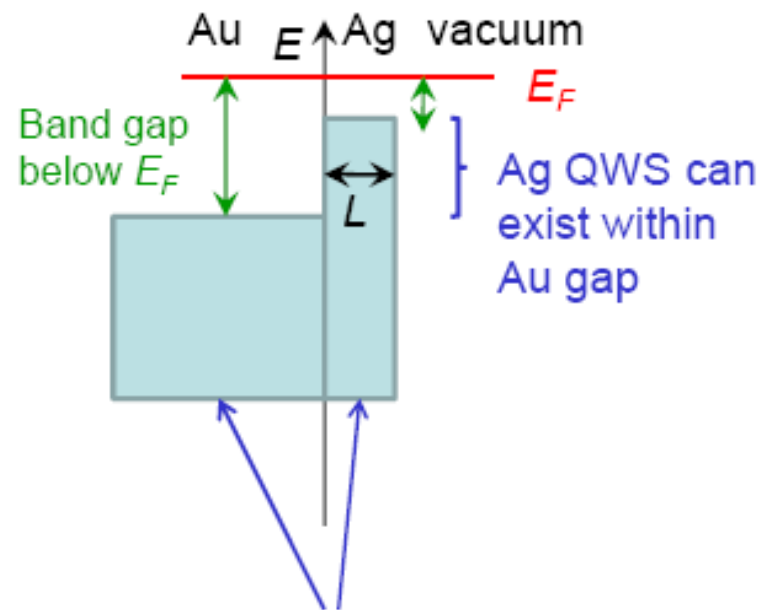
Quantum well states



Quantized discretely along z -direction
Energy levels depend on film thickness L

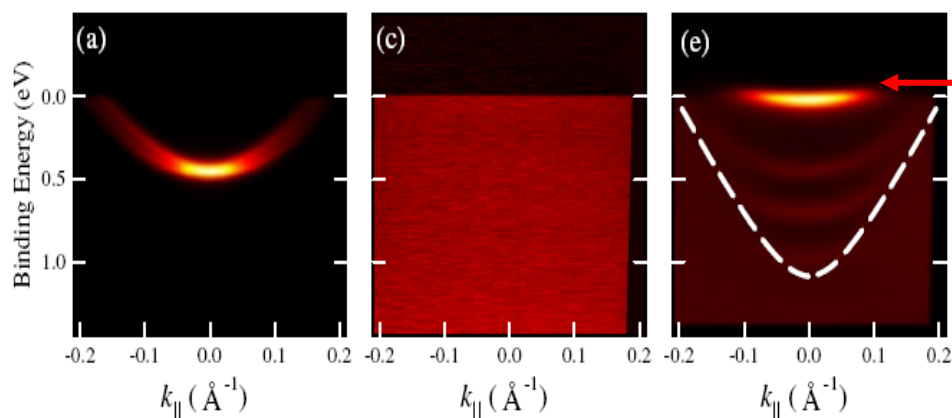
Nearly free electron like in xy -plane

Ag(111) thin films epitaxially grown on Au(111) substrate



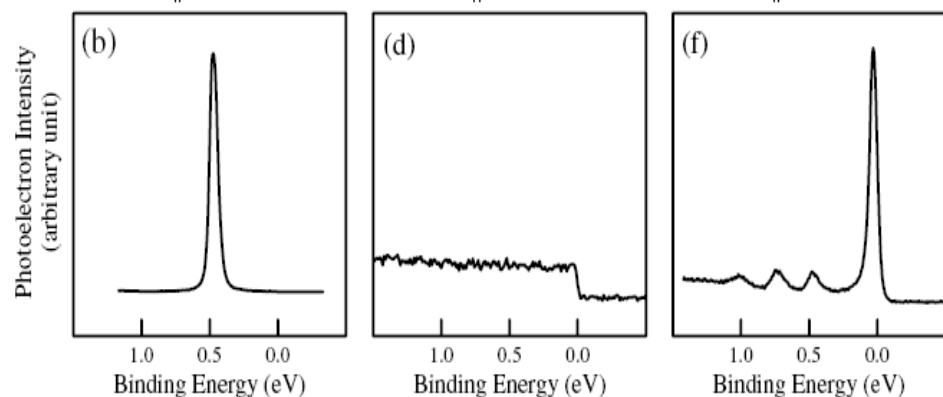
Bulk projected bands along ΓL of Au and Ag, respectively

Absolute coverage of thin films : Ag/Au(111) system



Ag S.S

Ag QWs



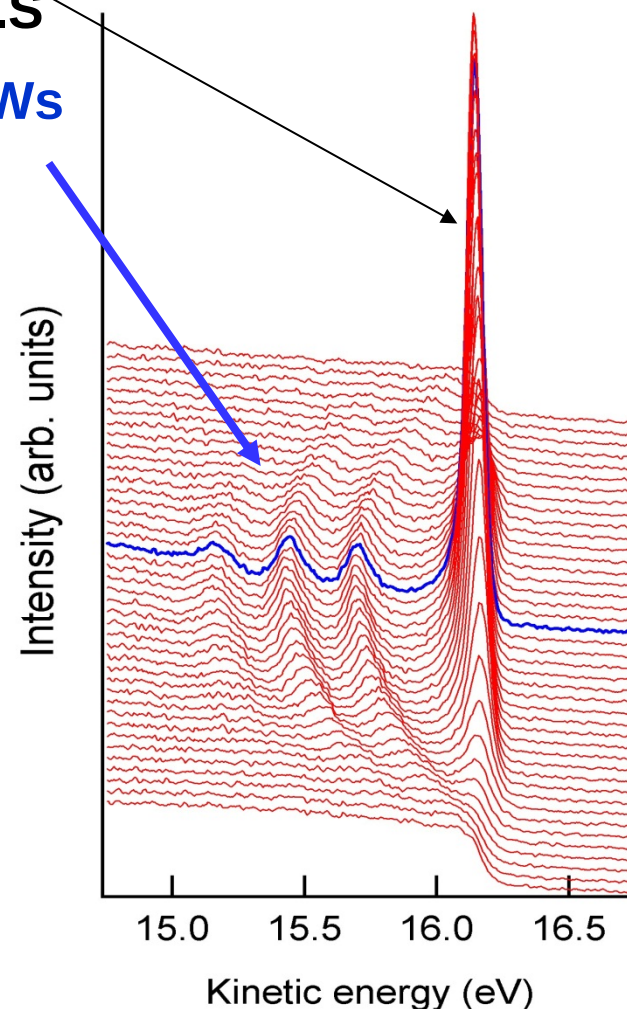
Clean Au(111)^{LT}
deposit

Anneal to near
RT

Ag/Au(111)

$k_{\parallel} = 0$ normal emission

EDCs



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D. A. Luh et. al., PRL (2008)

Dynamically monitor the thin film growth mechanism

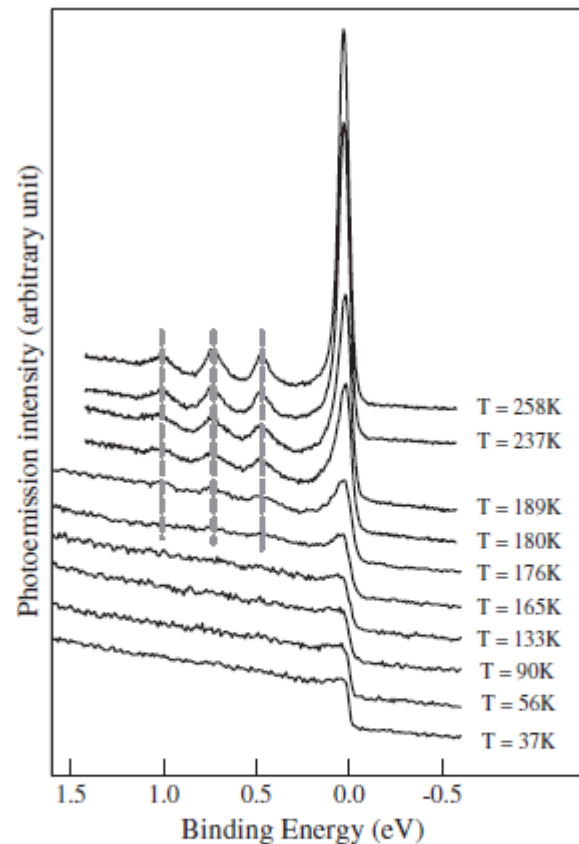
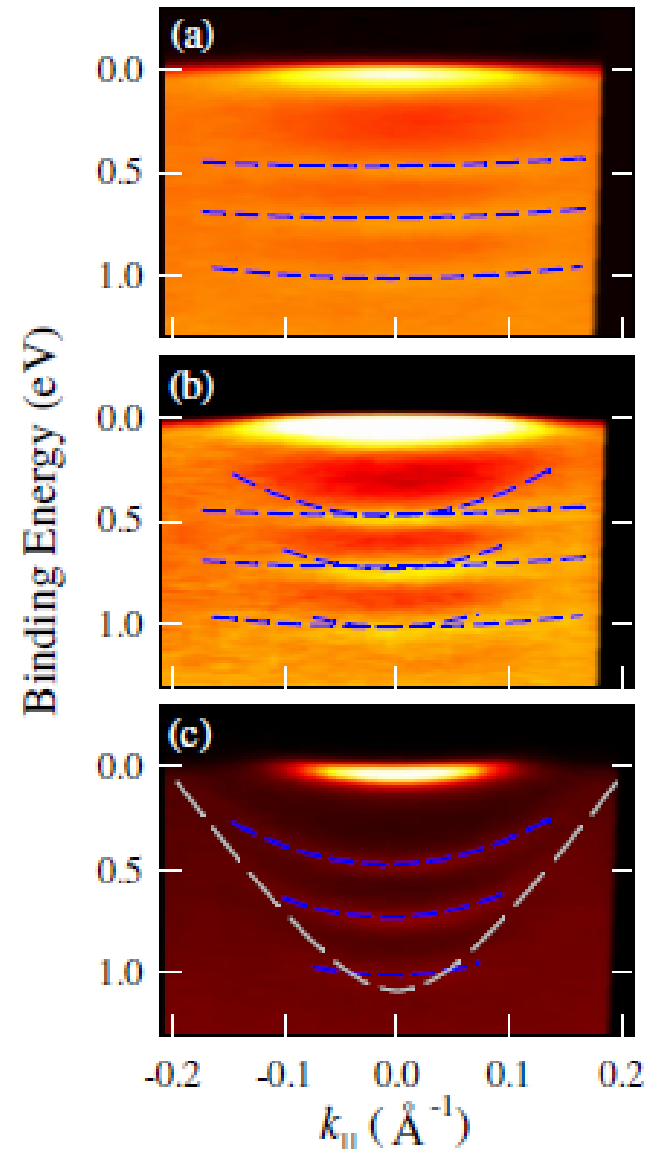
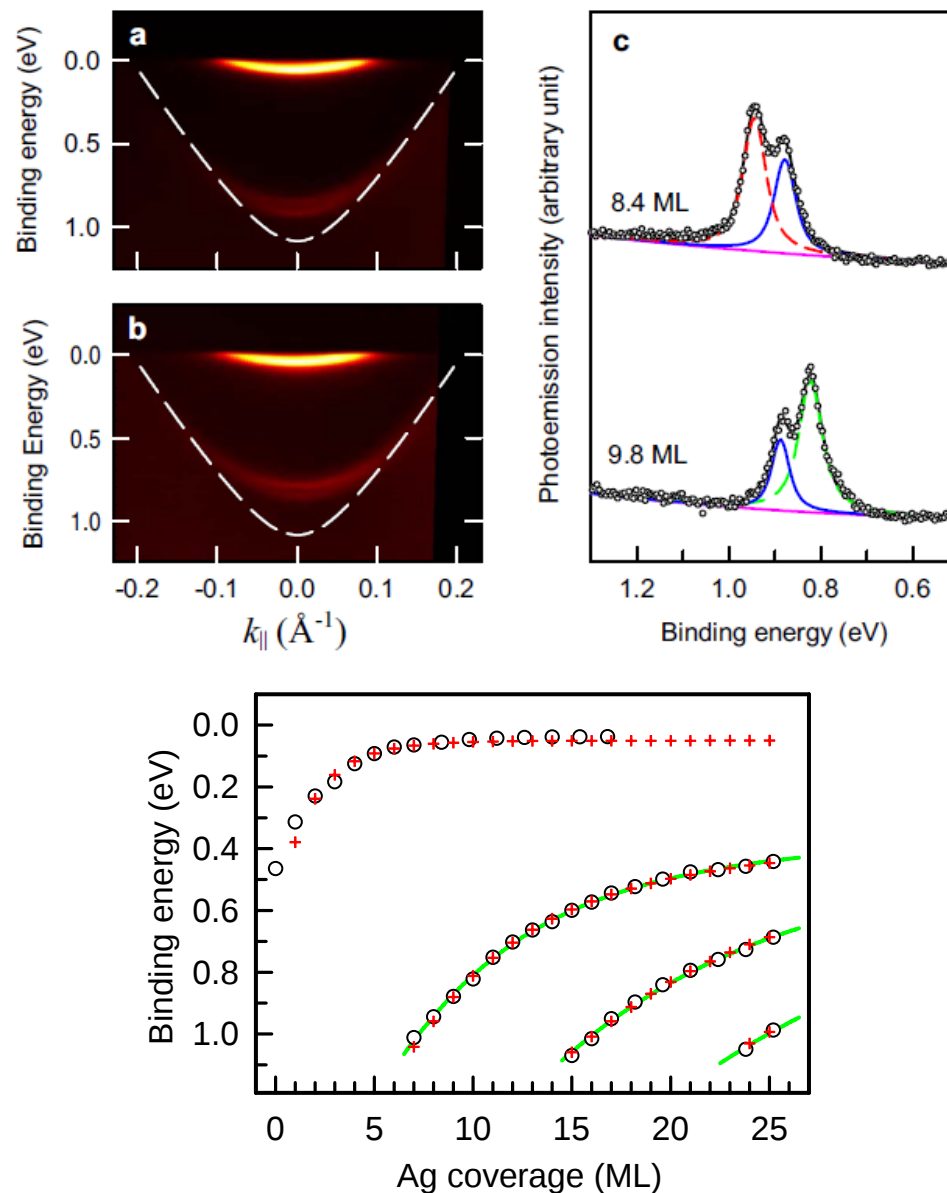
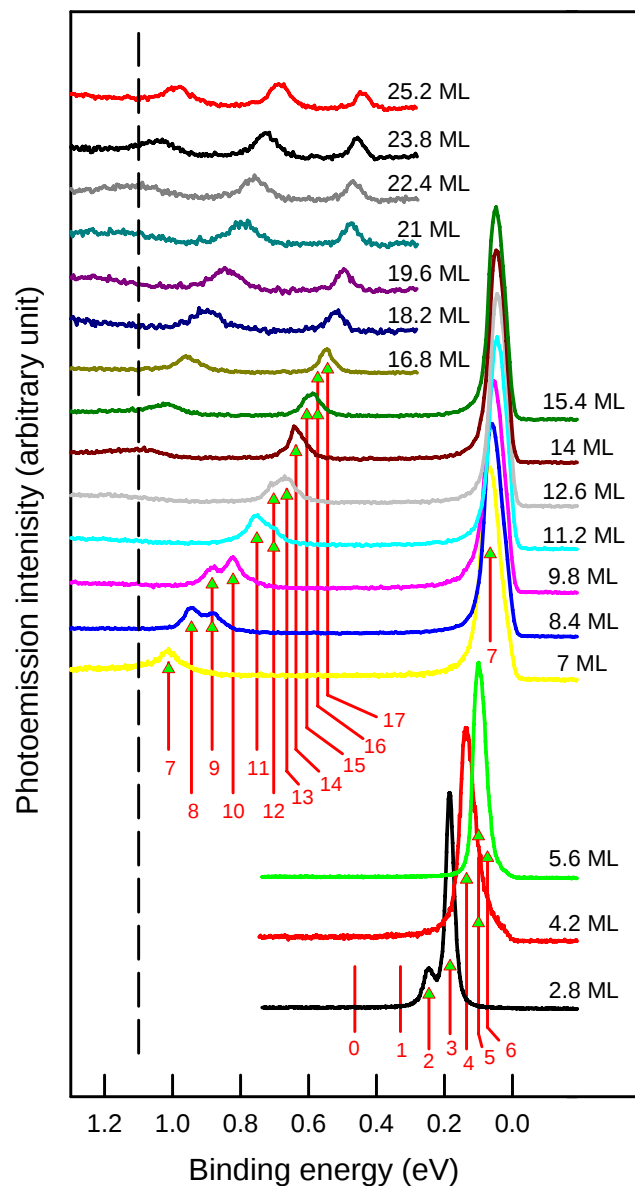


FIG. 2. Energy distribution curves of normal emission from Ag (22 ML) on Au(111) annealed at the indicated temperatures; intensities have been scaled variously for stacking presentation.

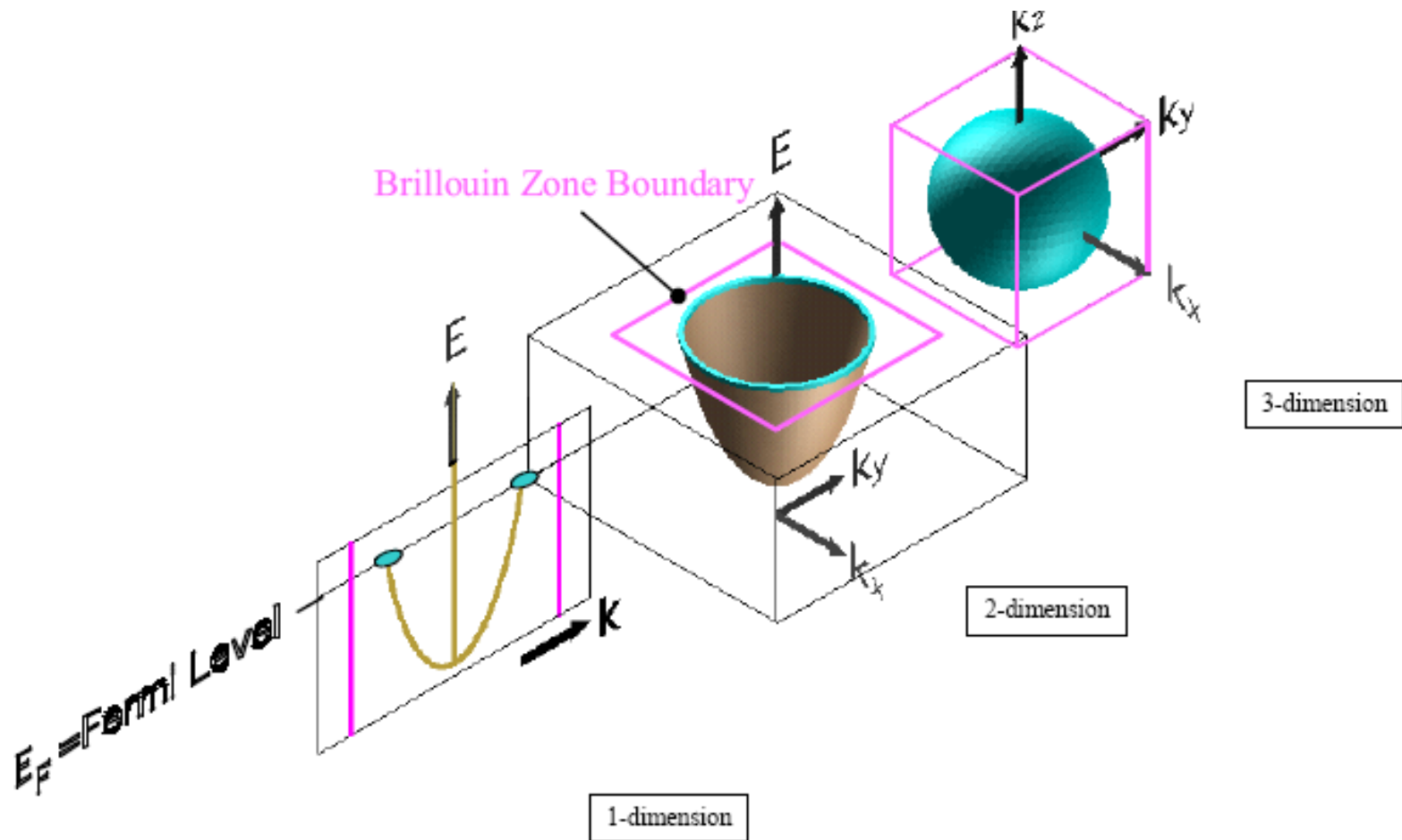




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C.-M. Cheng et al., *APL* (2008)
C.-M. Cheng et al., *J. Phys. D: Appl. Phys.* (2008)
D.-A. Luh et al., *PRB* (2008)

Fermi Surface

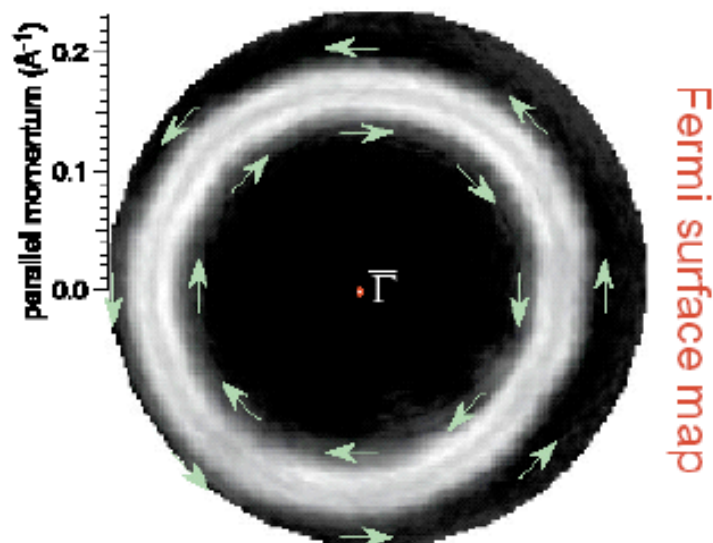
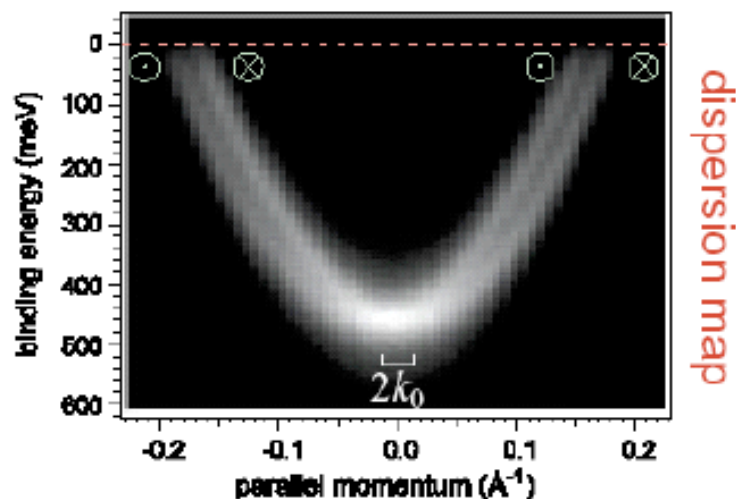


Surface state

The Shockley surface state on Au(111)

spin-integrated photoemission at $h\nu = 21.1$ eV, $T = 160$ K

instrumental resolution
 $\Delta E = 25$ meV, $\Delta\theta = 0.5^\circ$ (FWHM)



$$2k_0 = 0.026 \text{ \AA}^{-1} \quad E_B = 470 \text{ meV} \quad k_F = 0.173 \text{ \AA}^{-1} \pm k_0 \quad m^* = 0.24 m_e$$



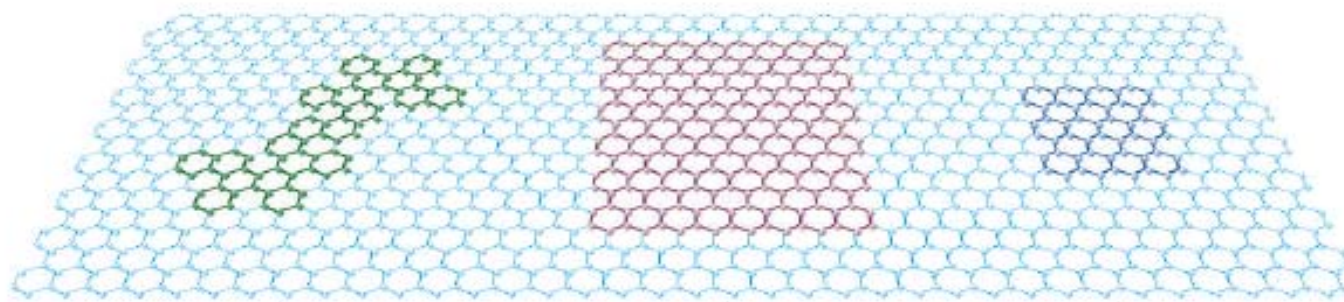
The electronic structure of graphene



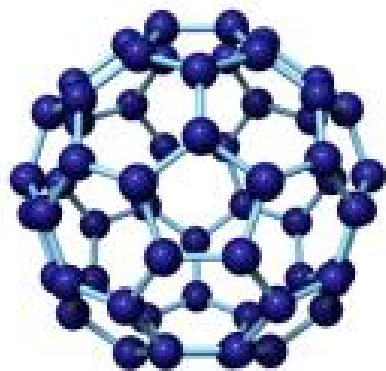
Graphene is the mother of them all !

Very good conductors

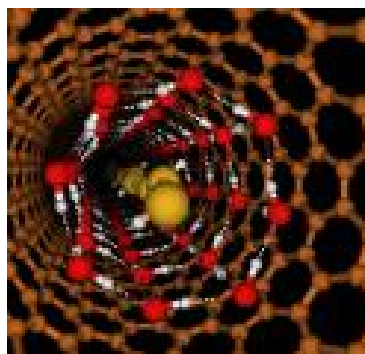
Extremely thin and resistant



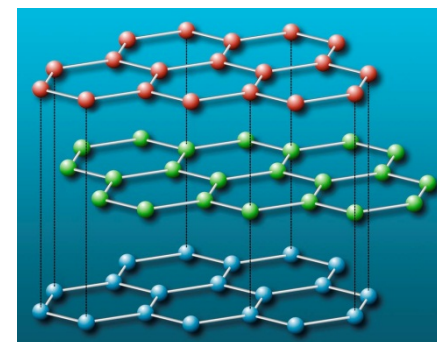
wrapped



Rolled



stacked

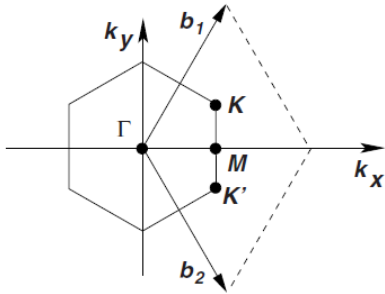


Why graphene

- The strictly two-dimensional material
 - *Exceptionally high crystal and electronic quality*
- Unusual electronic spectrum
 - *New paradigm of 'relativity' condensed-matter physics*
- Graphene-based electronics : new candidate material to take over from Si
 - *High mobility, high carrier density, high v_F*
 - *Tunable gap by electrical field : Field-effect transistor (FET), Single-electron-transistor (SET)*
 - *Superconducting field effect transistor and Spin valve, Composite material for electric battery, hydrogen storage material*

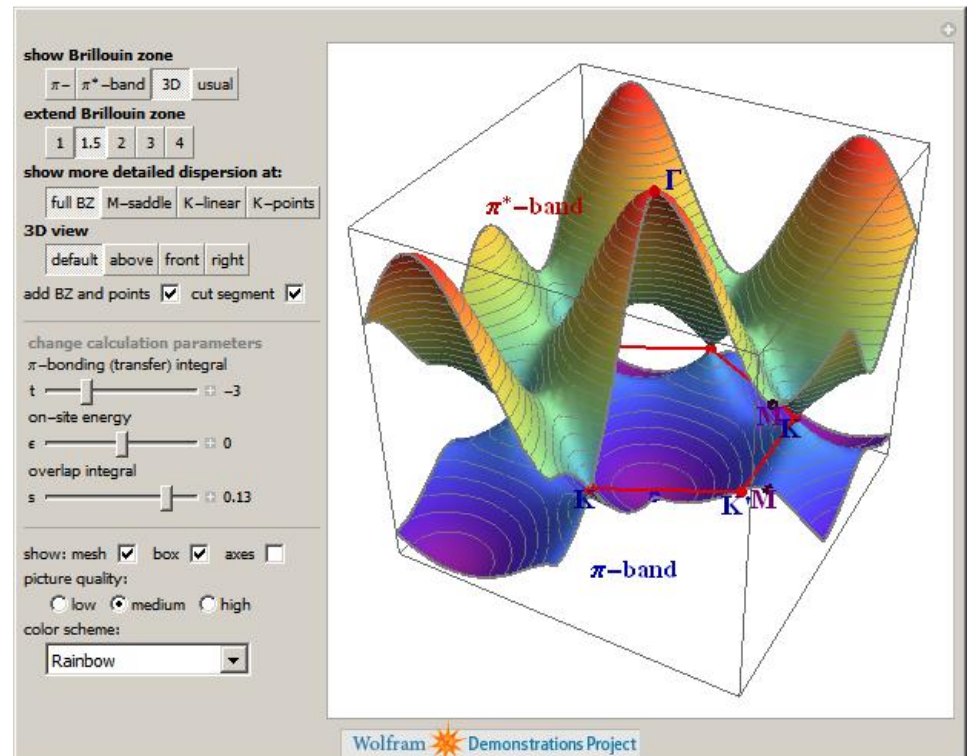
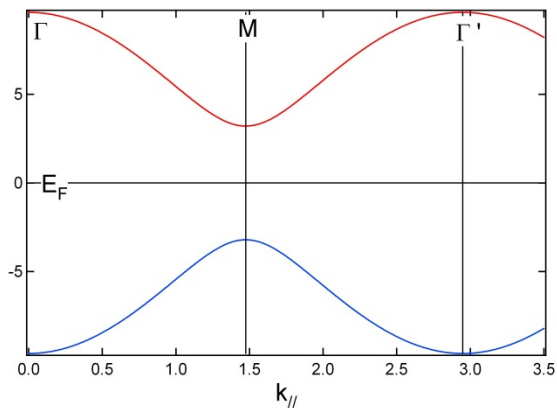
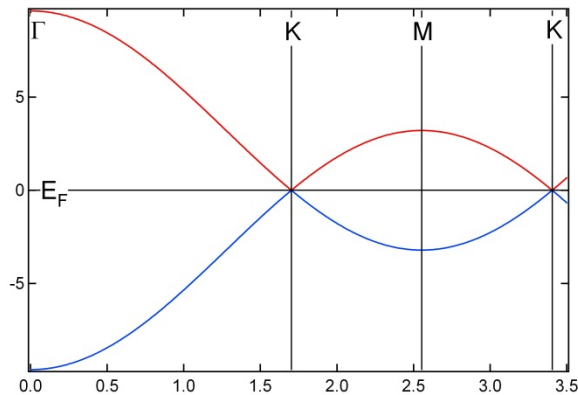


Pure 2D material : graphene



$$\mathbf{b}_1 = \frac{2\pi}{3a}(1, \sqrt{3}), \quad \mathbf{b}_2 = \frac{2\pi}{3a}(1, -\sqrt{3})$$

$$\mathbf{K} = \left(\frac{2\pi}{3a}, \frac{2\pi}{3\sqrt{3}a} \right), \quad \mathbf{K}' = \left(\frac{2\pi}{3a}, -\frac{2\pi}{3\sqrt{3}a} \right)$$

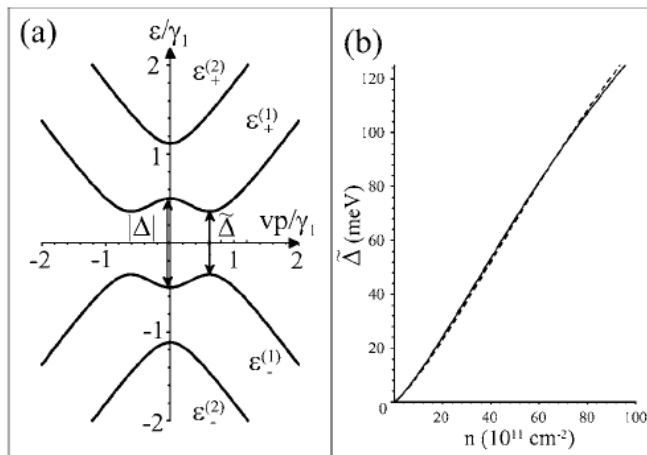


Bilayer graphene : tunable energy gap

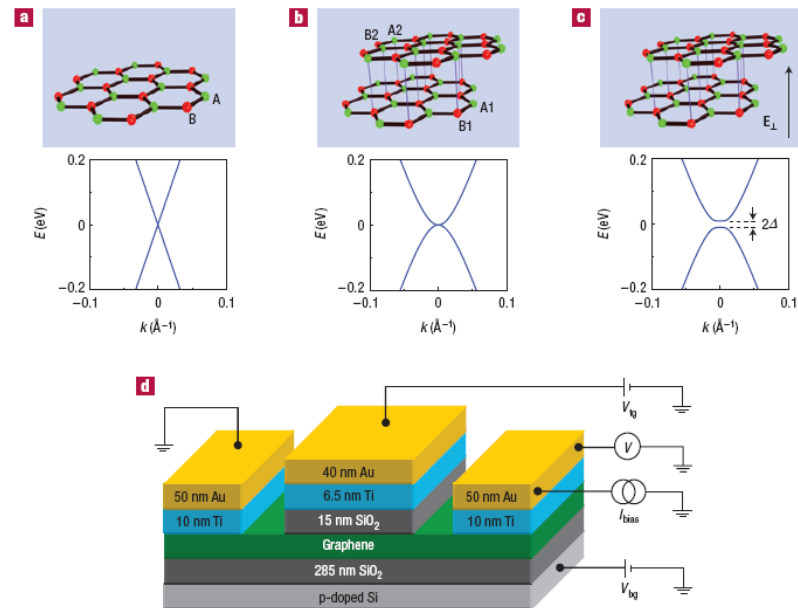
Bilayer graphene

Max. 250 meV by IR detection

Zhang et al., Nature (2009)

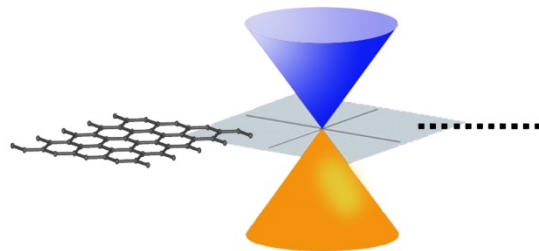


McCann, PRB (2006)



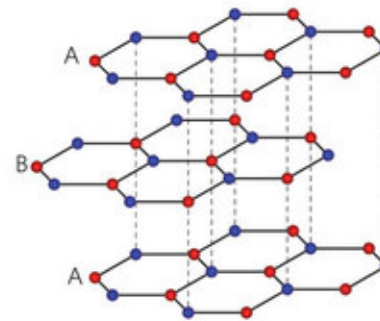
J.B. Ostinga et al., Nature Mat. (2007)



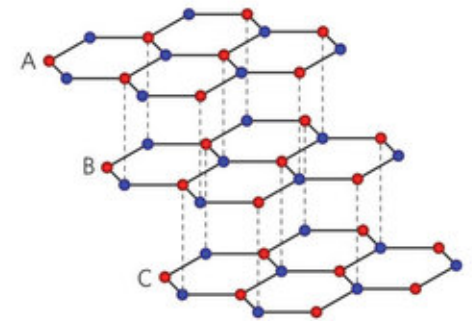


a

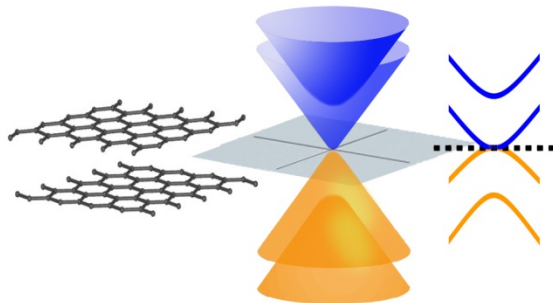
Trilayer graphene



Bernal stacking
(ABA)

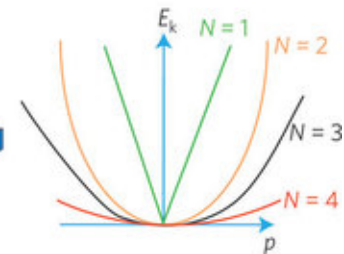
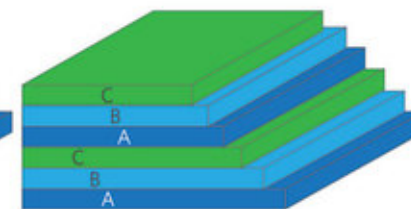
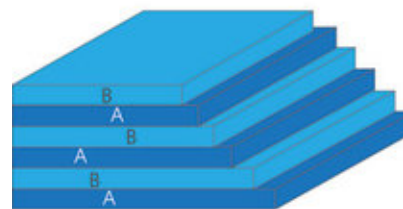


Rhombohedral stacking
(ABC)



b

Multilayer graphene

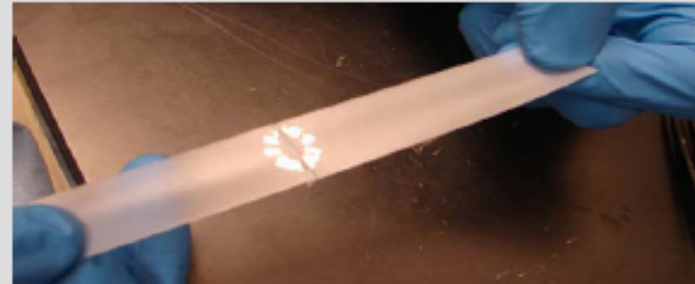
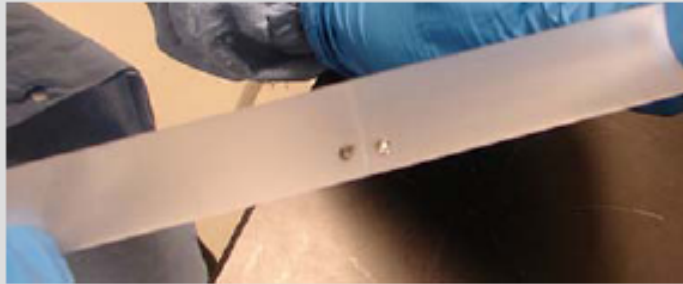


How to prepare graphene

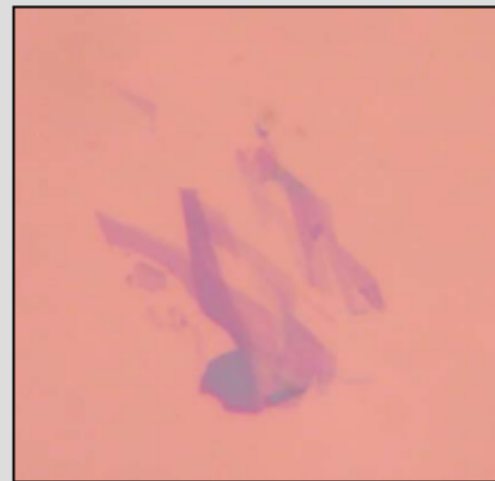
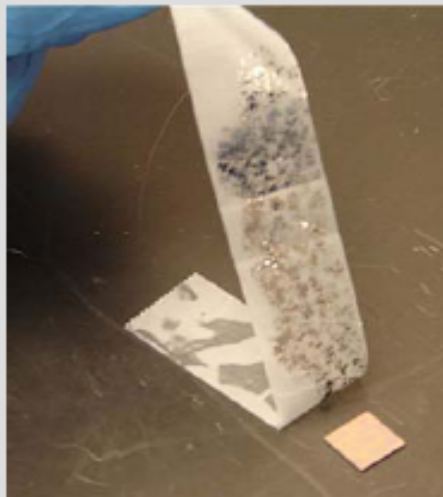


mechanical cleavage

peeling off layers of graphite with a sticky tape



transfer onto substrate



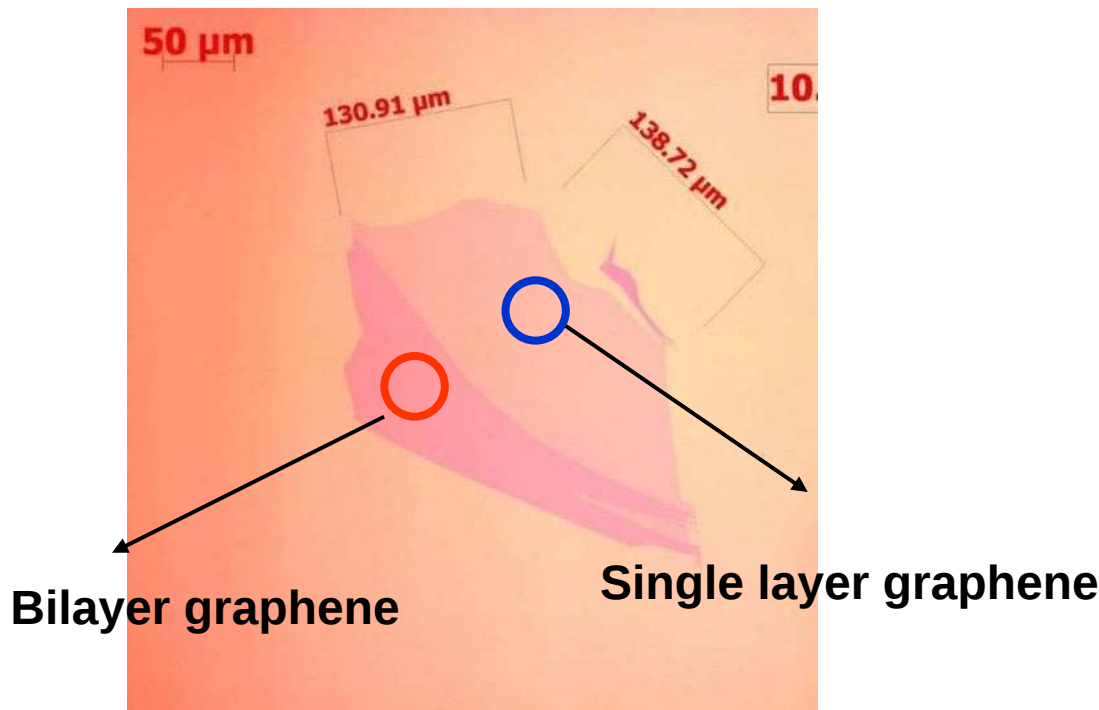
optical microscope image of
resulting flakes



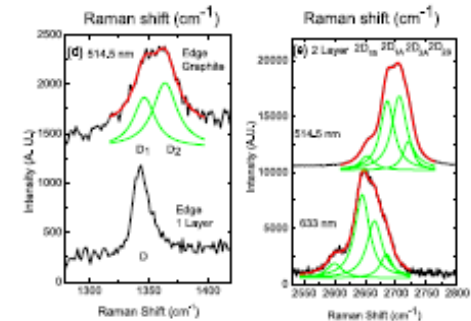
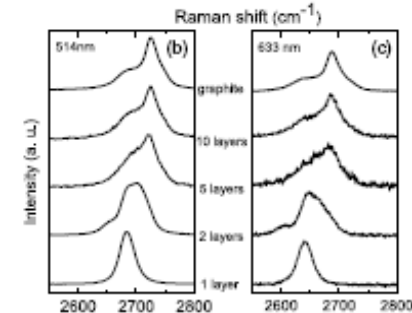
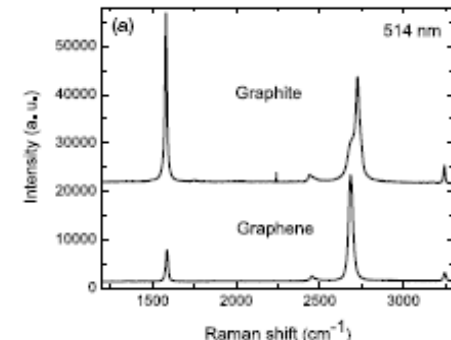
How to distinguish the thickness of graphene

SiO₂(200 nm)/Si

Optical microscopy



Raman spectroscopy



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National Synchrotron Radiation Research Center

Barbaros, NUS, Singapore

A. Ferrari et al. PRL 97,187401 (2006)

CVD for large scale graphene film

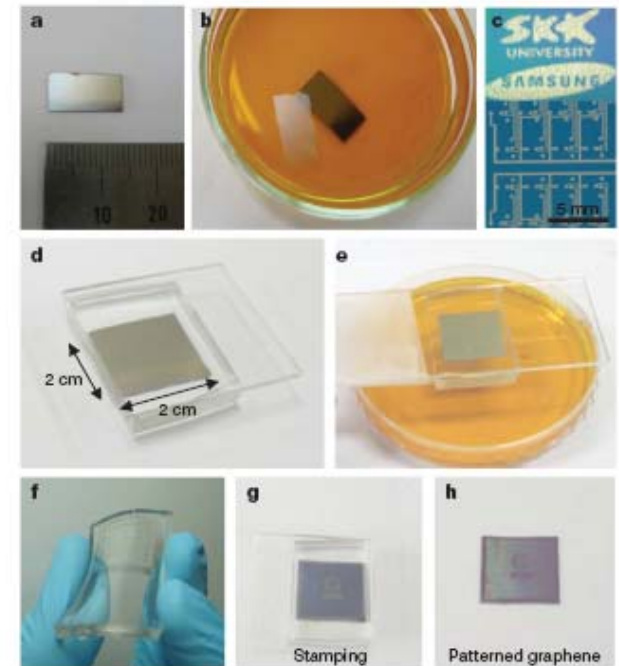
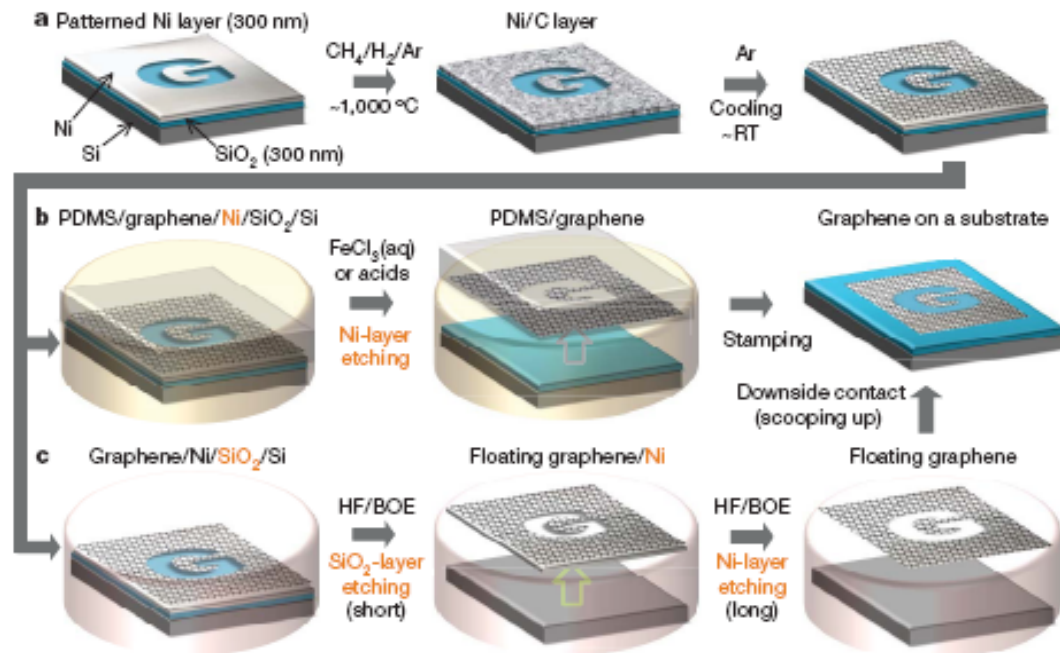
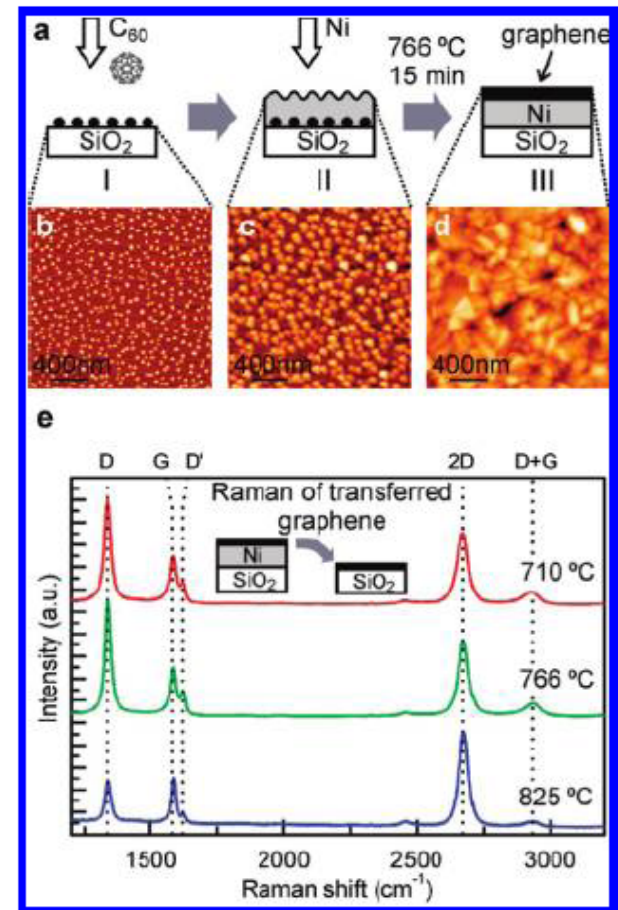
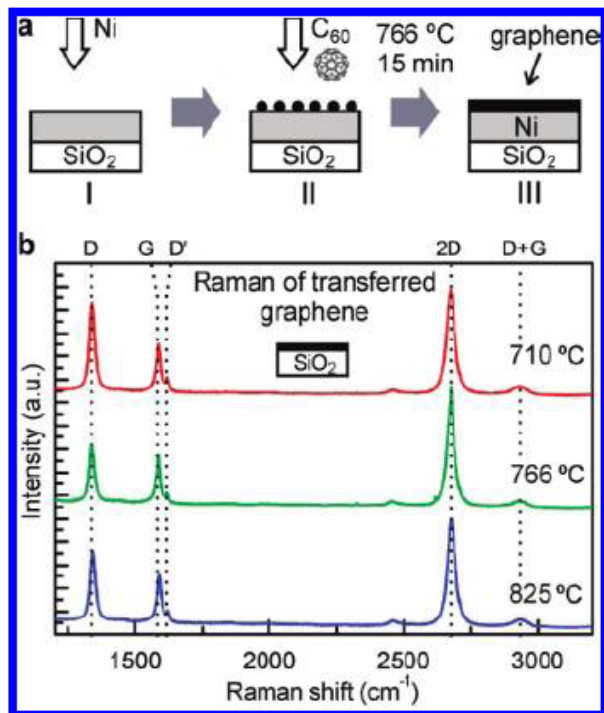
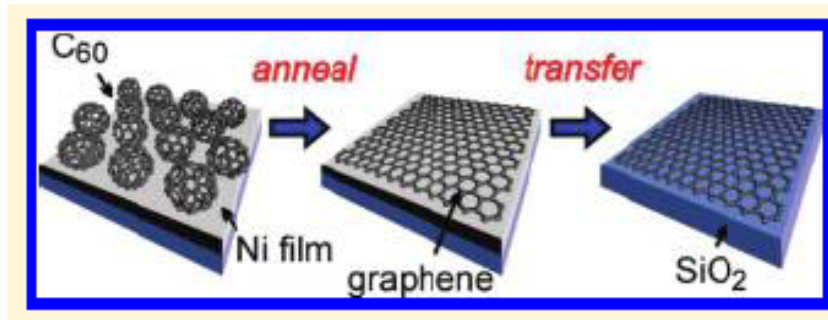


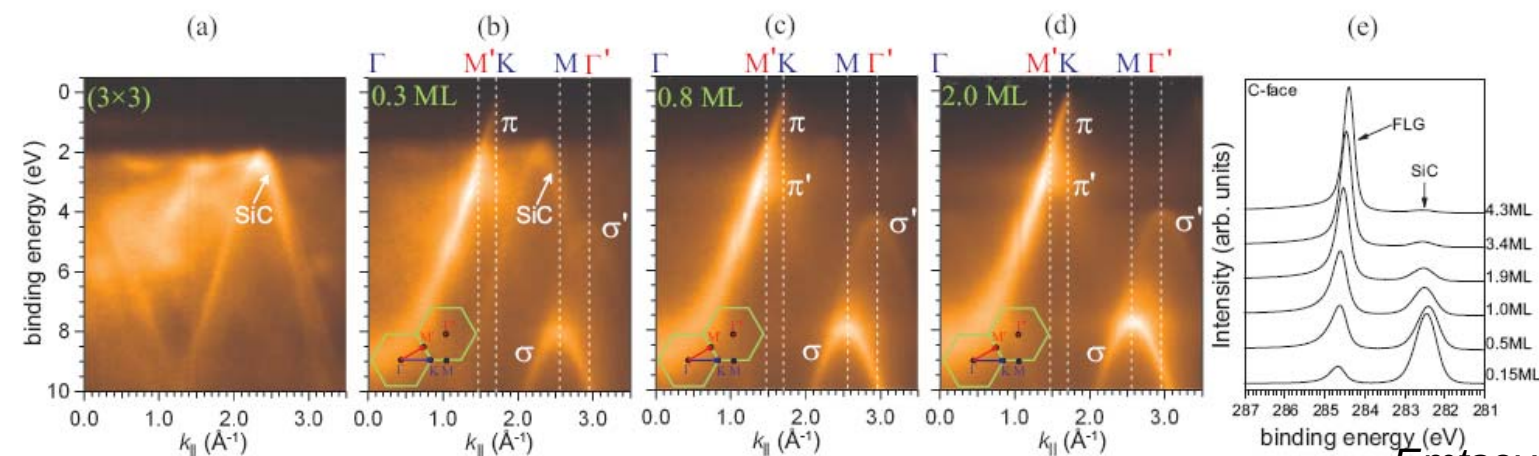
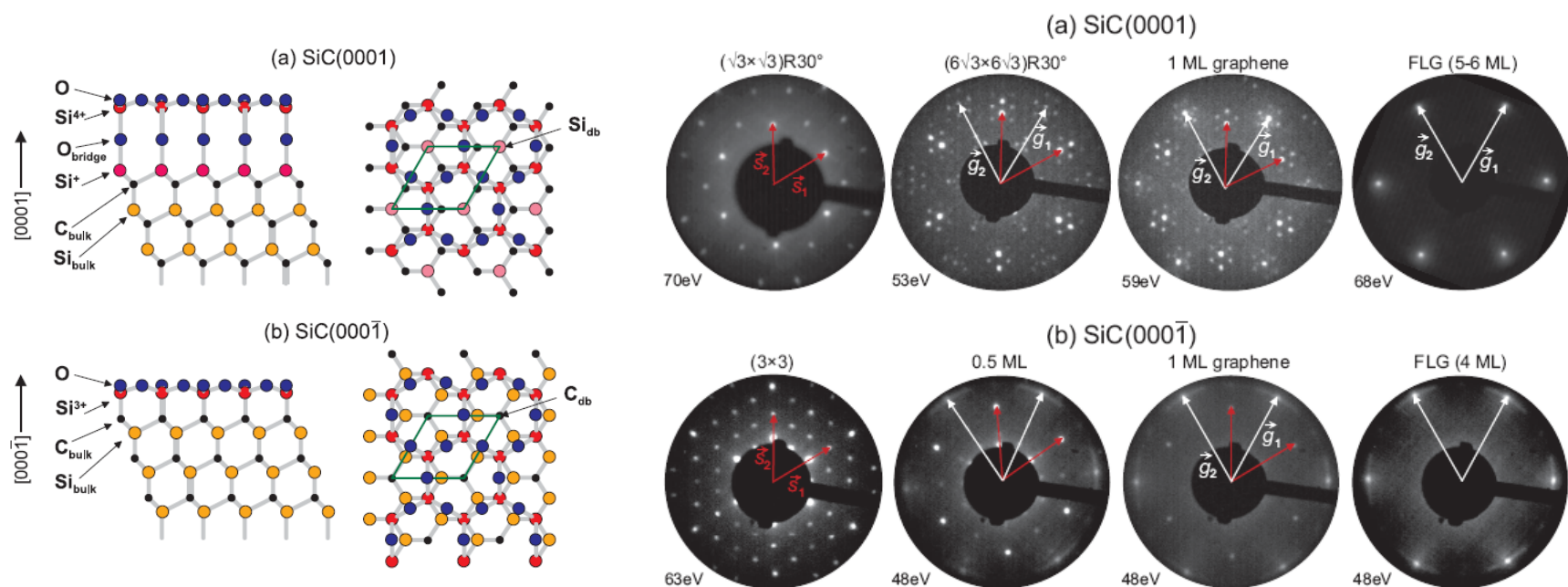
Figure 3 | Transfer processes for large-scale graphene films. a, A



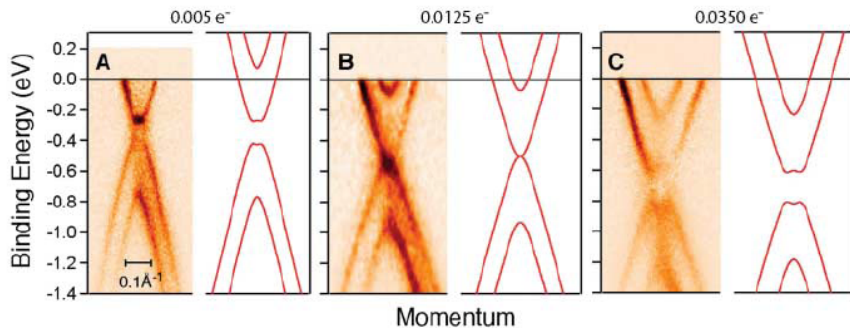
Graphene formation by decomposition of C_{60}



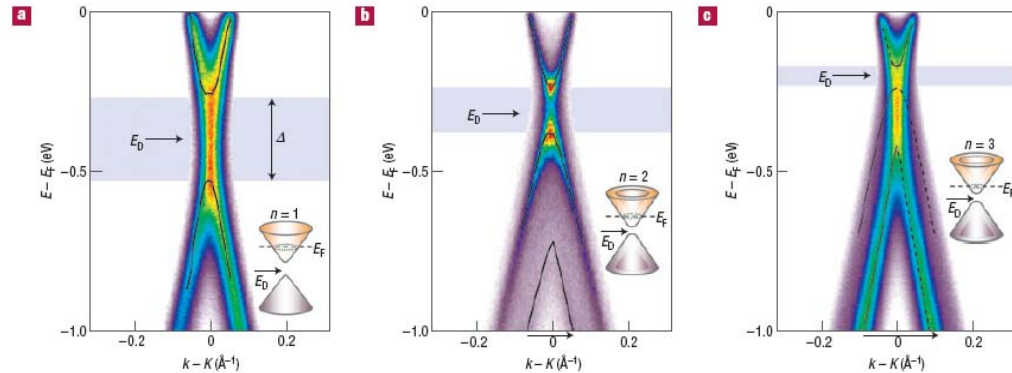
Epitaxial growth graphene on SiC



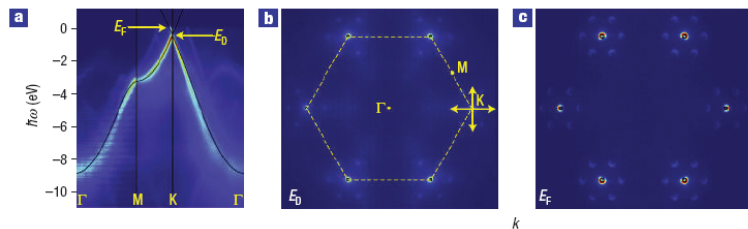
Epitaxial growth graphene on SiC



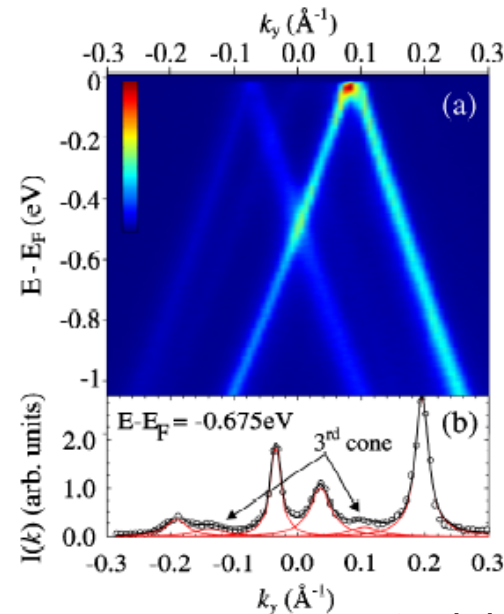
Ohta et al., Science (2007)



Zhou et al., Nat. Mat. 6,770 (2008)



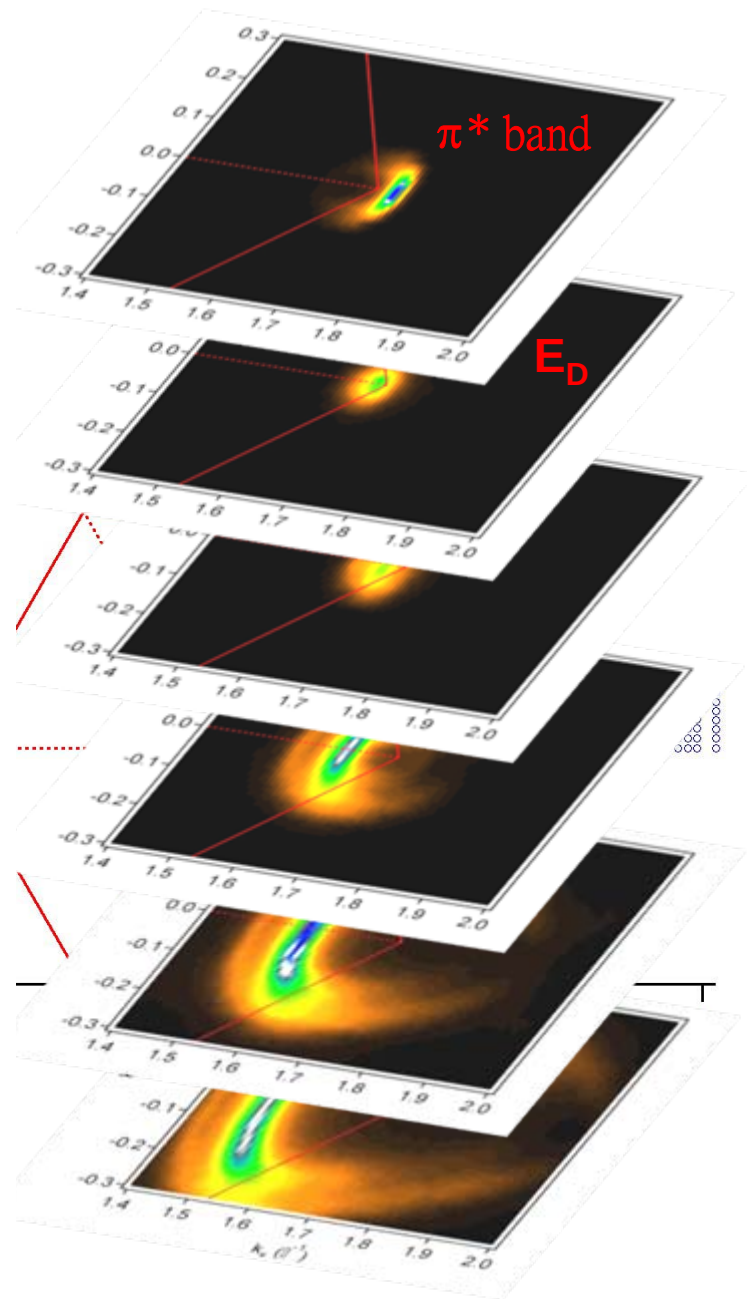
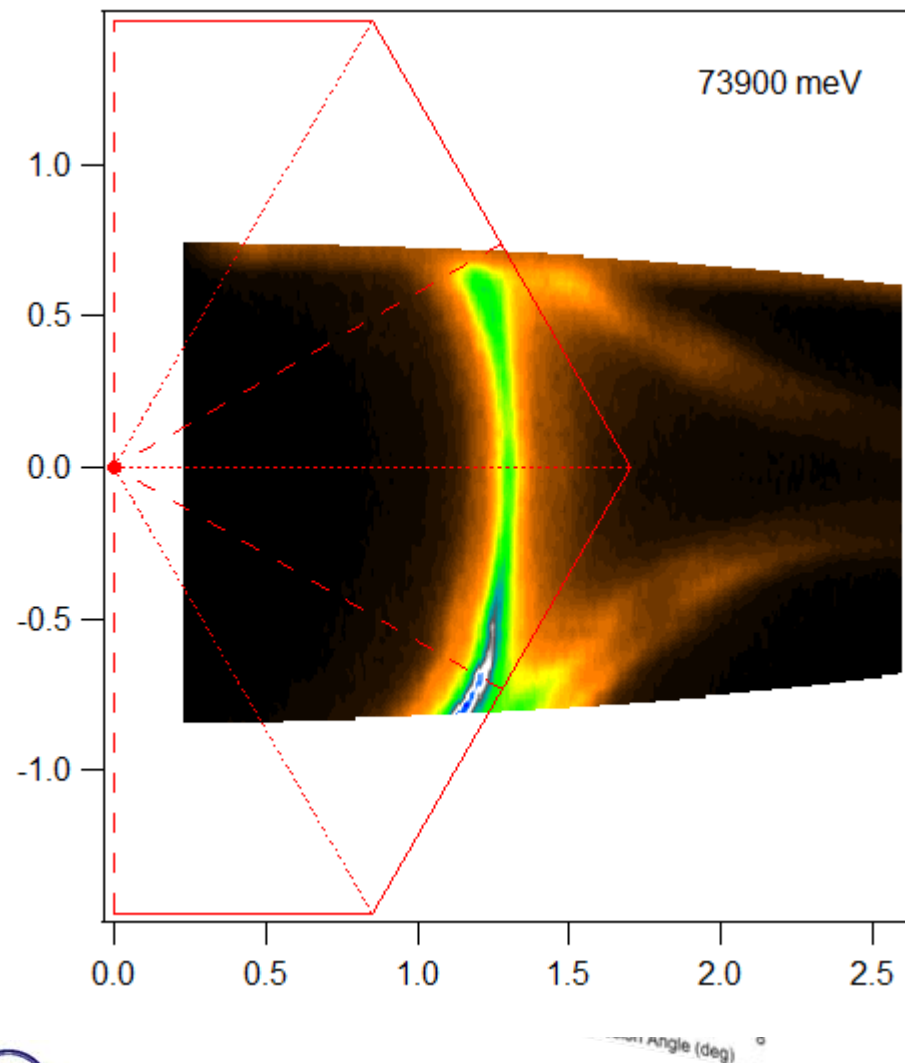
Bostwick et al., Nat. Phys. 3,36 (2007)



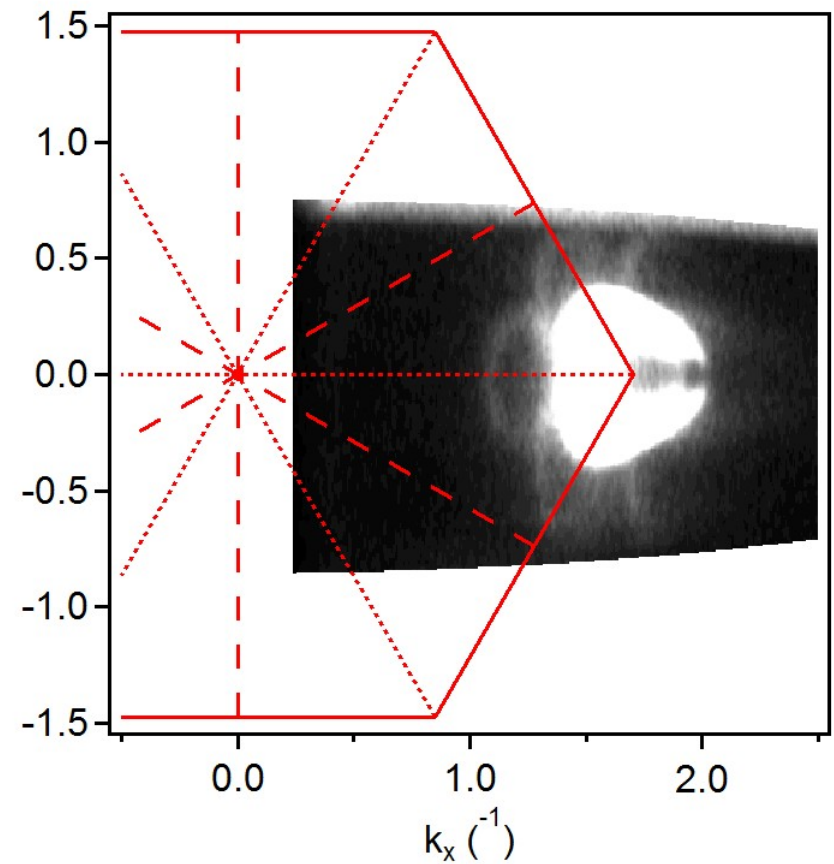
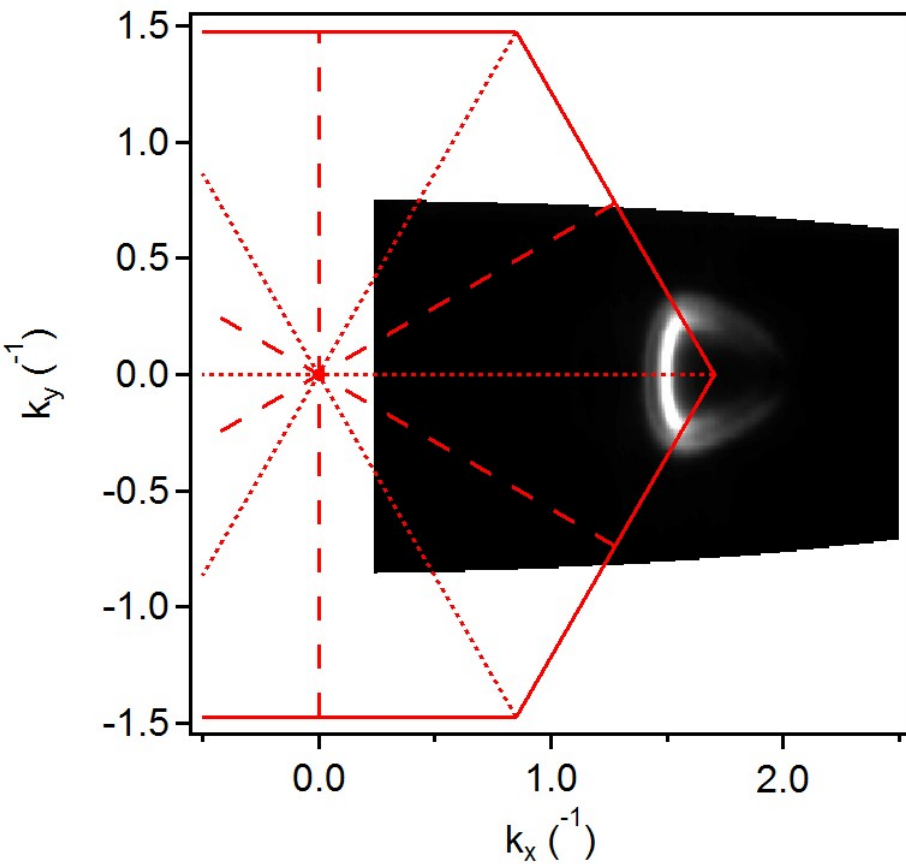
6H-SiC(000 -1)

Sprinkle et al., PRL (2009)

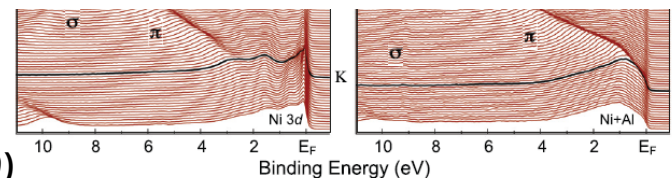
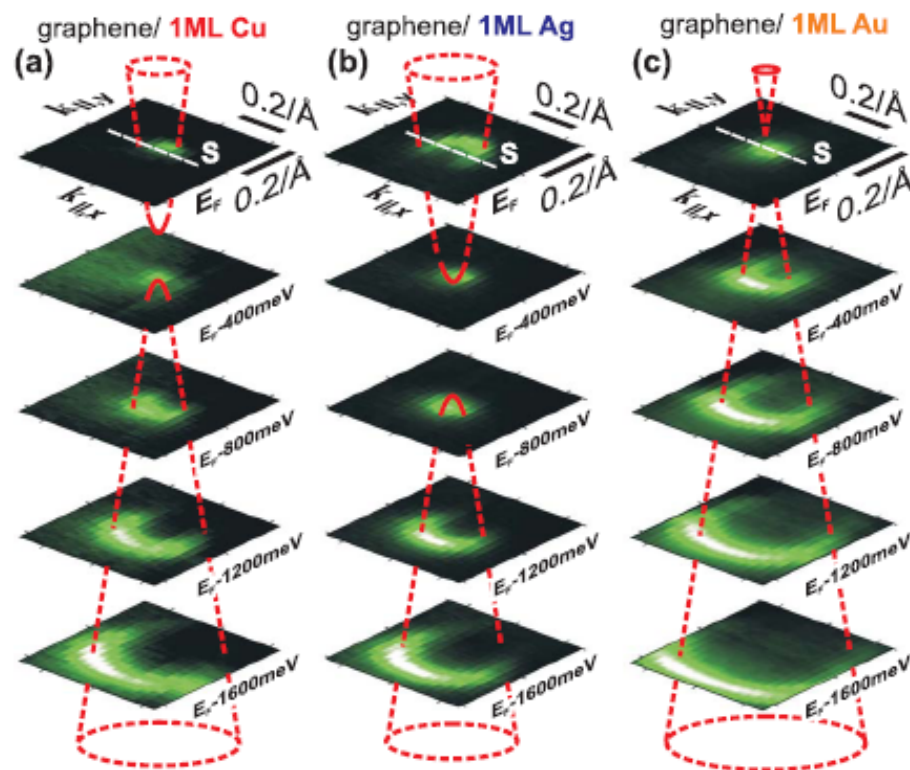
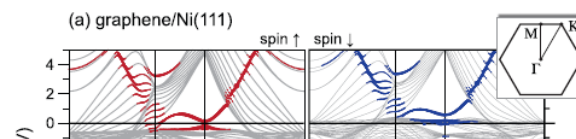
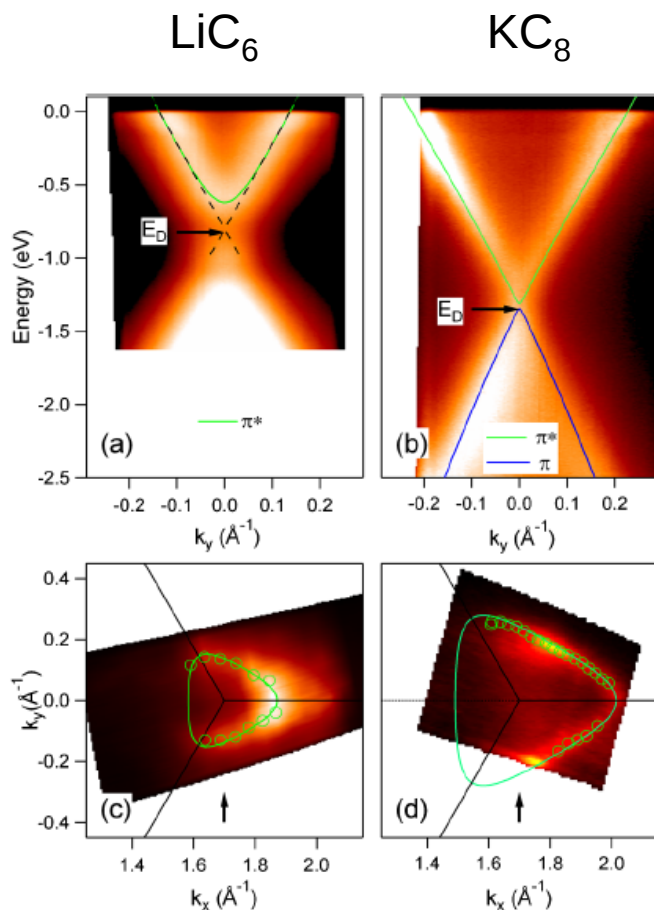
Bilayer graphene/SiC



High quality graphene/SiC



Graphene intercalated compounds (GICs)



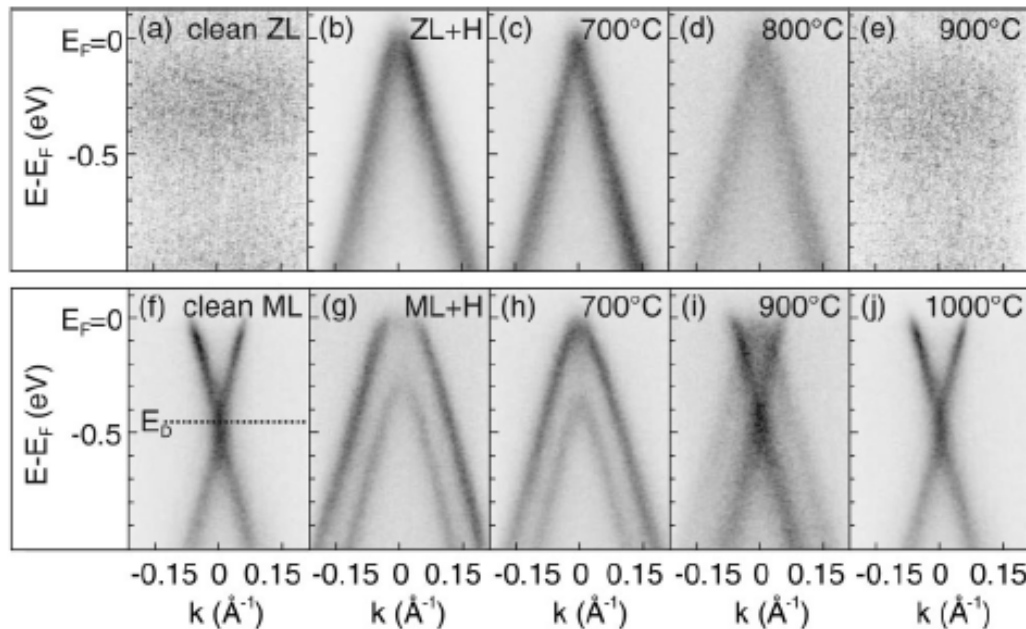
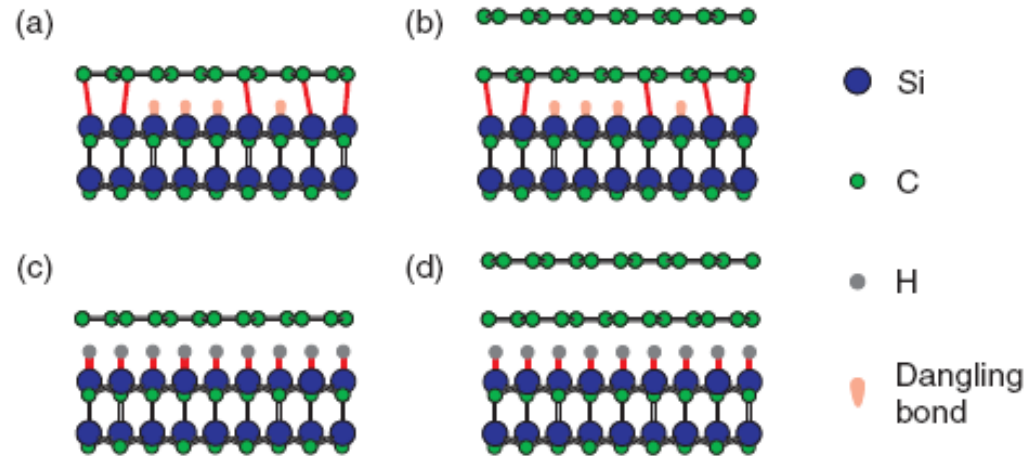
國家同步輻射研究中心
National Synchrotron Radiation Research Center

Pan et al., PRL (2011)

Voloshina et al., NJP (2011)

Varykhalov et al., PRB (2010)

Hydrogen intercalated graphene/SiC



A intrinsic gap exists or not ?

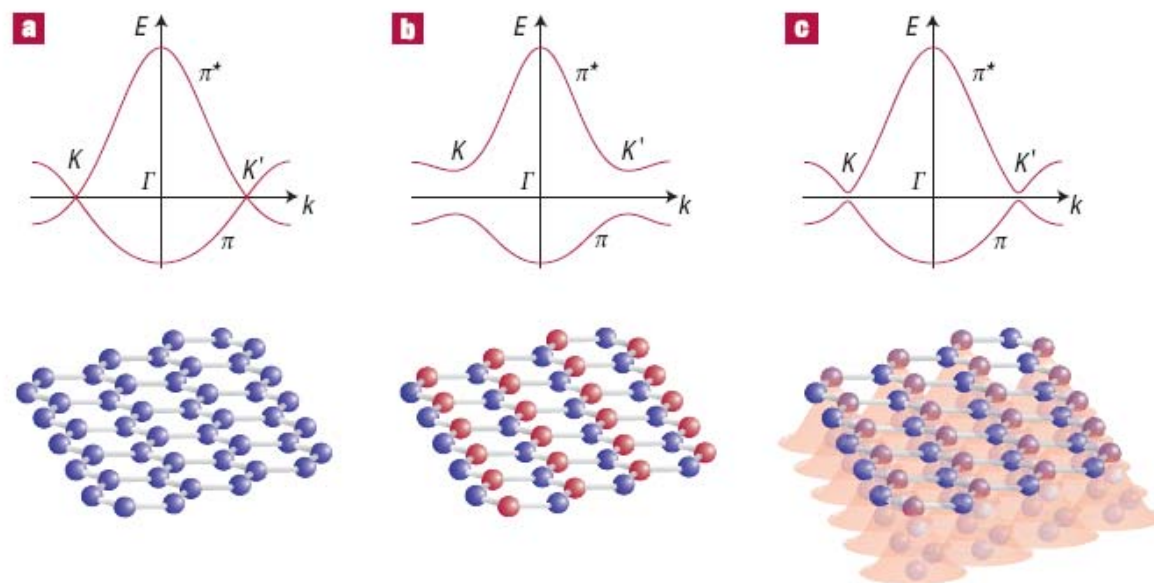


Figure 1 Schematic representation of crystal and electronic band structures (only π -bands are shown). **a**, Free-standing graphene. **b**, Boron-nitride. **c**, Epitaxial graphene. Symmetry between the sublattices in graphene guarantees gapless spectra around K points. This symmetry is broken in boron-nitride (one sublattice consists of boron atoms, another of nitrogen), which immediately opens a gap. In epitaxial graphene, the commensurate underlying potential gives rise to different on-site energies for the two sublattices, which opens a small gap around K points.

The difficulties for studying the electronic structure of exfoliated graphene

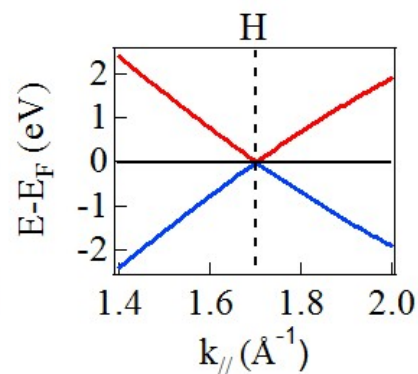
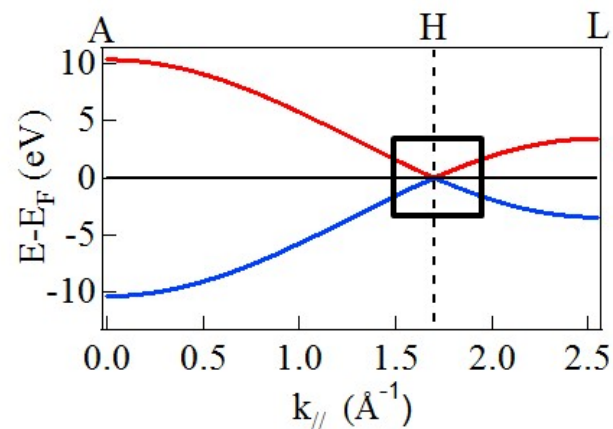
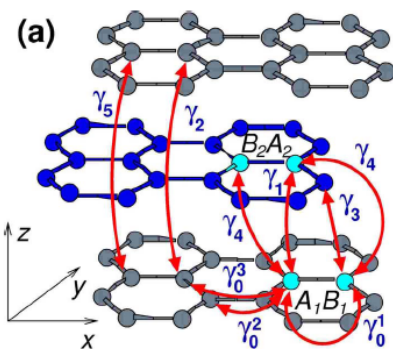
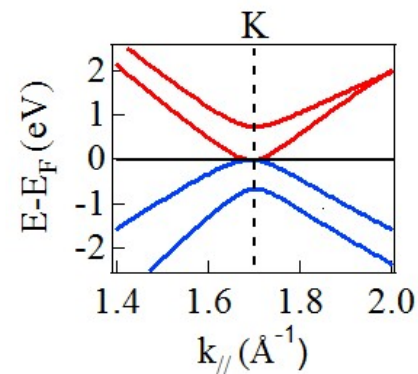
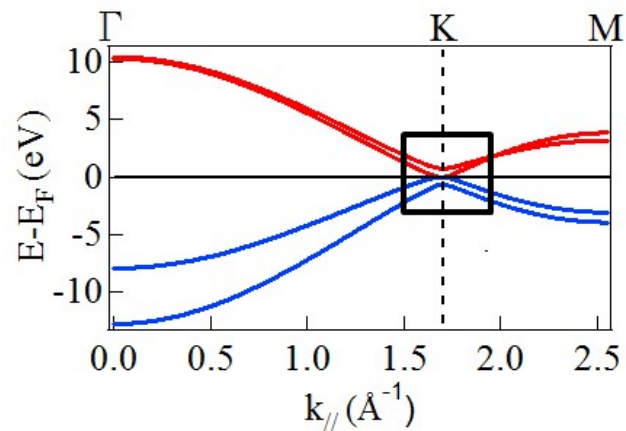
- Insulating substrates induce the strong charging effect
- Sample size : only several tens microns sample is obtained, the size is small for current ARPES beam spot in VUV region
- *ex-situ* sample preparation is not good for ARPES experiments



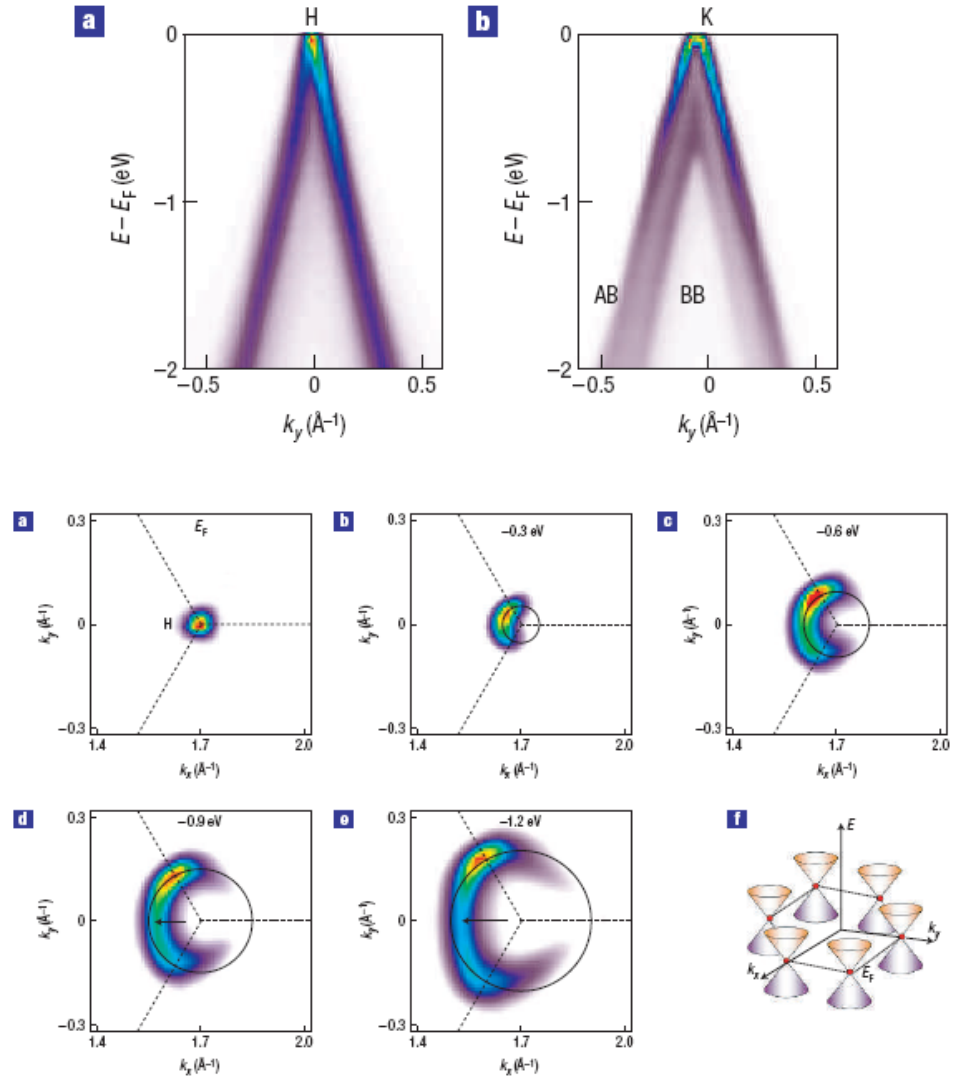
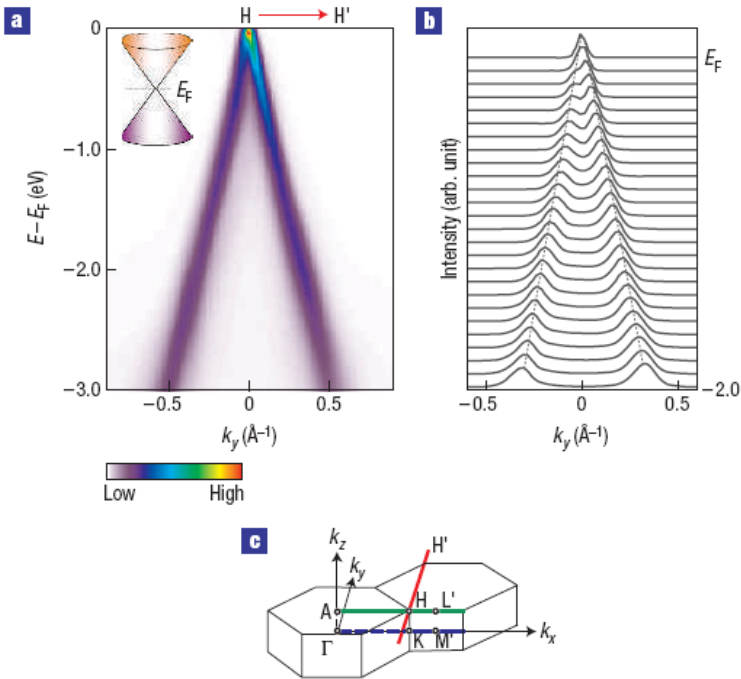
Sample preparation

- Use **highly-doped Si-substrate** to replace Si capped with 200nm SiO₂ substrate.
- Anneal sample above 400 °C to flash gas condensations in UHV environment.
- Choose suitable photon energy to enhance the cross section of carbon.

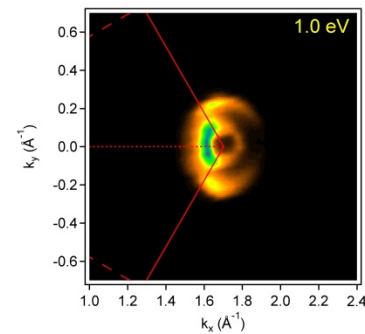
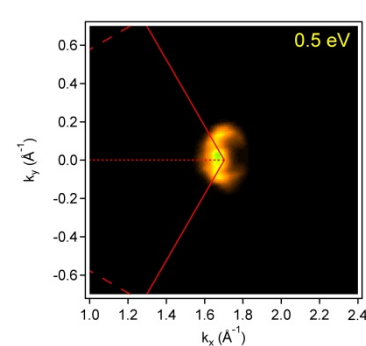
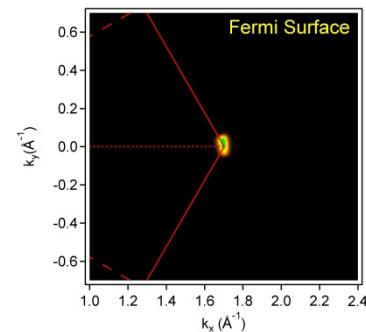
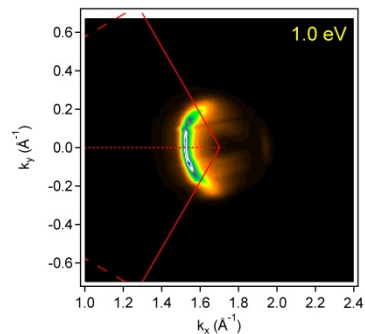
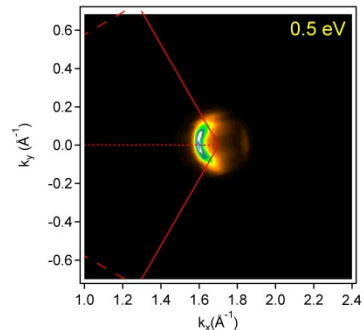
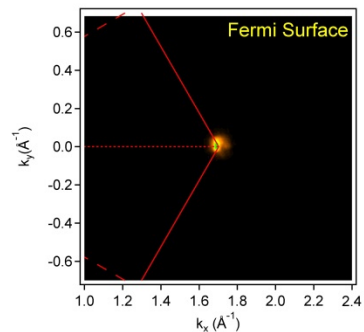
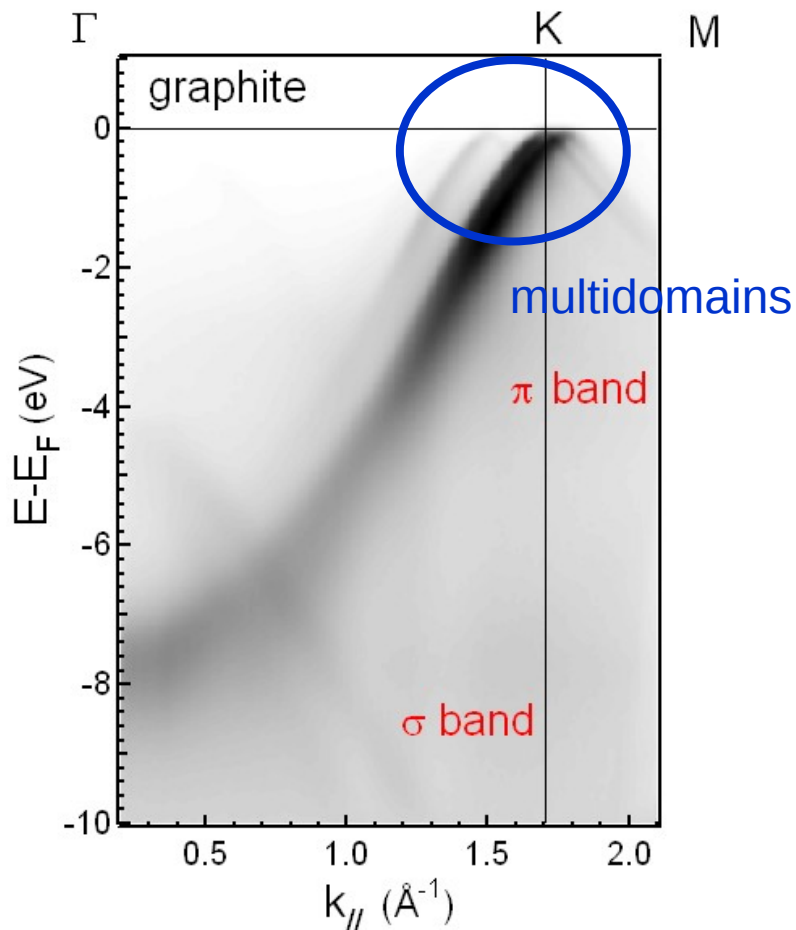




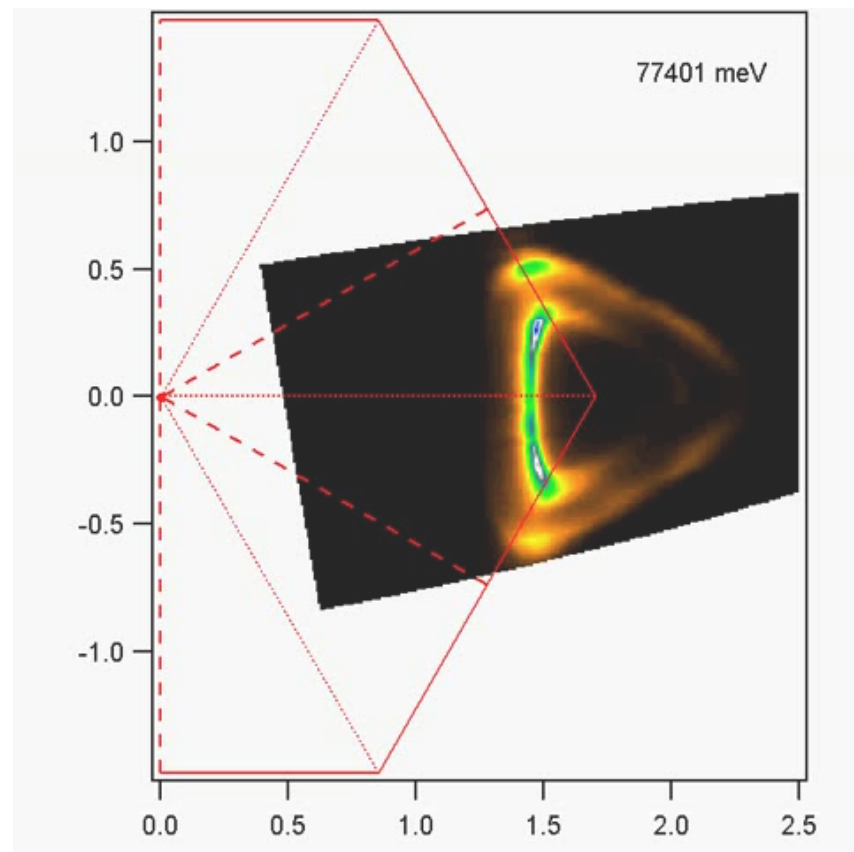
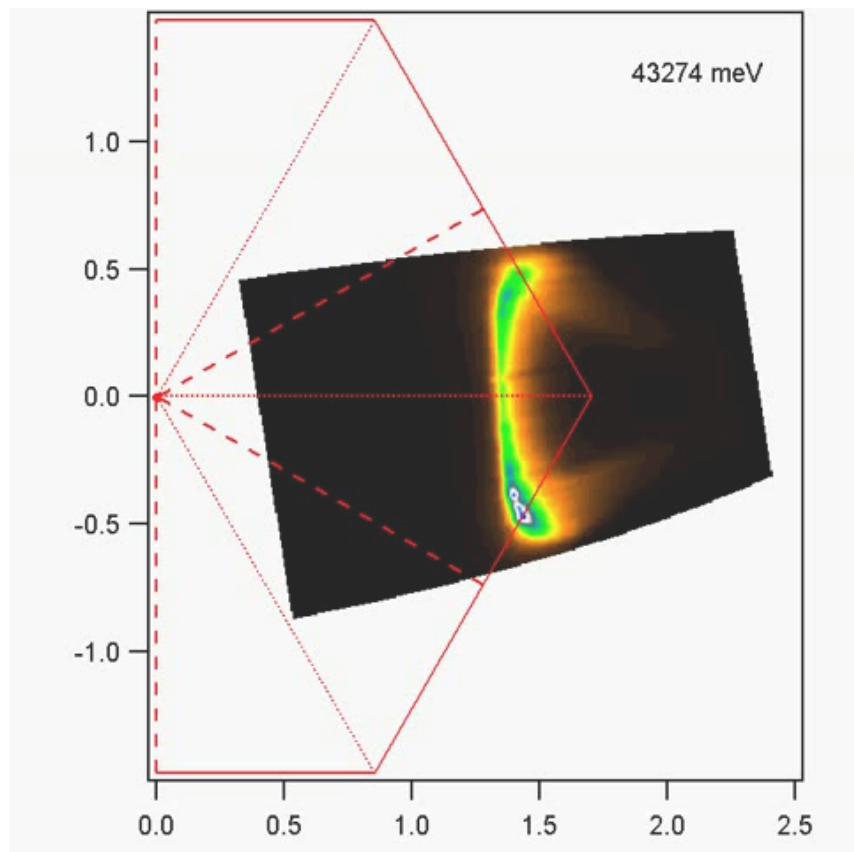
Early ARPES work on graphite



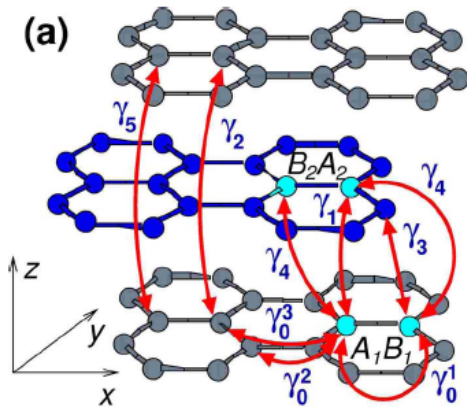
The band mapping result of Kish graphite



Constant energy mapping of graphite



3NNN SWMc Hamiltonian of bilayer graphene



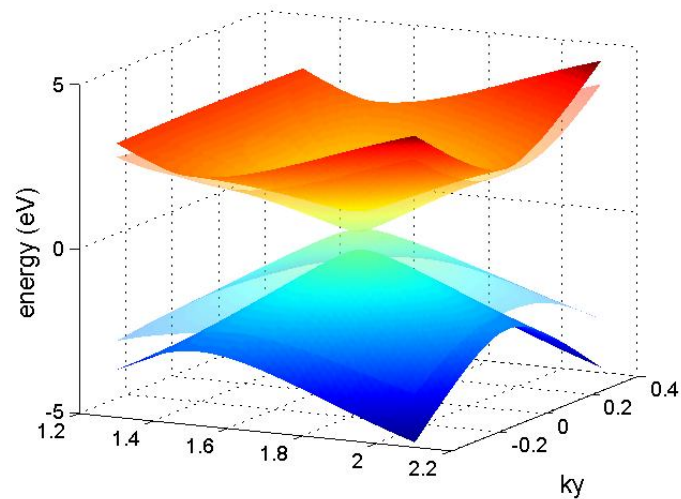
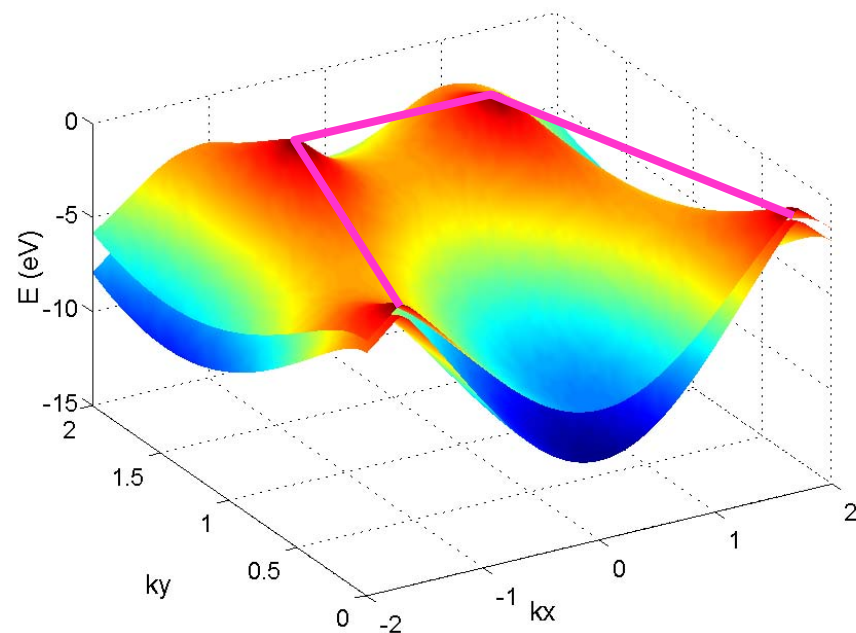
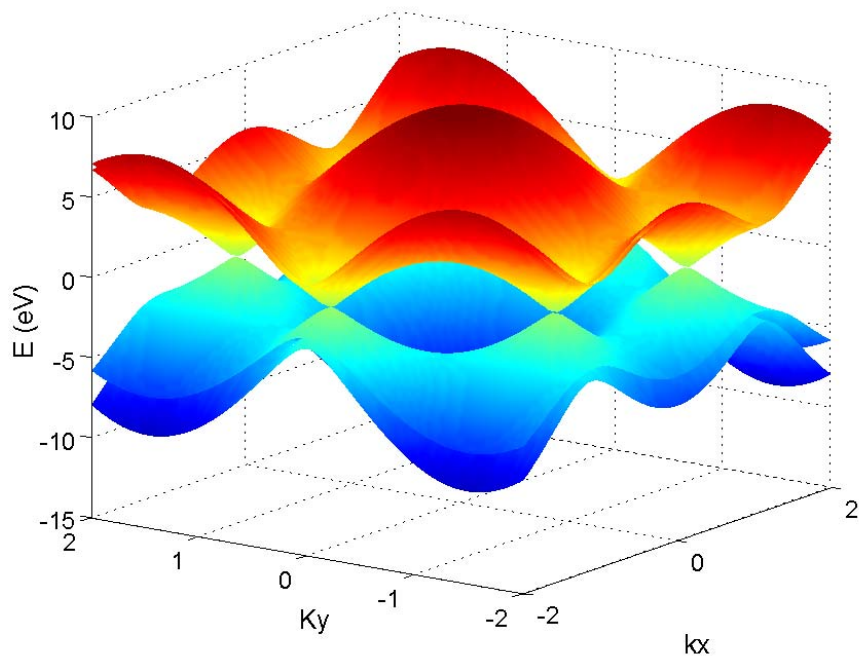
$$H(\mathbf{k})c(\mathbf{k}) = S(\mathbf{k})E(\mathbf{k})c(\mathbf{k}).$$

$$H(\mathbf{k}) = \begin{pmatrix} E_0 + \Delta + \gamma_0^2 f_2(\mathbf{k}) & \gamma_0^1 f_1(\mathbf{k}) + \gamma_0^3 f_3(\mathbf{k}) & \gamma_1 & \gamma_4 f_1(\mathbf{k})^* \\ \gamma_0^1 f_1(\mathbf{k})^* + \gamma_0^3 f_3(\mathbf{k})^* & E_0 + \gamma_0^2 f_2(\mathbf{k})^* & \gamma_4 f_1(\mathbf{k})^* & \gamma_3 f_1(\mathbf{k}) \\ \gamma_1 & \gamma_4 f_1(\mathbf{k}) & E_0 + \Delta + \gamma_0^2 f_2(\mathbf{k}) & \gamma_0^1 f_1(\mathbf{k})^* + \gamma_0^3 f_3(\mathbf{k})^* \\ \gamma_4 f_1(\mathbf{k}) & \gamma_3 f_1(\mathbf{k})^* & \gamma_0^1 f_1(\mathbf{k}) + \gamma_0^3 f_3(\mathbf{k}) & E_0 + \gamma_0^2 f_2(\mathbf{k}) \end{pmatrix}$$

$$S(\mathbf{k}) = \begin{pmatrix} 1 + s_0^2 f_2(\mathbf{k}) & s_0^1 f_1(\mathbf{k}) + s_0^3 f_3(\mathbf{k}) & 0 & 0 \\ s_0^1 f_1(\mathbf{k})^* + s_0^3 f_3(\mathbf{k})^* & 1 + s_0^2 f_2(\mathbf{k})^* & 0 & 0 \\ 0 & 0 & 1 + s_0^2 f_2(\mathbf{k}) & s_0^1 f_1(\mathbf{k})^* + s_0^3 f_3(\mathbf{k})^* \\ 0 & 0 & s_0^1 f_1(\mathbf{k}) + s_0^3 f_3(\mathbf{k}) & 1 + s_0^2 f_2(\mathbf{k}) \end{pmatrix}$$



Simulation result of the π band for bilayer graphene



TBM parameters determined by resonance Raman scattering

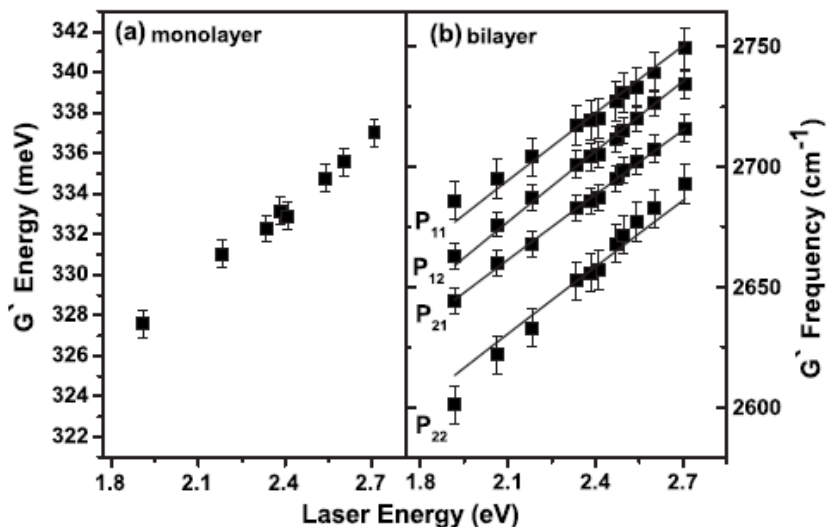
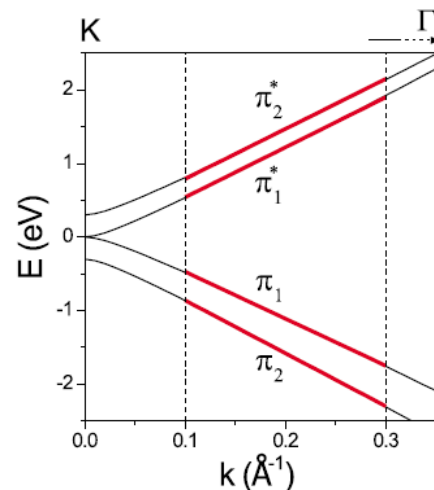
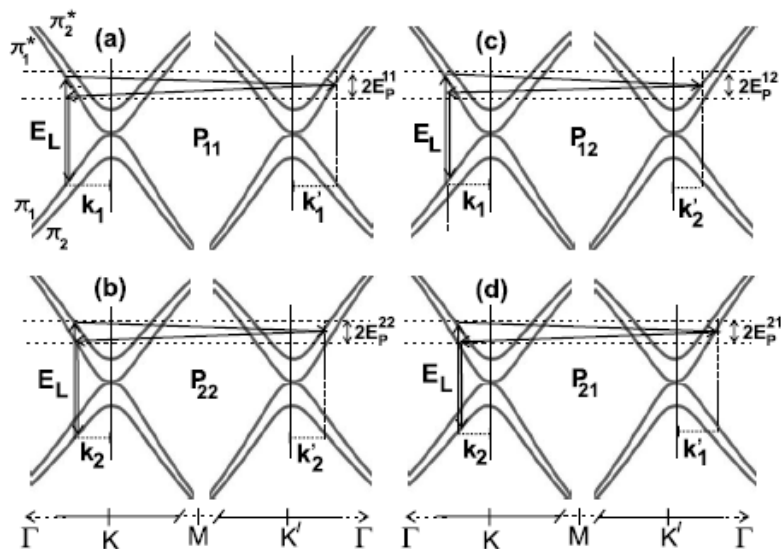
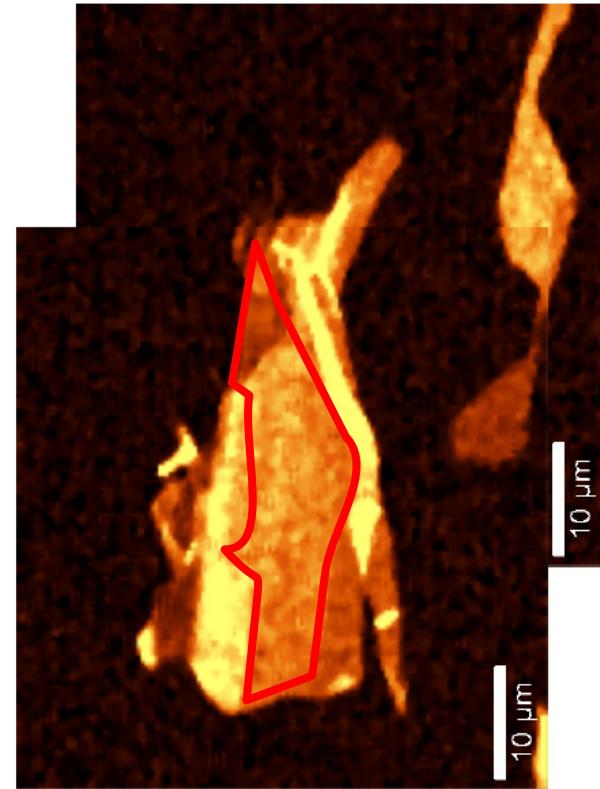
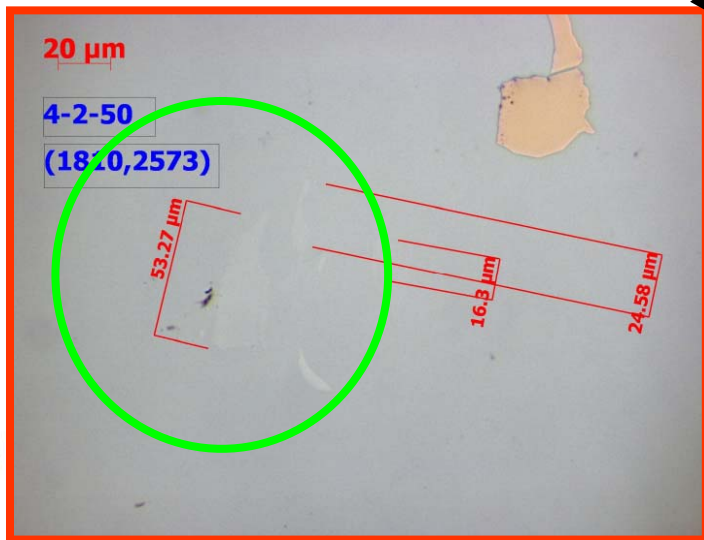
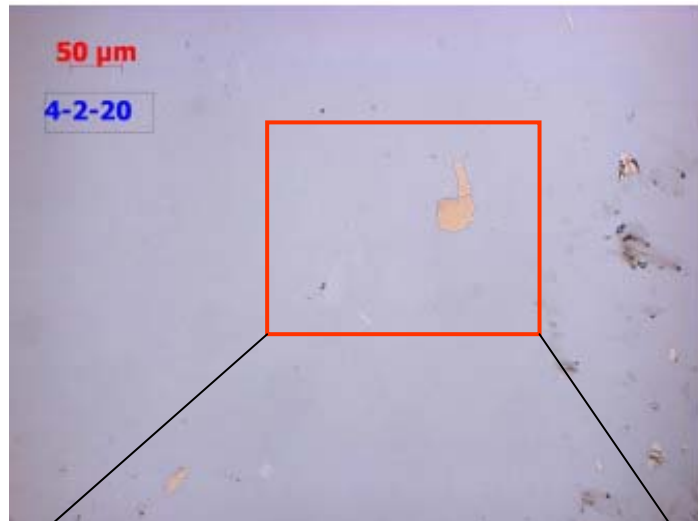


TABLE II. Experimental SWM parameters (in eV) for the band structure of bilayer graphene. The parameters for graphite are taken from Refs. 18 and 19.

	γ_0	γ_1	γ_2	γ_3	γ_4	γ_5	$\gamma_6 = \Delta$
Bilayer graphene	2.9	0.30	n/a	0.10	0.12	n/a	n/a
Graphite	3.16	0.39	-0.02	0.315	0.044	0.038	0.008

Malard et al., PRB (2007)

Bilayer graphene / Highly doped Si substrate

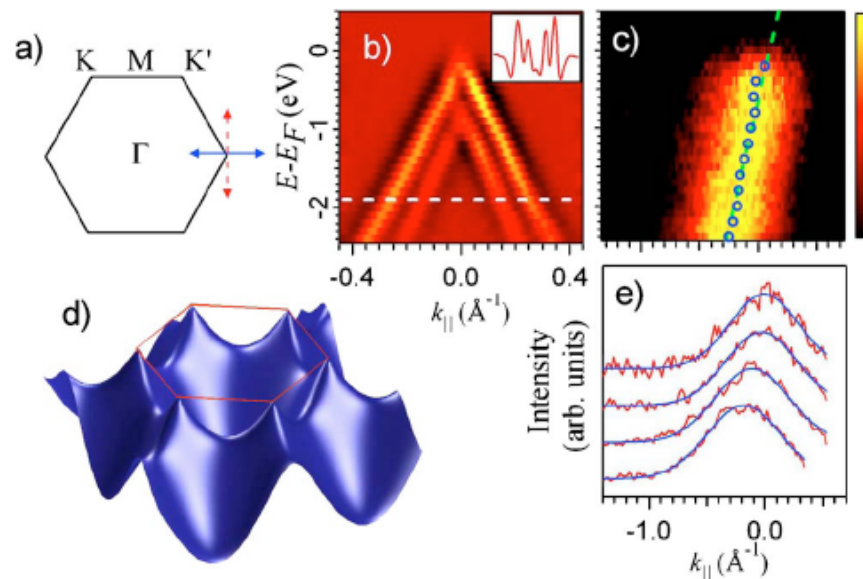
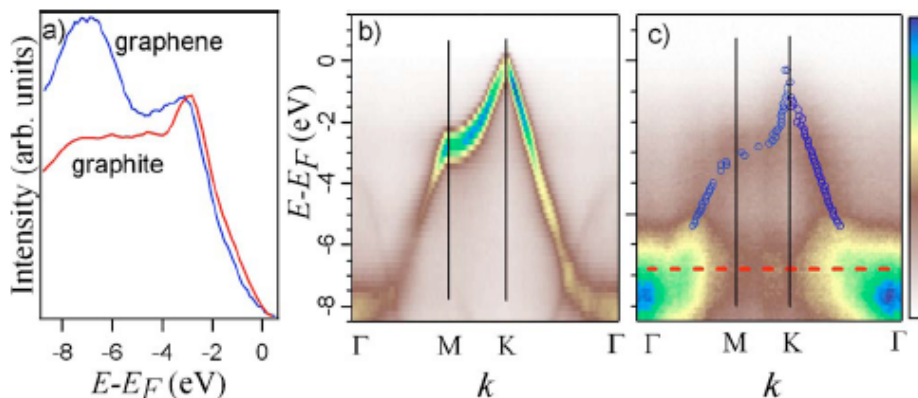
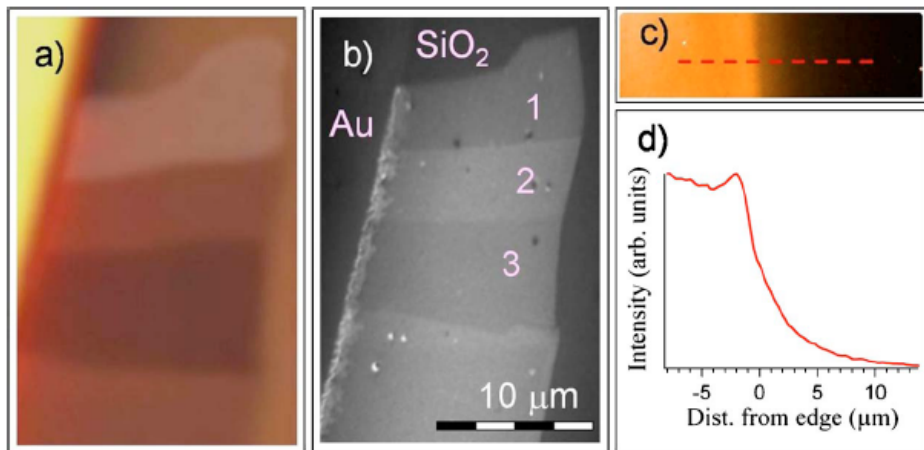


Intensity of G band (overlap of 2 scans showing flake 1 and 3)

Raman result from Germany,,
the bilayer graphene should
be the area marked in red.

The electronic structure of single layer graphene on SiO₂ (200nm)

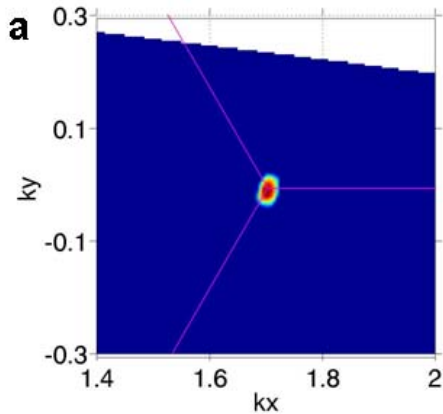
1. Use lithography to pattern graphene flake with gold contact
2. Microfocus beam size < 5 μm



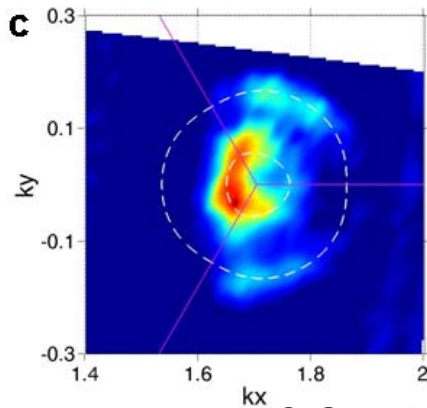
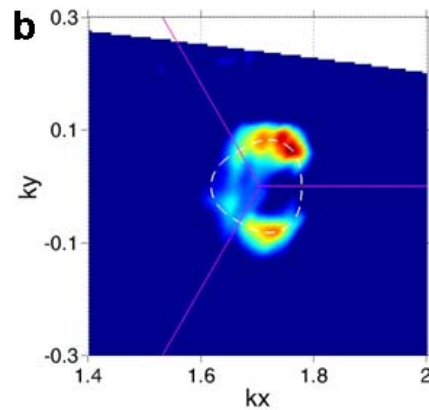
Fit TBM parameters to high binding energy

Data were taken at 82 eV

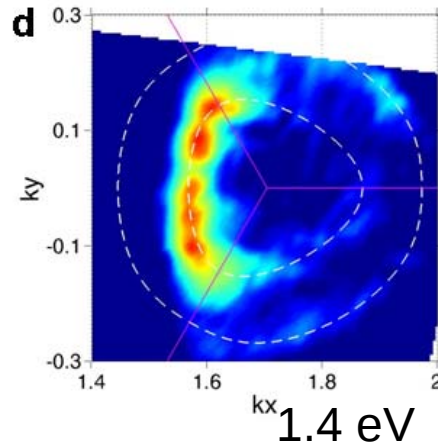
FS



0.3 eV

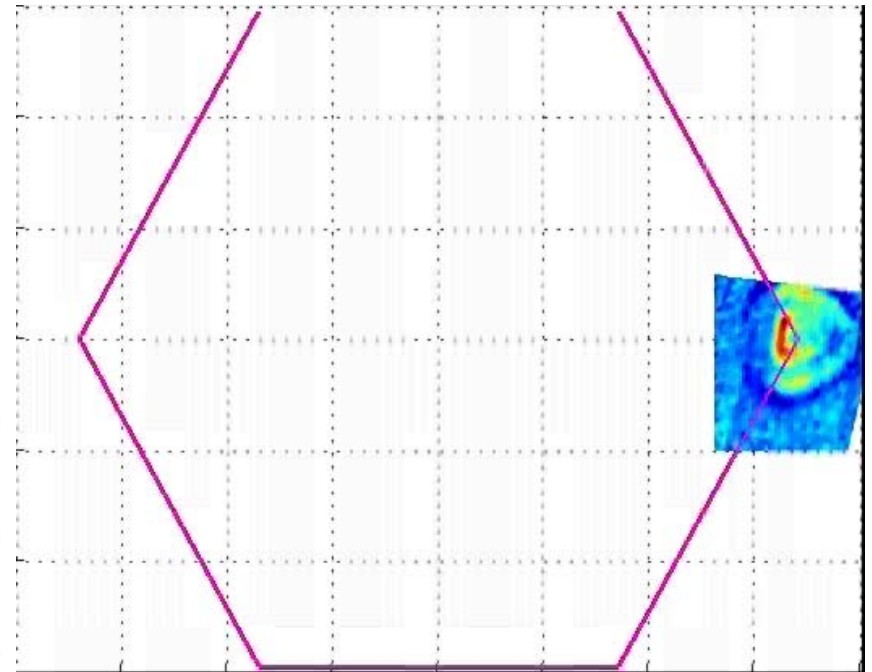


0.8 eV

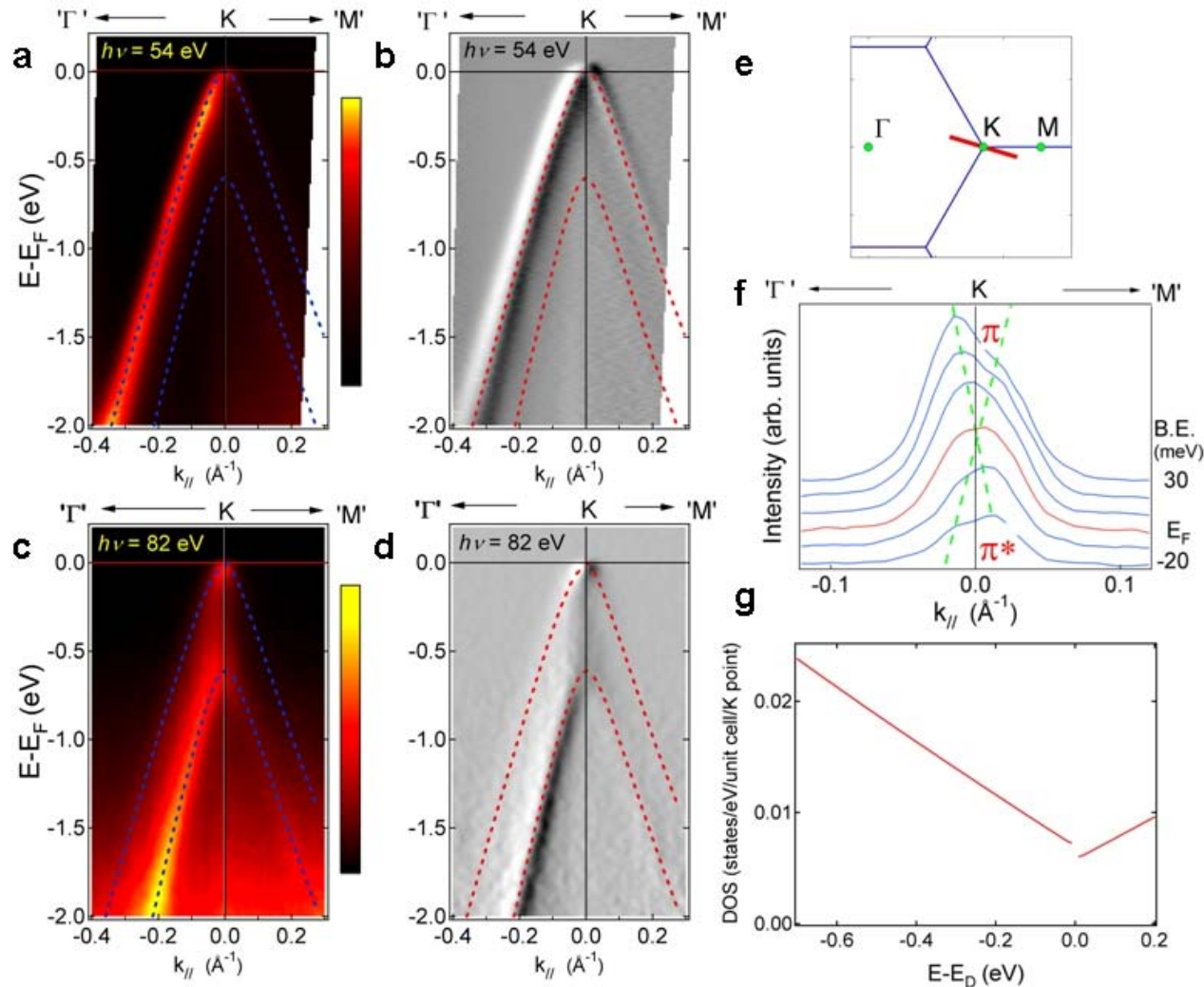


1.4 eV

Exfoliated BLG/Si



The electronic structure of bilayer graphene



Sample temperature at 70 K

Without gap exists on charge neutral bilayer graphene

What does ARPES measure

$$I \propto \sum_{f,i,\mathbf{k}} \left| \langle \phi_f | H_{\text{int}} | \phi_i \rangle \right|^2 A(\mathbf{k}, E)$$

Matrix element

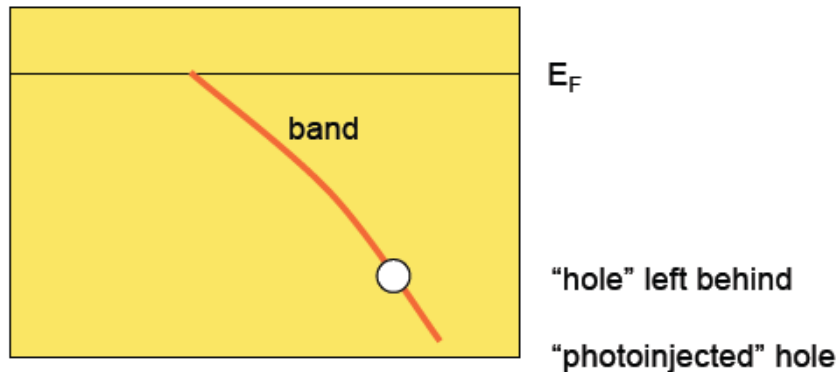
Spectra function



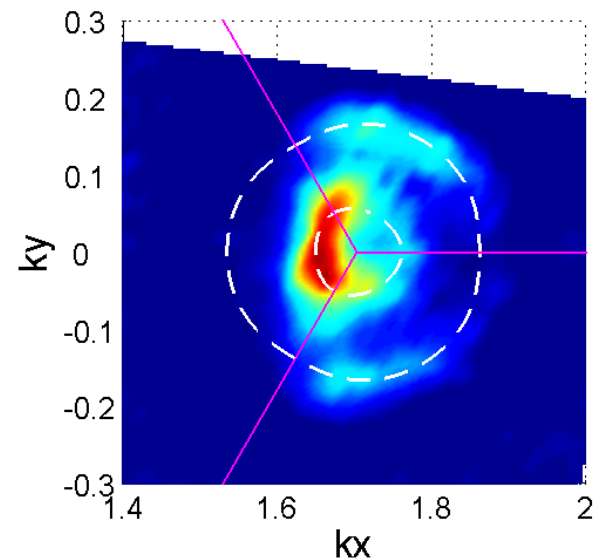
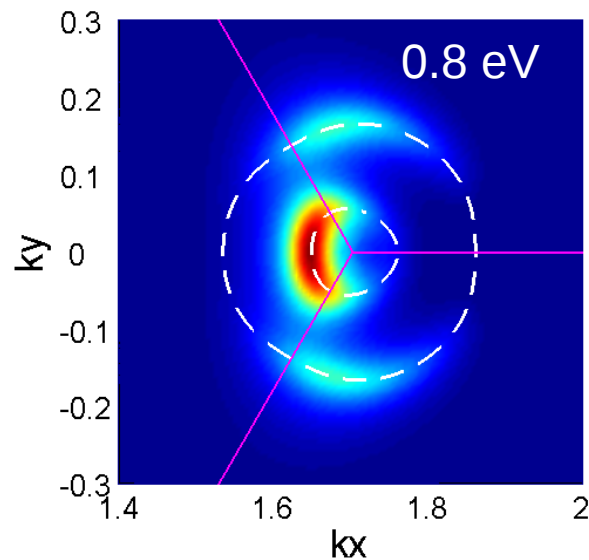
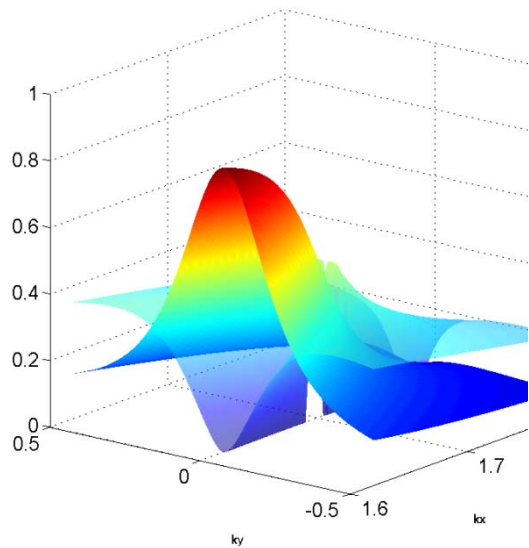
we believe the properties of the photoelectron reflect the properties of the injected hole

namely,

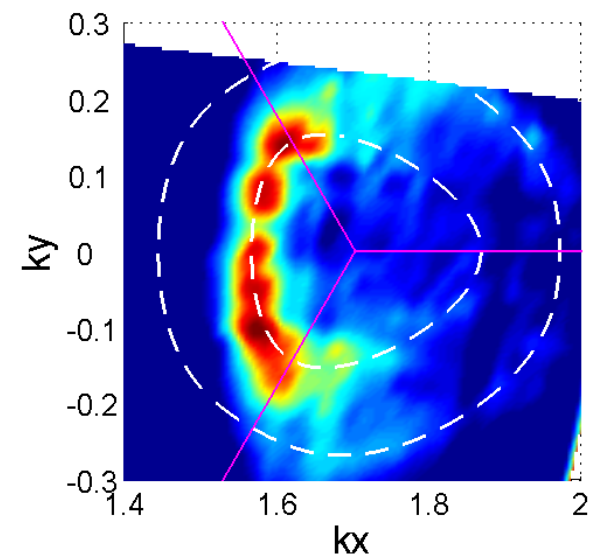
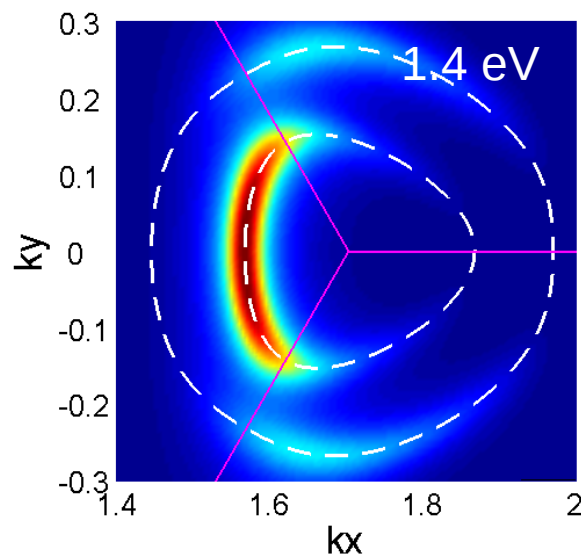
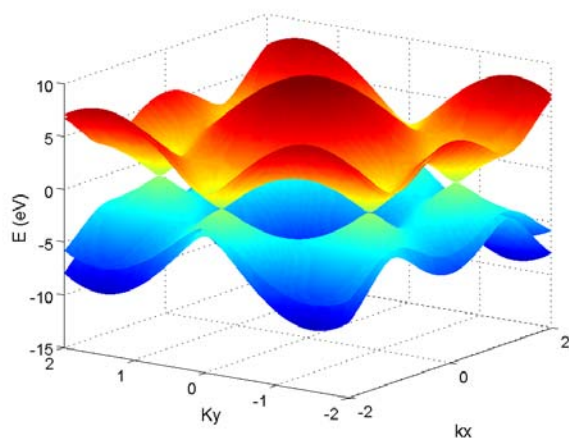
we can learn about the scattering and lifetime of the injected hole



82 eV ME effect



Electronic structure of BLG



TB parameters for experimental and theoretical results

TABLE I. 3NN tight-binding parameters for few-layer graphene and graphite. All values except the ones for s_0^1 , s_0^2 , and s_0^3 are in eV. The parameters of fits to LDA and *GW* calculations are shown. The 3NN Hamiltonian is valid in the whole two (three) dimensional BZ of graphite (graphene layers).

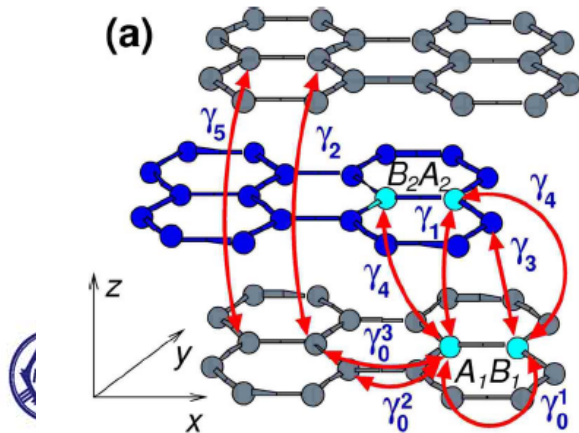
Method	γ_0^1	γ_0^2	γ_0^3	s_0^1	s_0^2	s_0^3	γ_1	γ_2	γ_3	γ_4	γ_5	E_0	Δ
3NN TB- <i>GW</i> ^a	-3.4416	-0.7544	-0.4246	0.2671	0.0494	0.0345	0.3513	-0.0105	0.2973	0.1954	0.0187	-2.2624	0.0540 ^b
3NN TB-LDA ^a	-3.0121	-0.6346	-0.3628	0.2499	0.0390	0.0322	0.3077	-0.0077	0.2583	0.1735	0.0147	-1.9037	0.0214
EXP ^c	-5.13	1.70	-0.418	-0.148	-0.0948	0.0743							
3NN TB-LDA ^d	-2.79	-0.68	-0.30	0.30	0.046	0.039						-2.03	

^aThis work.

^bWe adjusted the impurity doping level in order to reproduce the experimental value of Δ .

^cFit to ARPES by Bostwick *et al.* (Ref. 22).

^dFit to LDA by Reich *et al.* (Ref. 20).

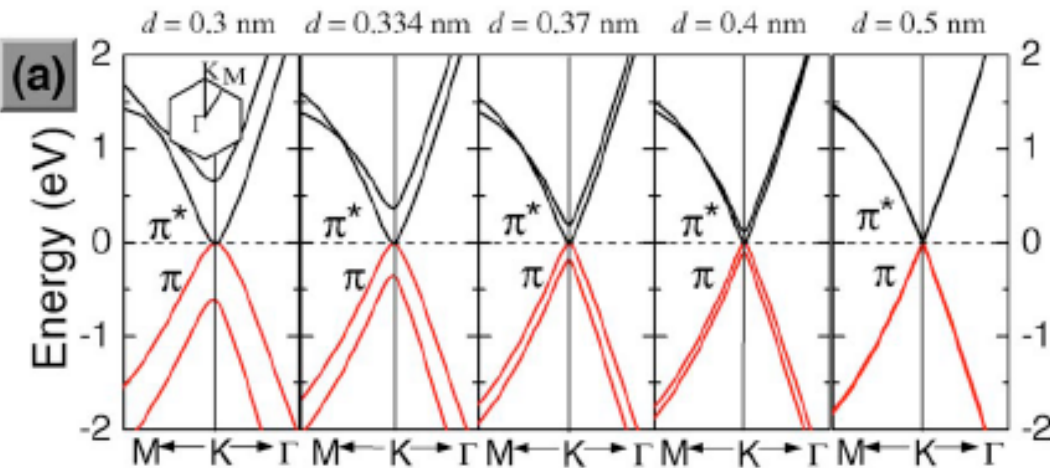


TB parameters	γ_0	γ_1	γ_3	γ_4
Pres. work	-3.21	0.61	0.39	0.15
Prev. bilayer/SiC	-3.24	0.48		
Prev. graphite	-3.16	0.39	0.315	0.044

Strong interlayer interaction
induced smaller interlayer spacing
on BLG ?

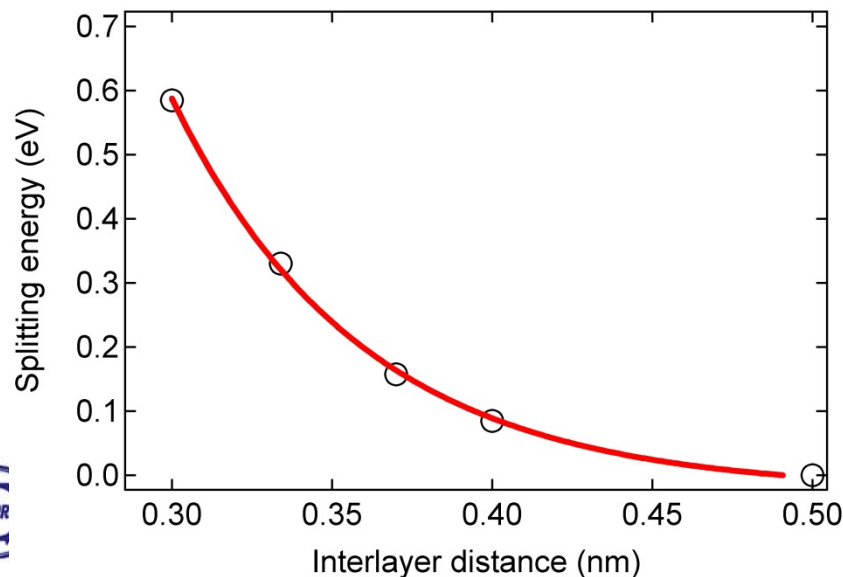


Interlayer spacing of neutral BLG



Graphite : 3.35 Å

BLG/SiO₂ with 0.61
splitting energy: 2.99 Å



Consistent with larger γ_1 in
our case

What does ARPES measure

$$I \propto \sum_{f,i,\mathbf{k}} \left| \langle \phi_f | H_{\text{int}} | \phi_i \rangle \right|^2 A(\mathbf{k}, E)$$

Matrix element

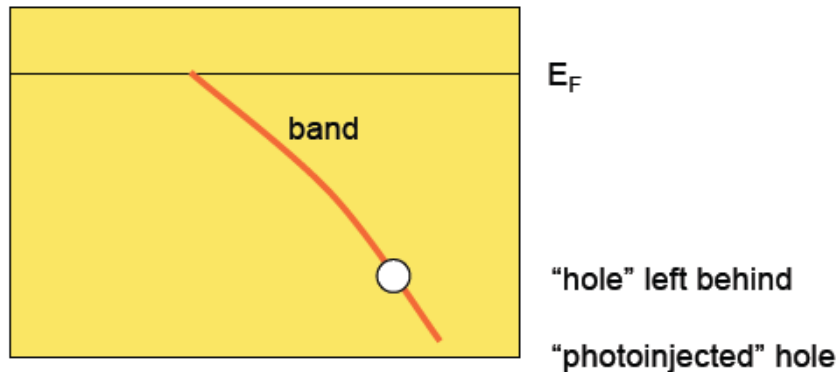
Spectra function



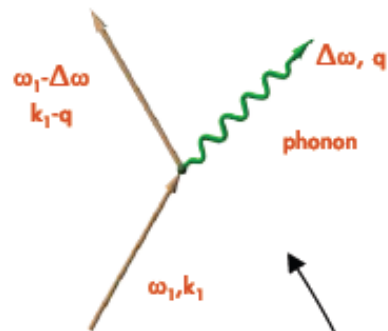
we believe the properties of the photoelectron reflect the properties of the injected hole

namely,

we can learn about the scattering and lifetime of the injected hole



The carriers have a finite lifetime due to absorption and emission of phonons and other excitations



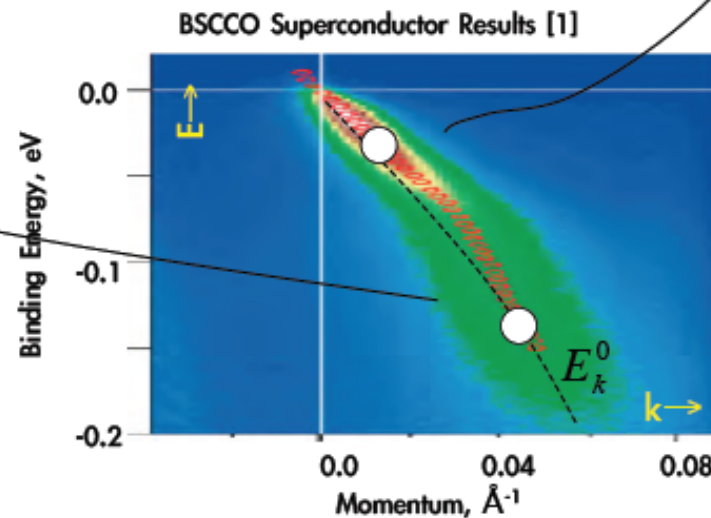
electron emits a phonon :
change of energy ω and
momentum k

The measured state is broader in
momentum and energy



electron emits and reabsorbs a
phonon :Change of mass and slope

The mass of carrier is increased



there is no direct way to probe
these processes except through
ARPES measurements

Self energy in photoemission spectra

The quantity determined in ARPES experiments is the single-particle spectral function

$$G(k, \omega) = \frac{1}{\omega - \varepsilon_k - \Sigma(k, \omega)}$$

$$A(k, \omega) = \frac{\text{Im} \Sigma(k, \omega)}{[\omega - \varepsilon_k - \text{Re} \Sigma(k, \omega)]^2 + [\text{Im} \Sigma(k, \omega)]^2}$$

$$\Sigma = \text{Re} \Sigma + i \text{Im} \Sigma$$

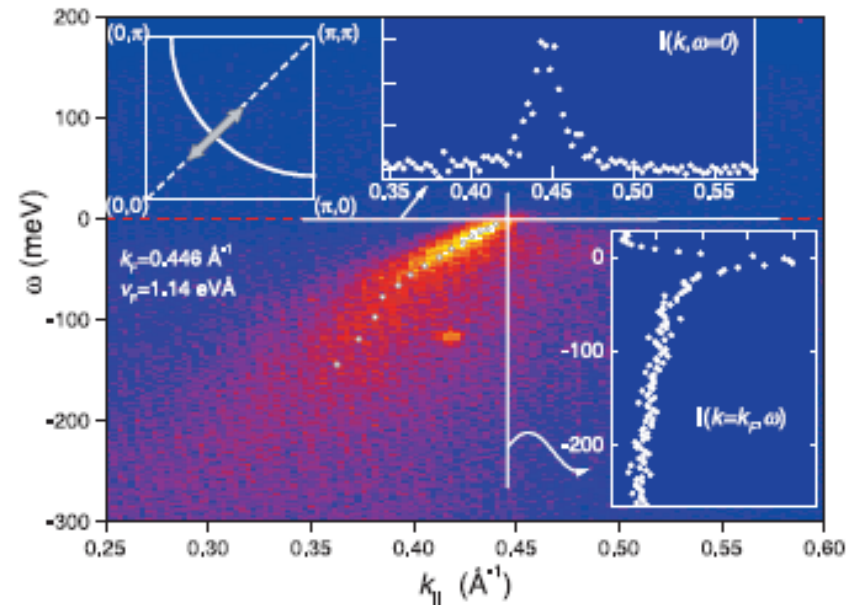
Dispersion:
E-k Relation (Velocity;
Effective mass etc.)

Scattering rate
(Lifetime)



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Optimally doped Bi-2212 cuprate



$$\hbar v_k \Delta k = \frac{\hbar v_k}{l} = |2 \text{Im} \Sigma(k, \omega)|$$

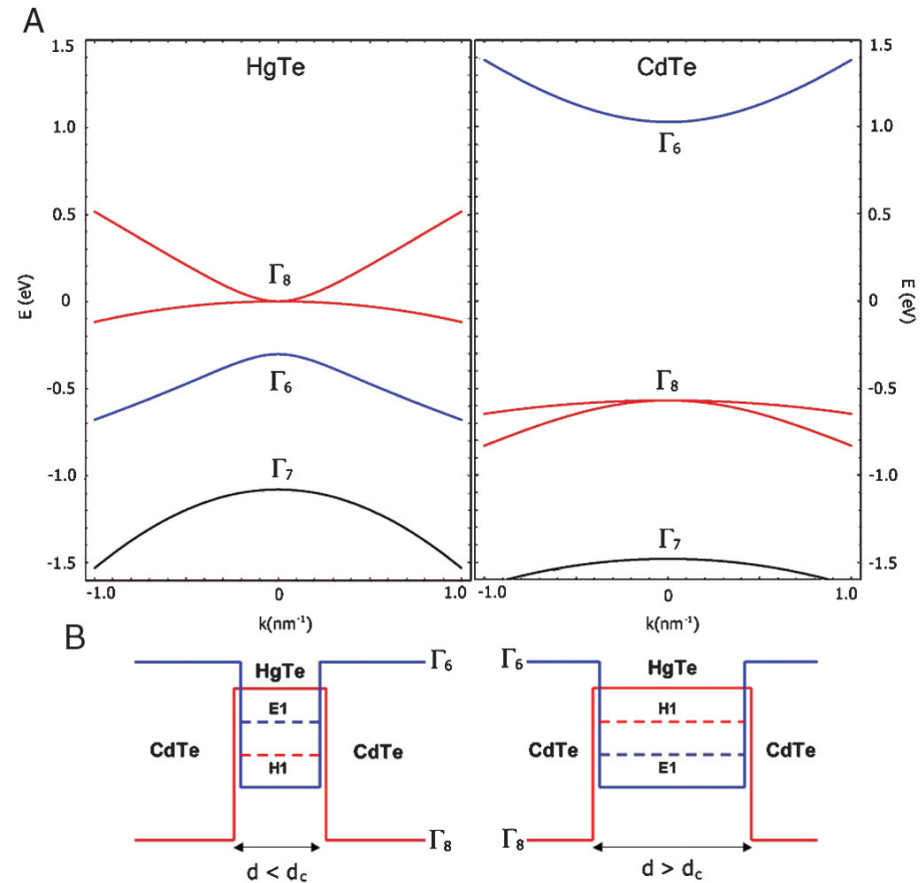
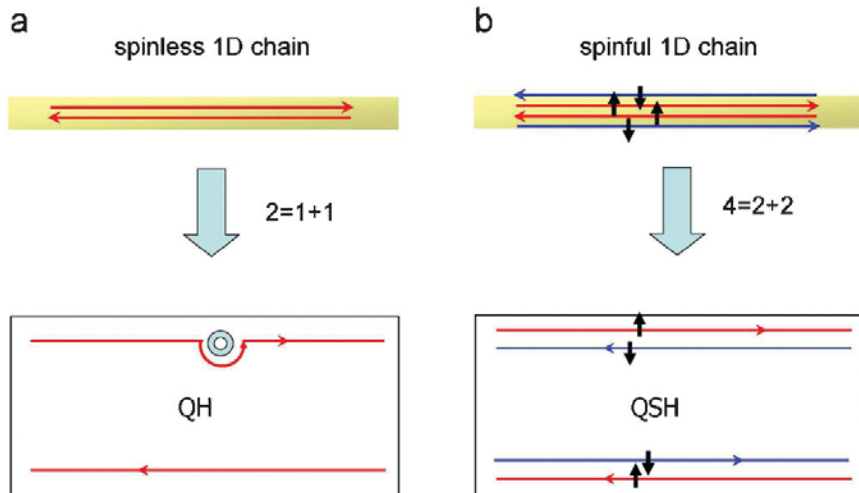
T. Valla et al., Science 285, 2110 (2000)

Summary for graphene

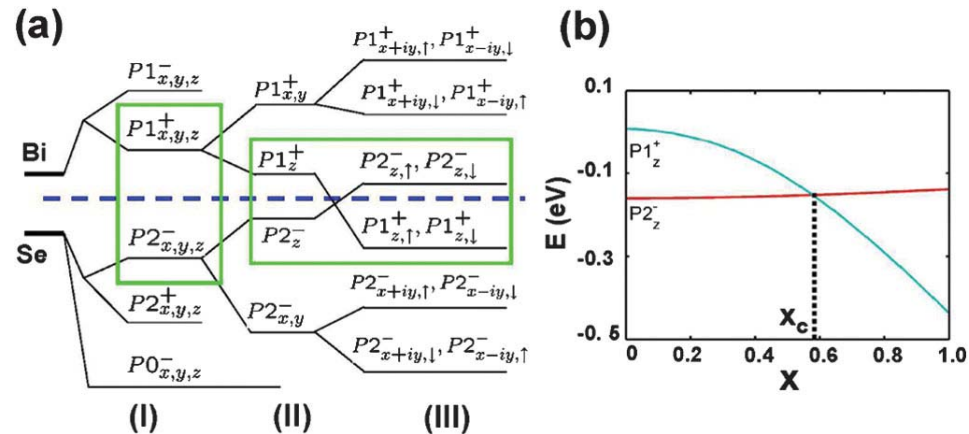
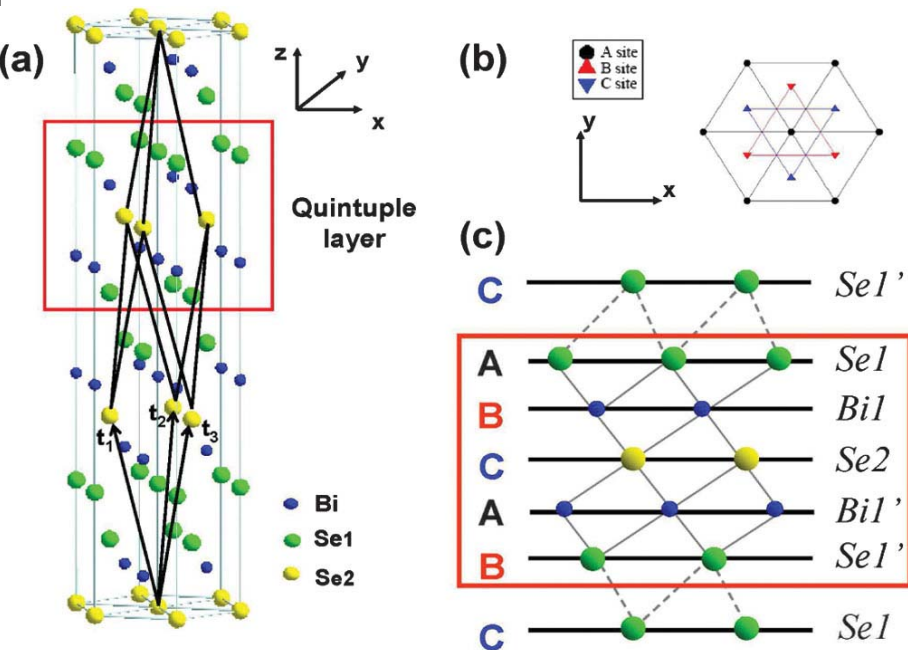
- The free standing bilayer graphene is gapless semiconductor.
- The splitting energy is larger than epitaxial graphene and bulk graphite due to the stronger screening effect.
- A reliable TBM parameters be obtained from presented experimental result.



Topological insulators

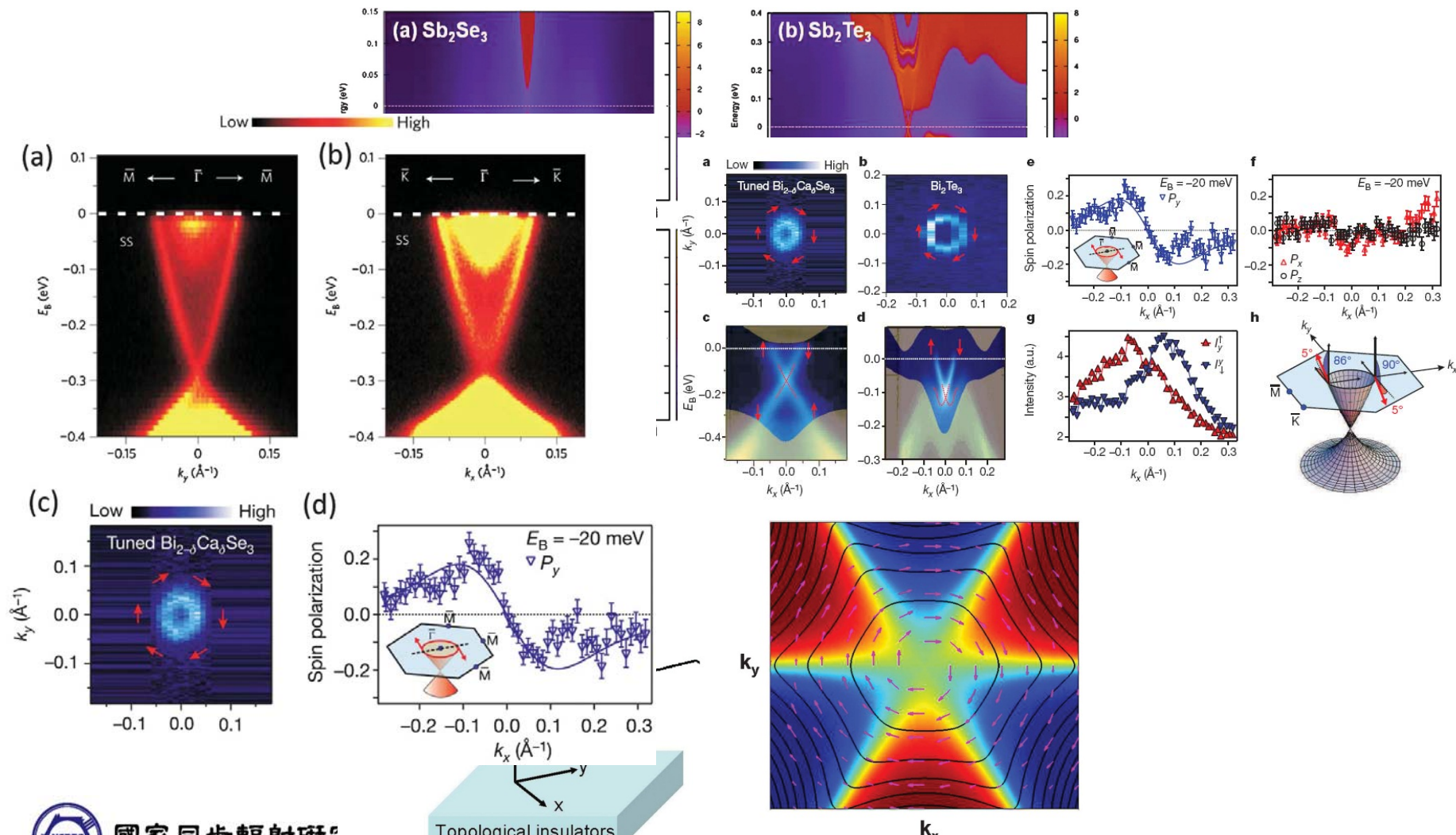


3D topological insulators



Strong spin-orbit coupling
Band inversion

Predictions for 3D topological insulators



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Topological insulators

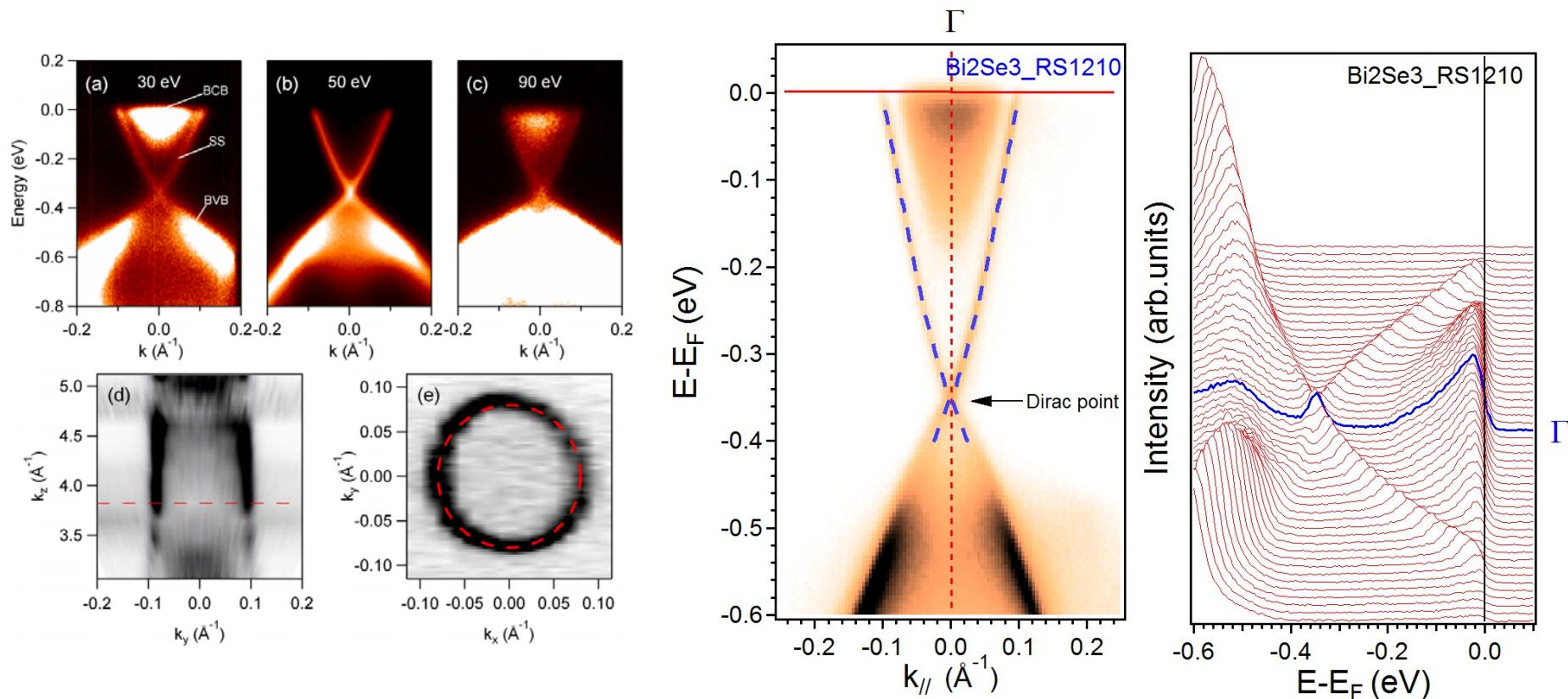
Xia et al., Nature Physics (2009)

Hsieh et al., Nature (2009)

Chen et al, Science (2009)

Xiao-Liang Qi and Shou-Cheng Zhang, RMP (2011)

Typical experimental result at NSRRC

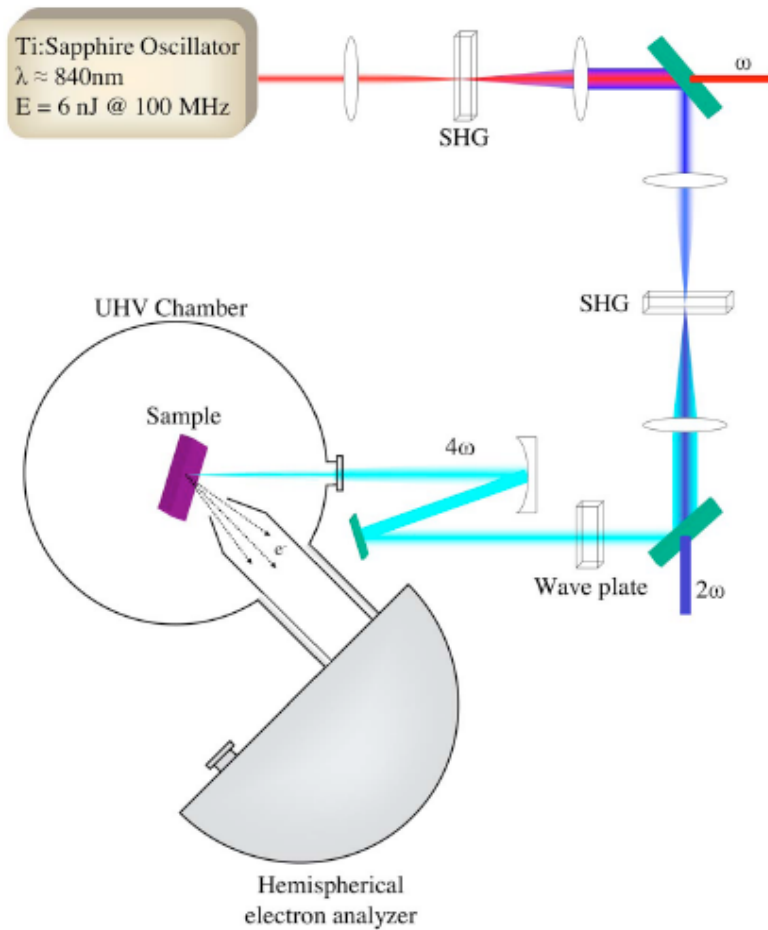


Pan et al., PRL (2011)

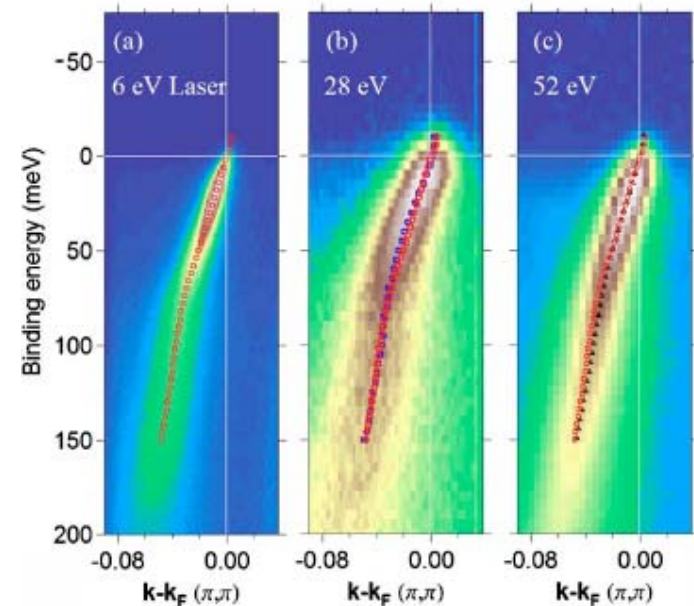


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Setup for Laser ARPES



Band mapping with various photon energies on Bi-2212



Time-resolved ARPES

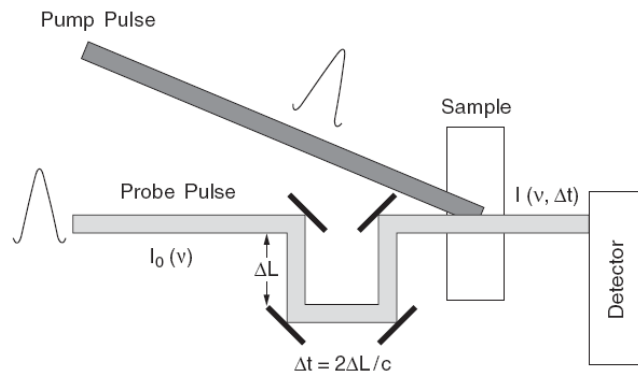


Fig. 8.1. Typical scheme of a “pump–probe” experiment

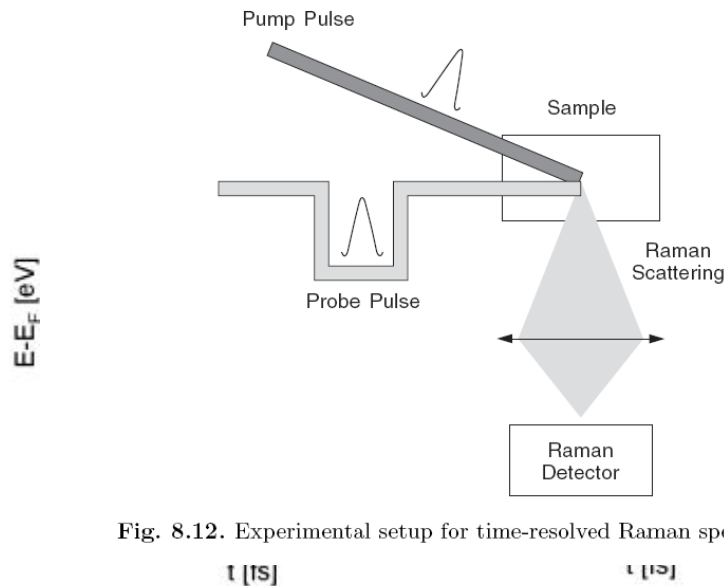
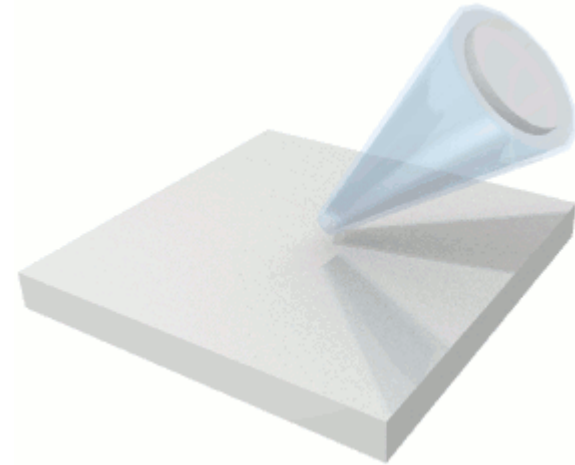
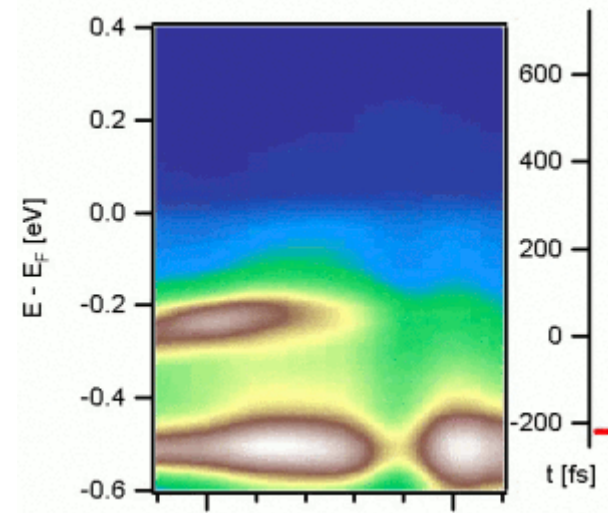
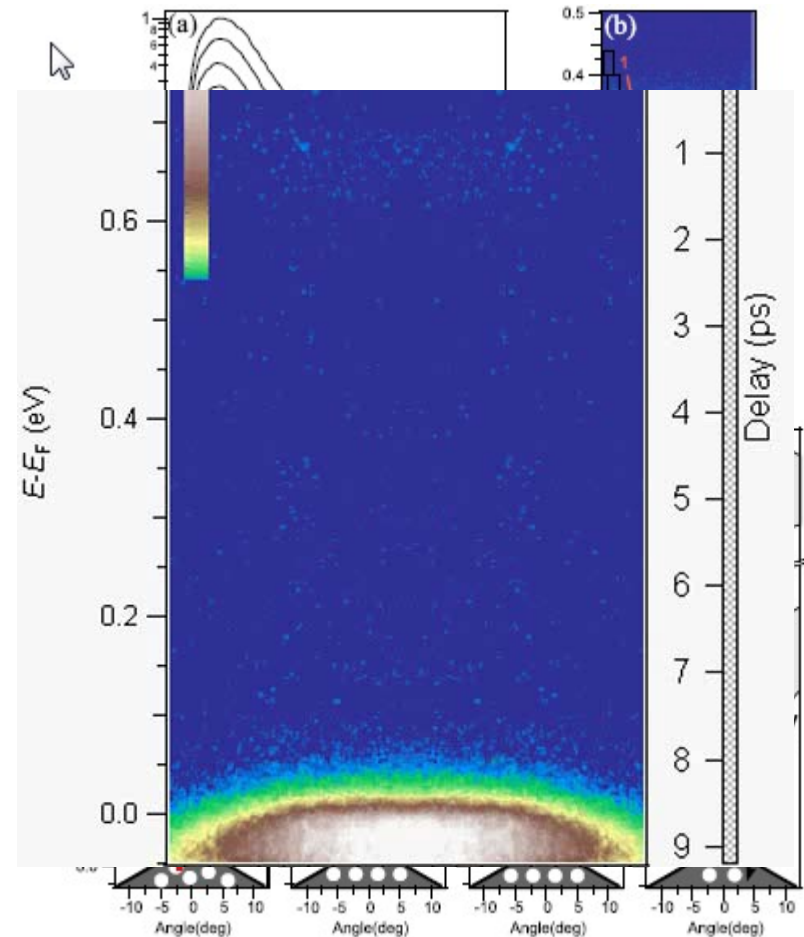
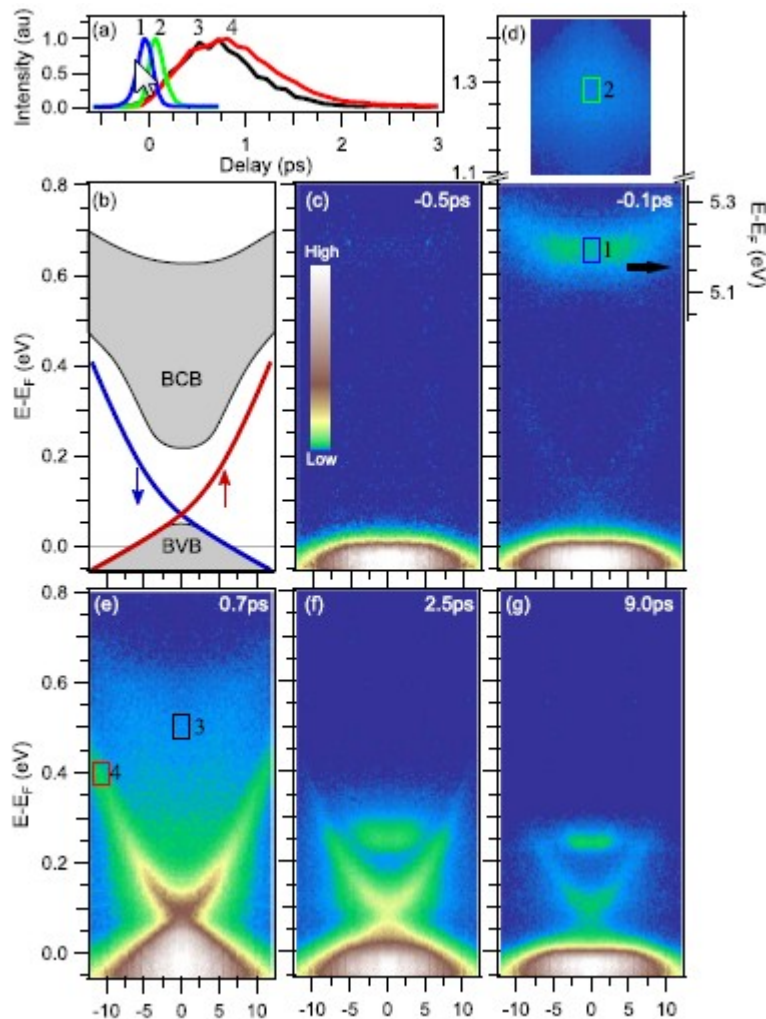


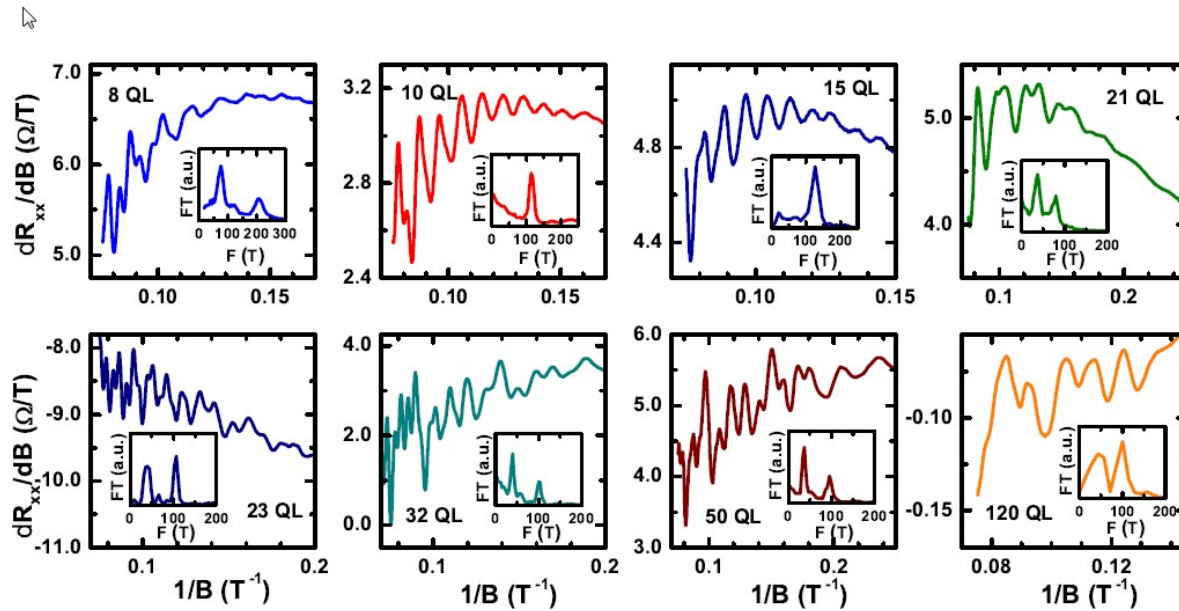
Fig. 8.12. Experimental setup for time-resolved Raman spectroscopy



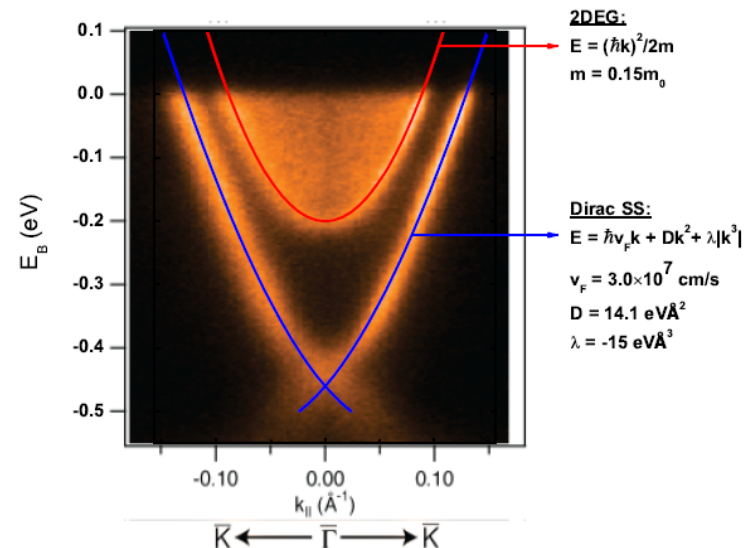
Ultrafast Dynamics of Dirac Fermion in Topological Insulators



Estimate the surface charge carrier density : SdH oscillations ($n_s = \frac{k_F^2}{4\pi}$)

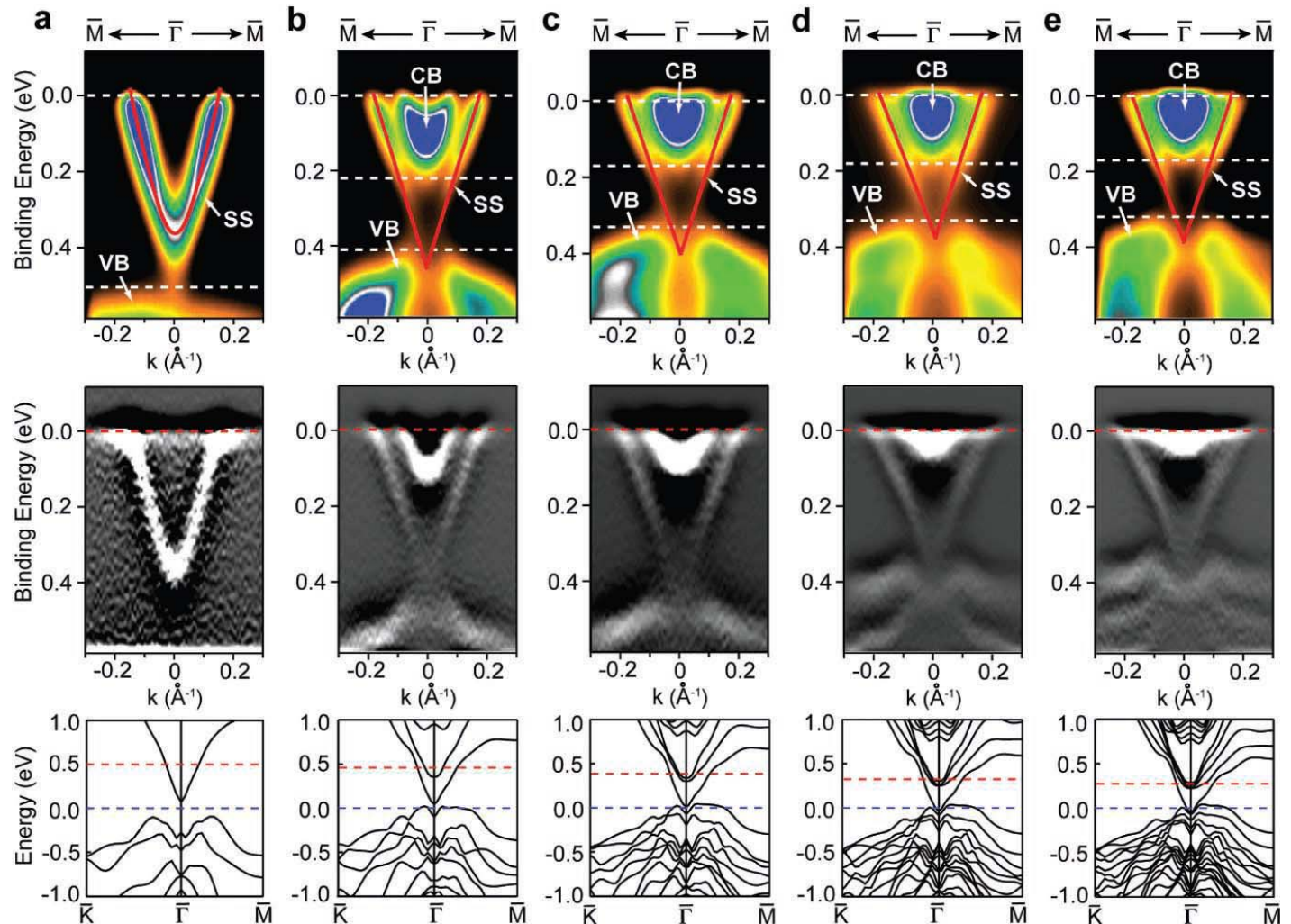


Estimate the surface charge carrier density : ARPES

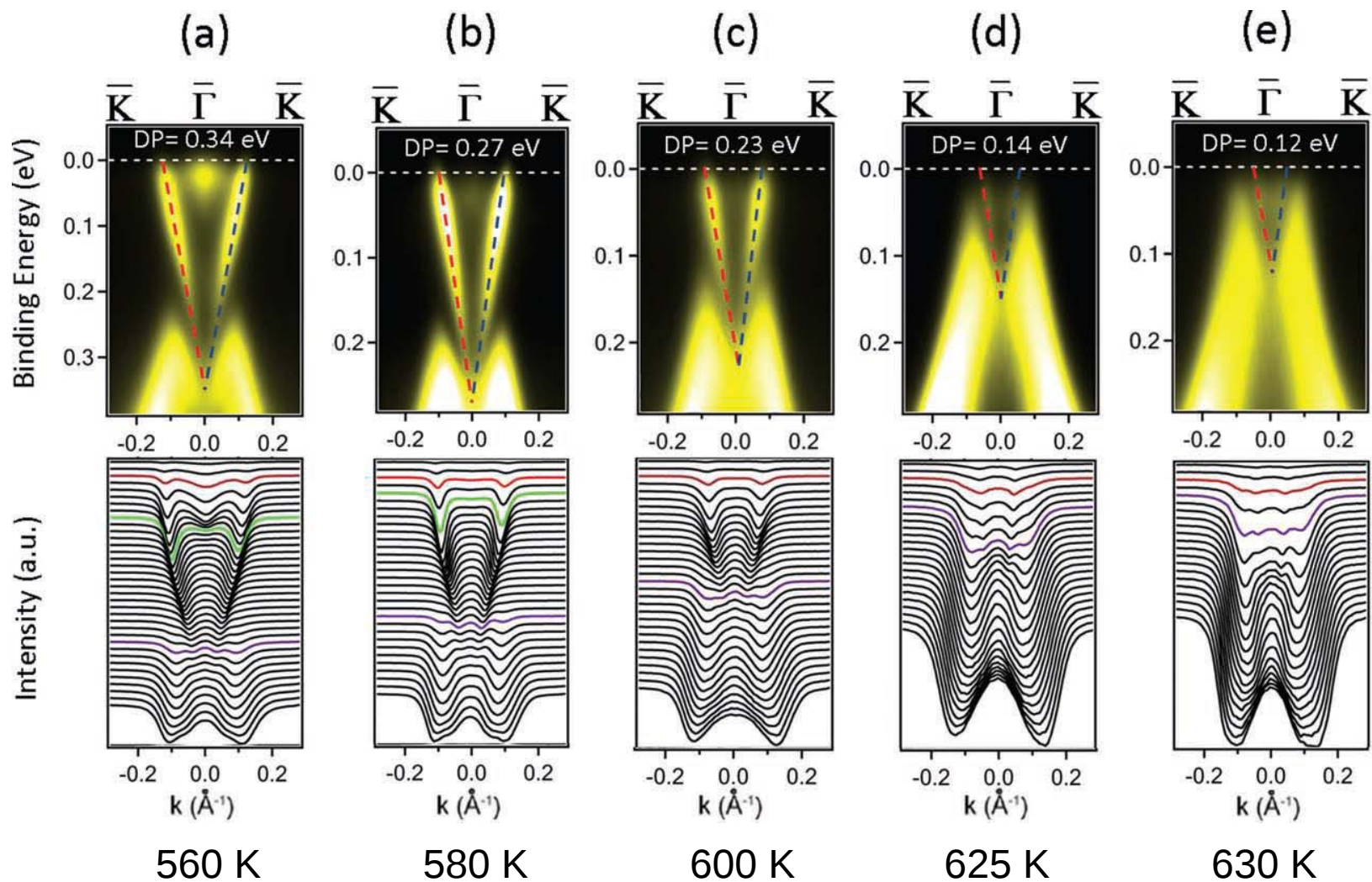


MBE growth topological insulators (Bi_2Te_3)

$\text{Bi}_2\text{Te}_3/\text{Si}$

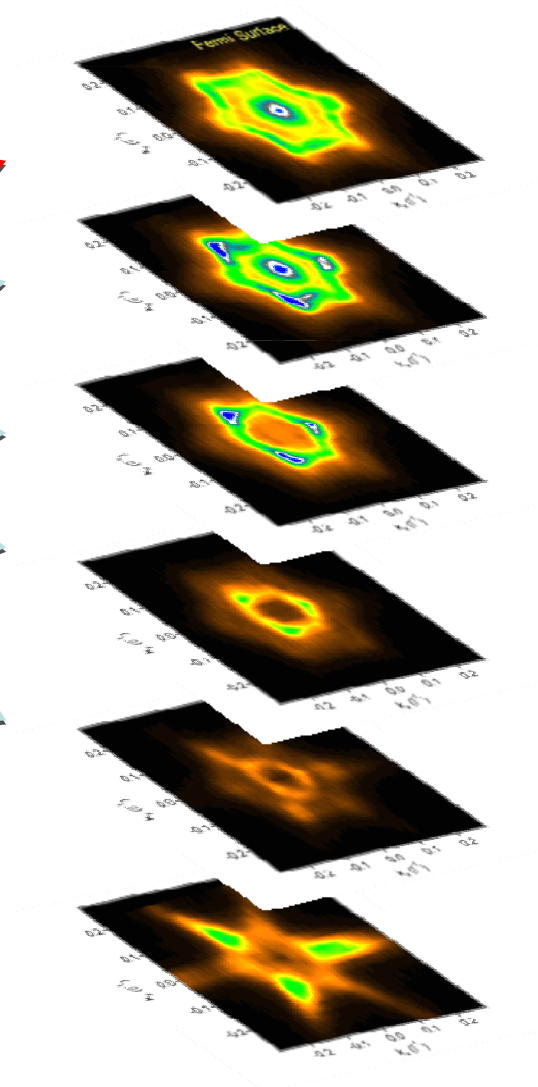
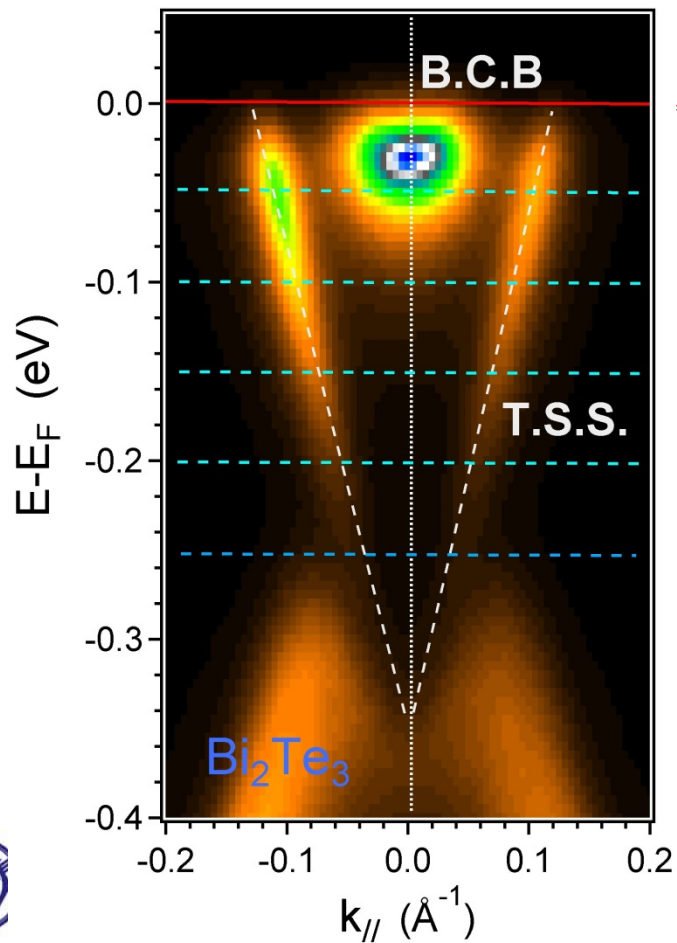


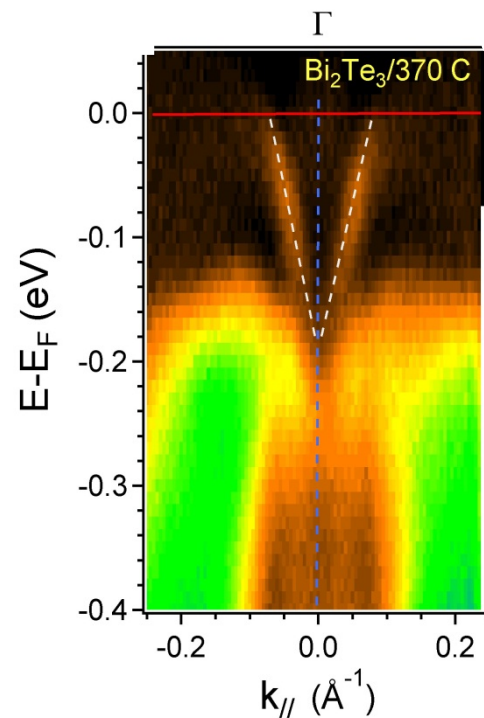
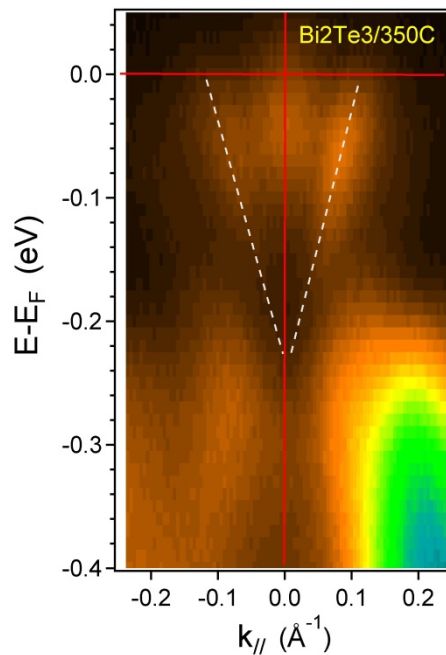
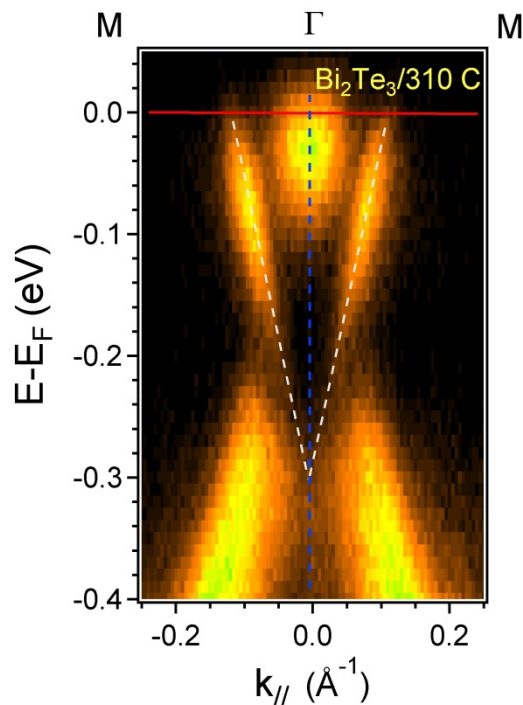
國家同步輻射研究中心
National Synchrotron Radiation Research Center



Bi₂Te₃ /Sapphire

Bi₂Te₃ (30QL)/sapphire





Controlling substrate temperature and Bi/Te flux ratio can vary the doping condition arbitrary



Topics for TIs

- New ternary TIs : $\text{Bi}_2\text{Te}_2\text{Se}$, TlBiSe_2 , GeBi_2Se_4 , SmB_6
- Impurity doping : Cu, Mn, Cr....
- Heterostructure TIs for devices : spintronic devices, thermoelectric devices



Collaborators

Graphene

- *Dr. Ku-Ding Tsuei, Chia-Jen Hsu, Ke-Fang Hsu, C.-H Chen, M.S. Chiang*
- *National Synchrotron Radiation Research Center*
- *Prof. Barbaros özyilmaz, Dr. Lanfei Xie*
– *Nano Core and Department of Physics, NUS, Singapore*
- *Prof. A.H. Castro Neto*
– *Graphene Research Centre and Department of Physics, NUS, Singapore*

TIs

Prof. Chi-Wei Luo and Prof. J.-Y. Lin
- *Department of Electrophysics and Institute of Physics, NCTU*

Prof. J.C.A. Huang and Dr. Y.F. Chiang
- *Department of Physics, NCKU*

